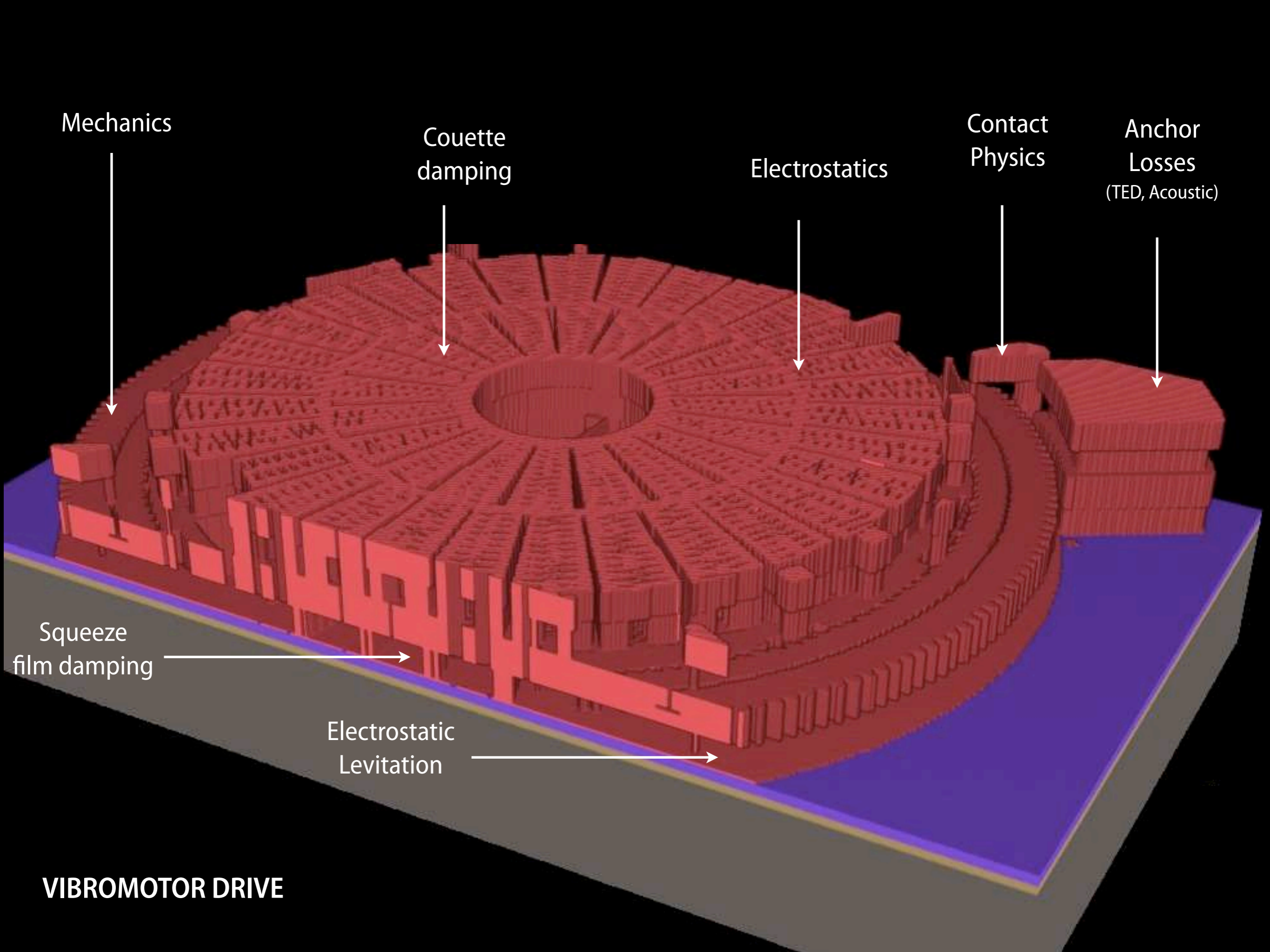




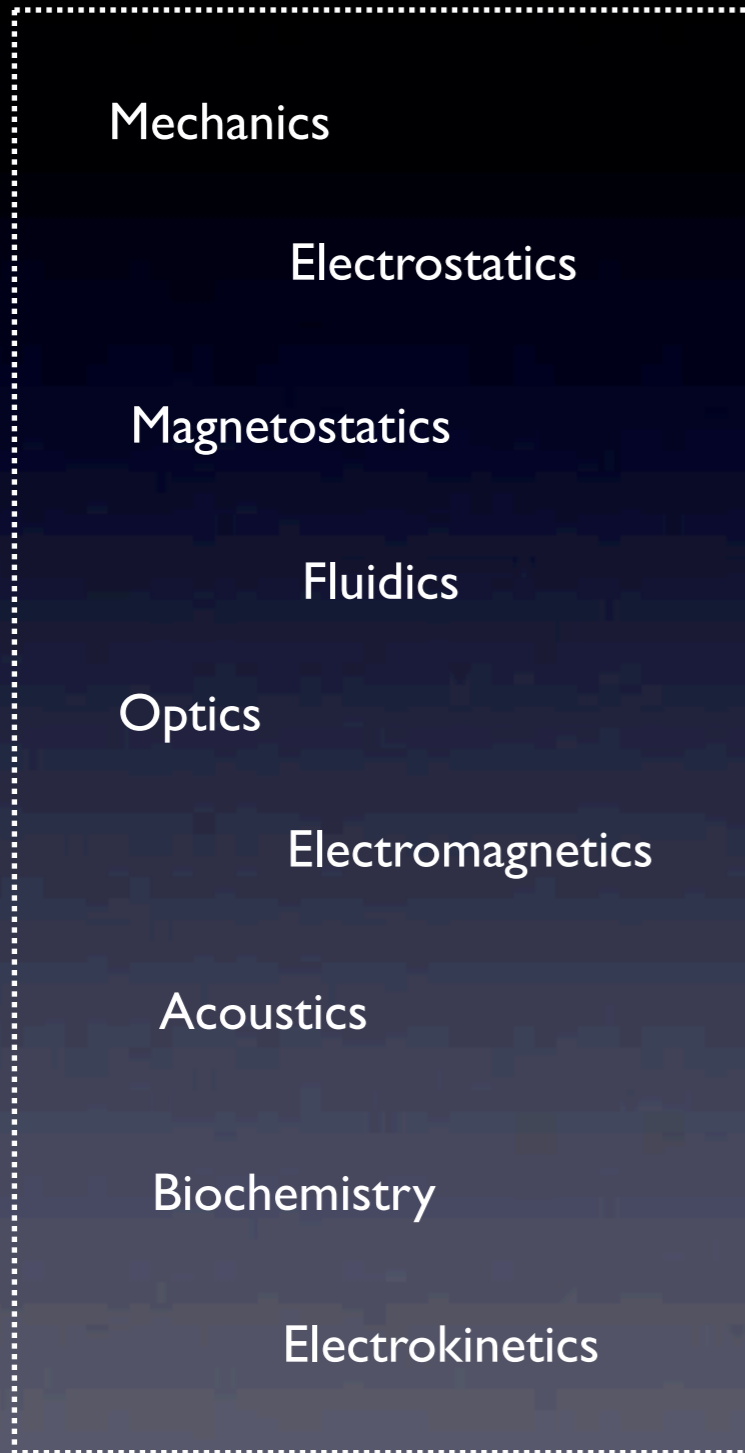
# Design Flow in IntelliSuite v8.6

# Design flow

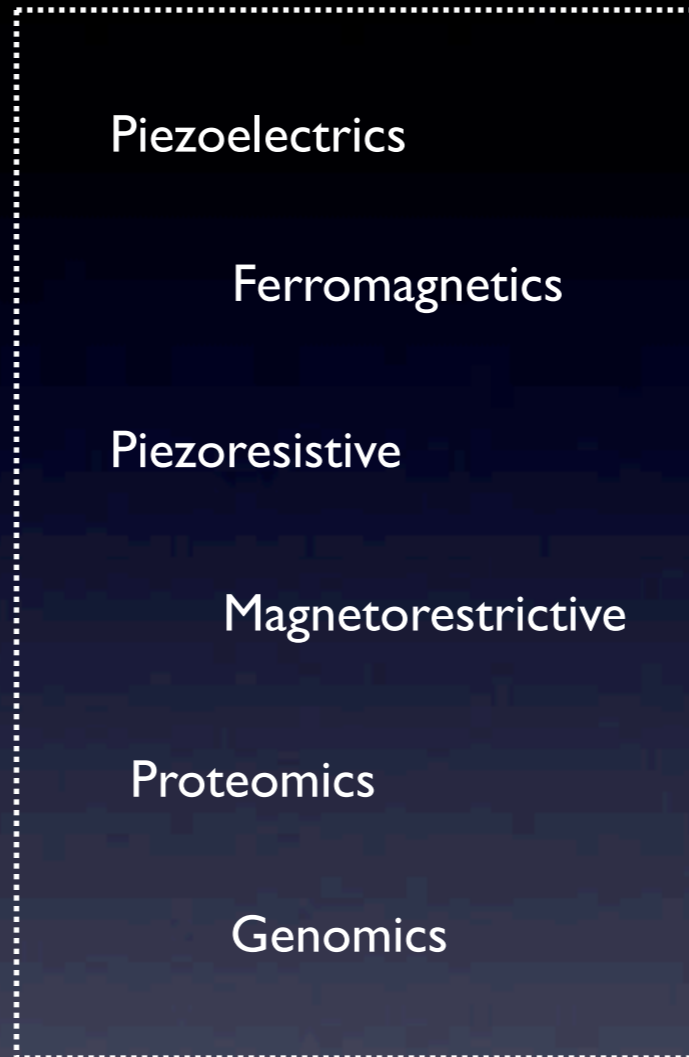
**MEMS design is highly interdisciplinary**



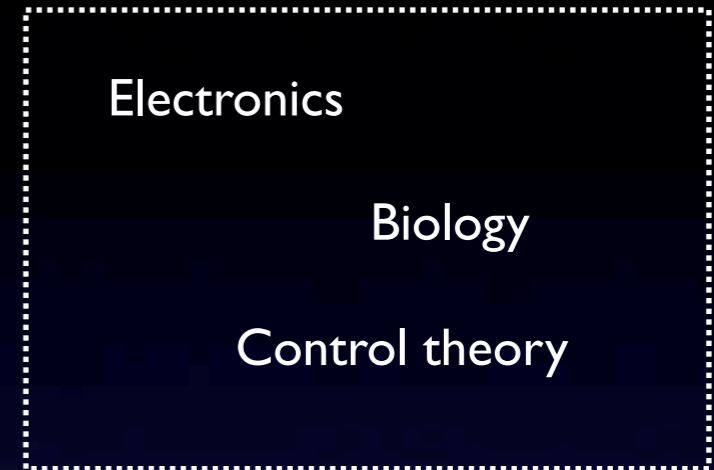
# Colliding domains



**PHYSICS**



**MATERIALS**

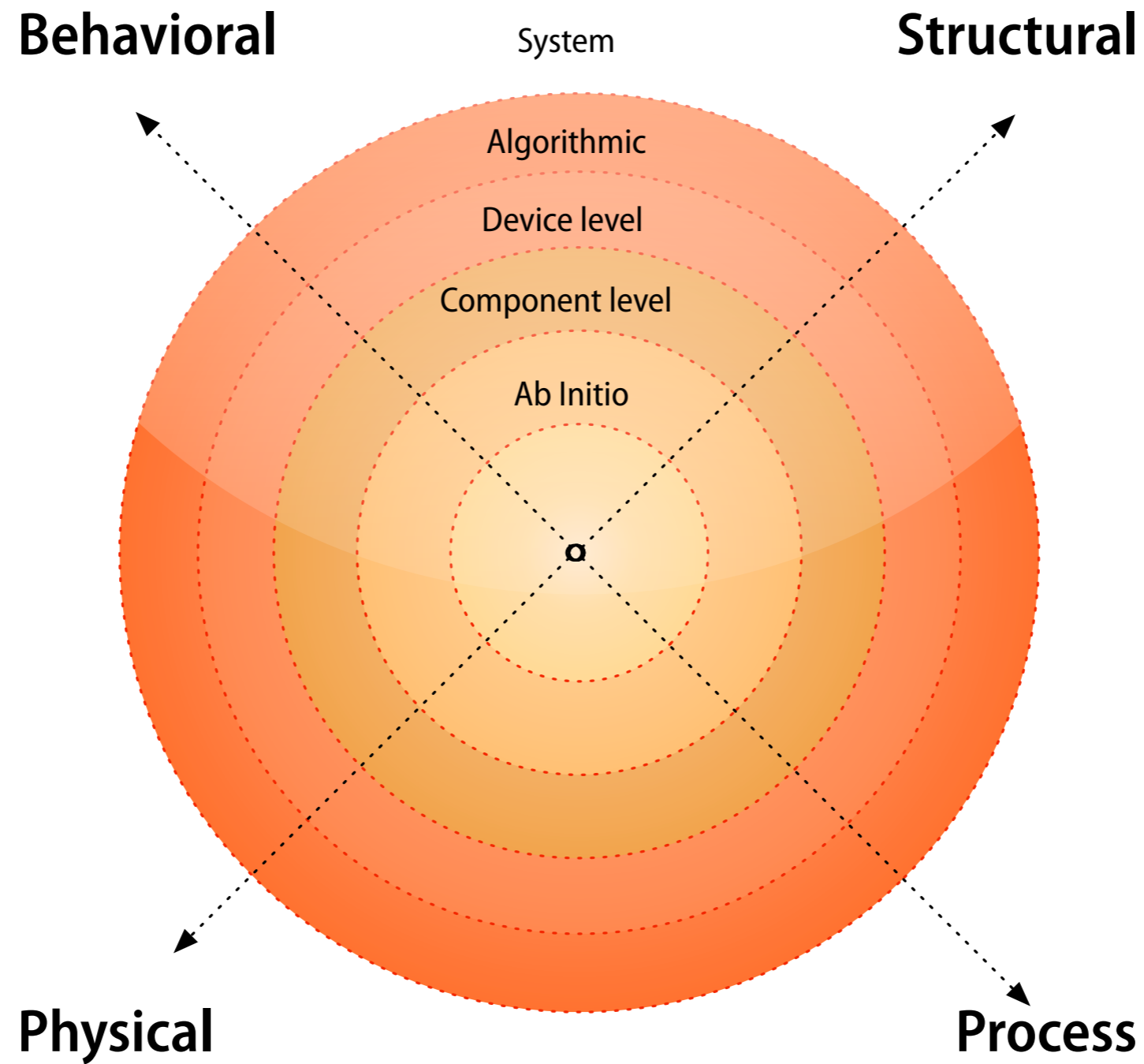


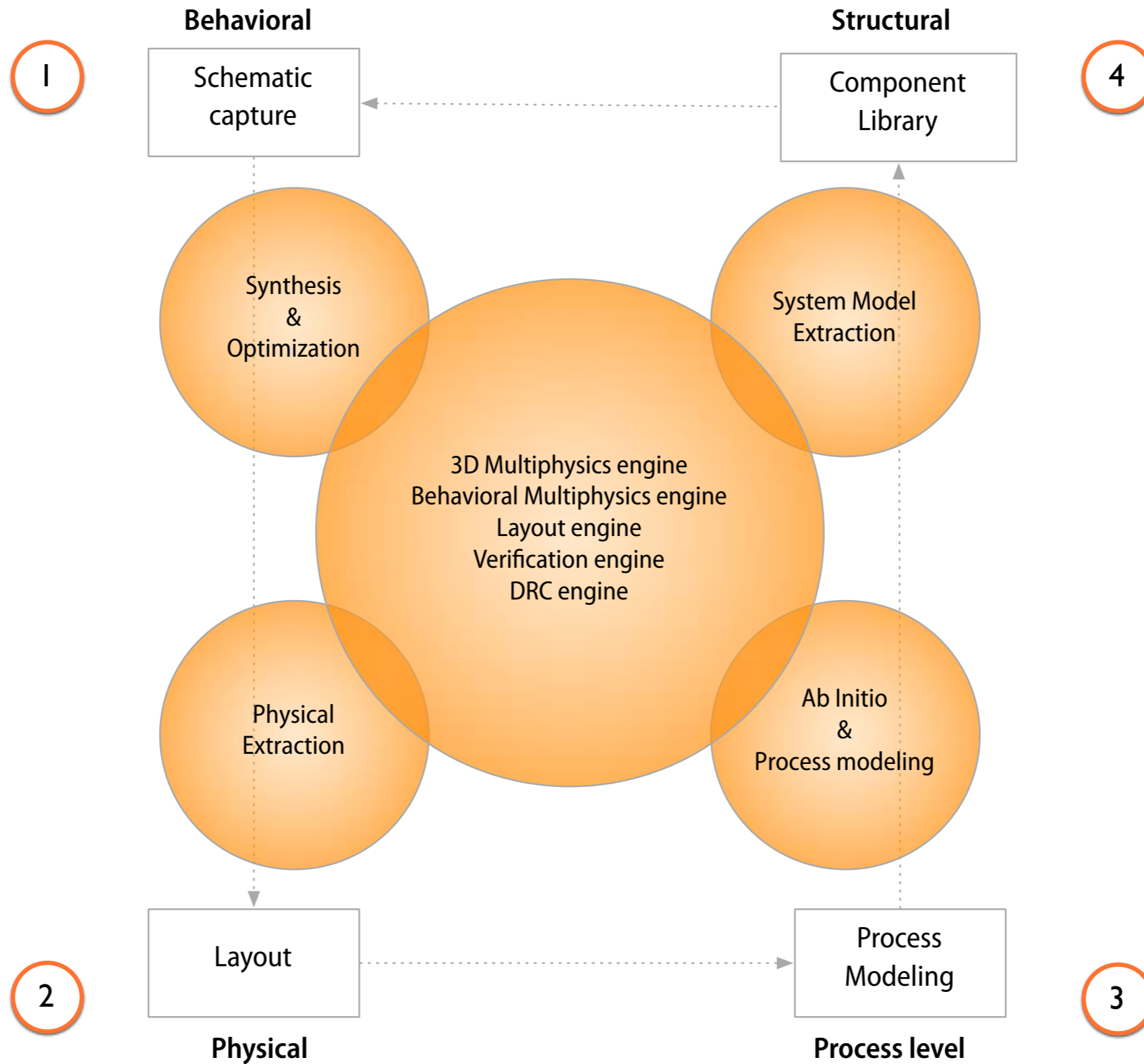
**SYSTEMS**



**MANUFACTURING**

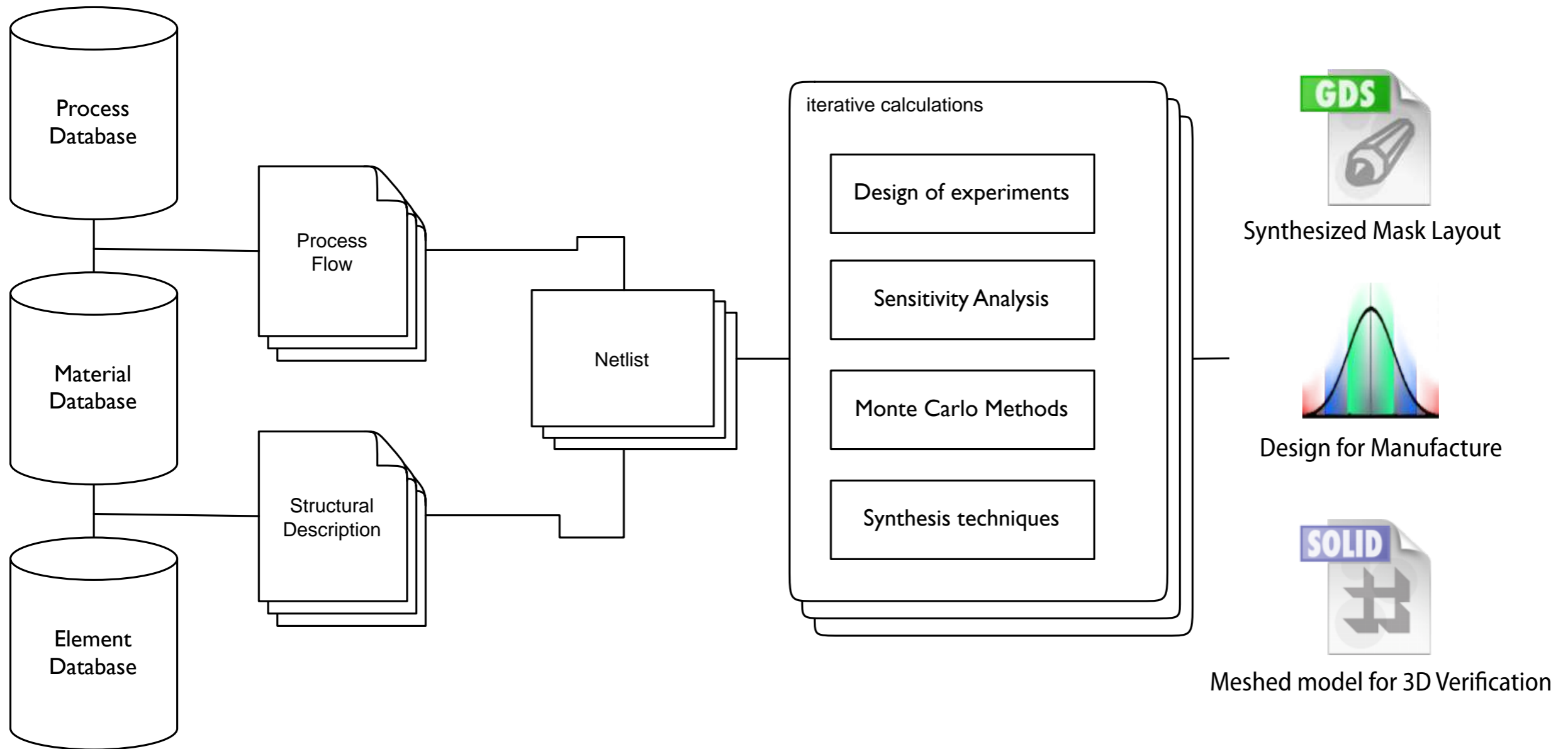
# Hierarchy of MEMS modeling





**Seamless integration of design flow...**

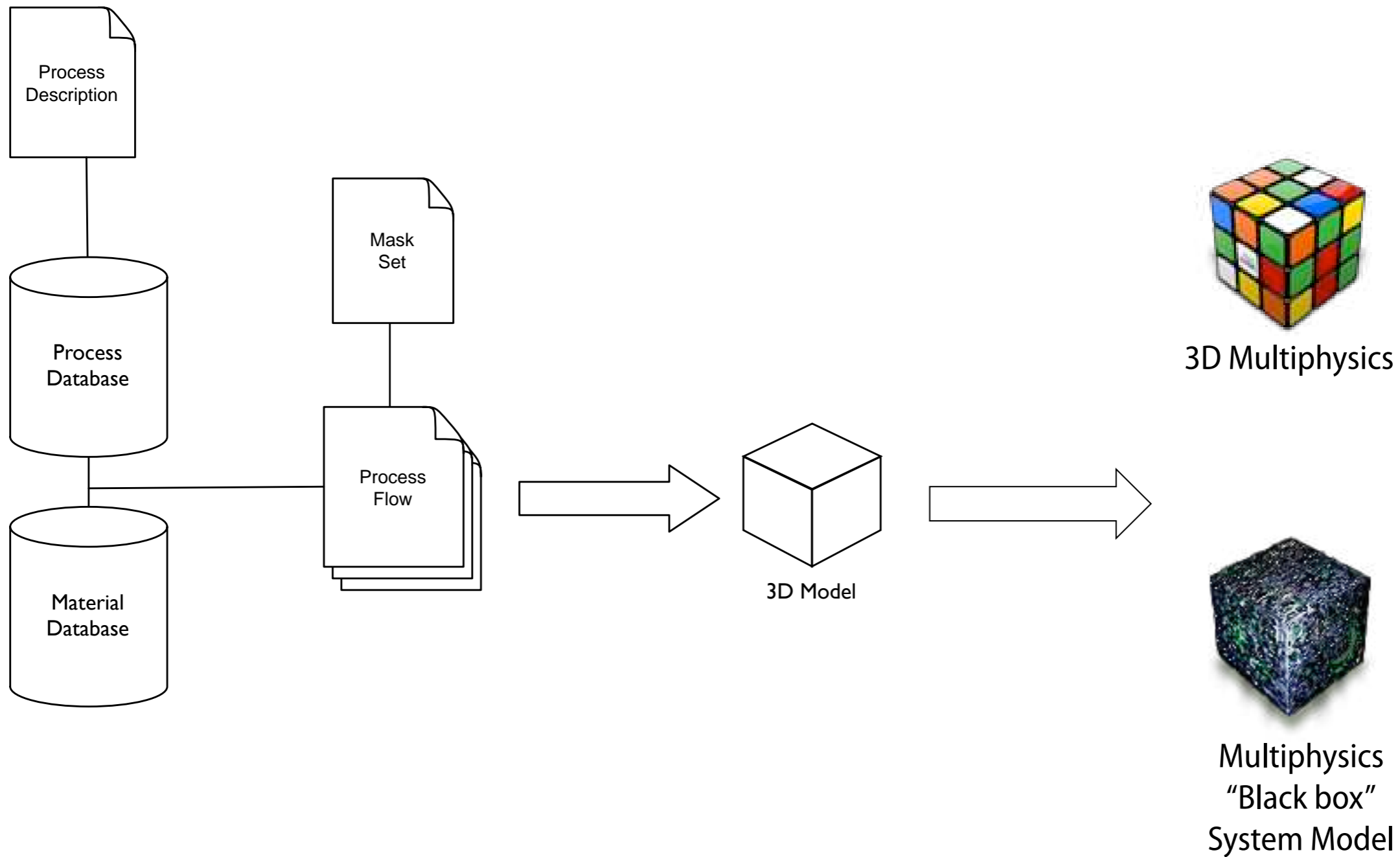
# Top down flow: schematic based...



Fast but less accurate...

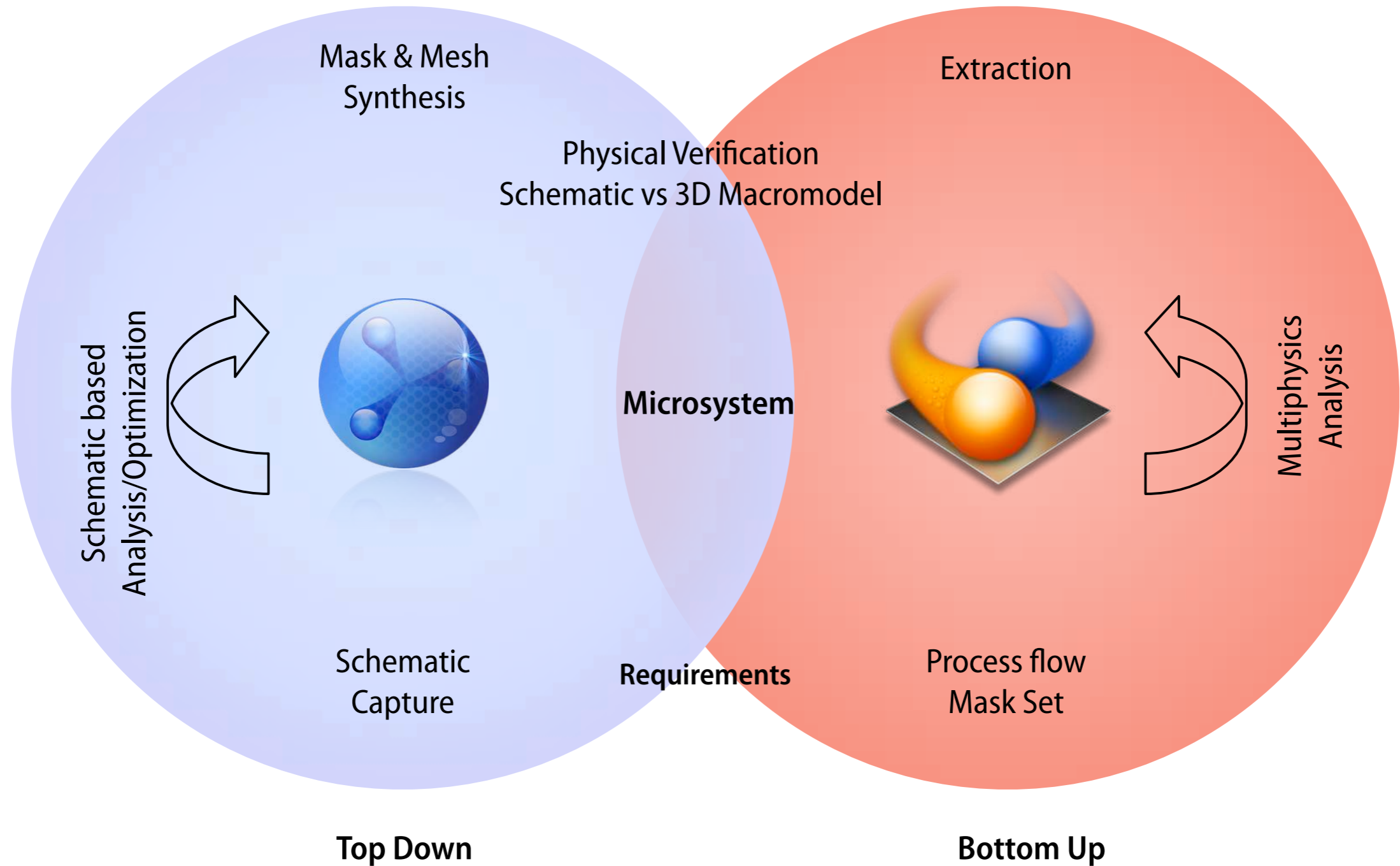


# Bottom up design flow: 3D based



Accurate but slower...

# IntelliSuite: Best of both worlds

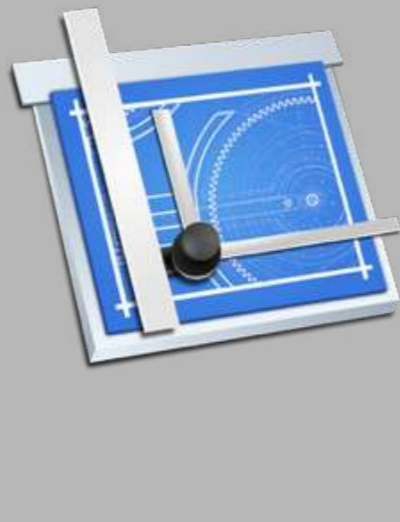


# IntelliSuite Tool Chain



## Synple

Schematic capture  
Component based  
Design exploration  
Mask and 3D synthesis



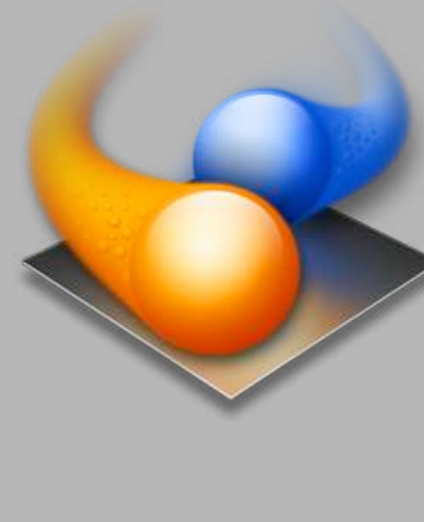
## Blueprint

Physical design  
Layout/DRC  
Tape Out



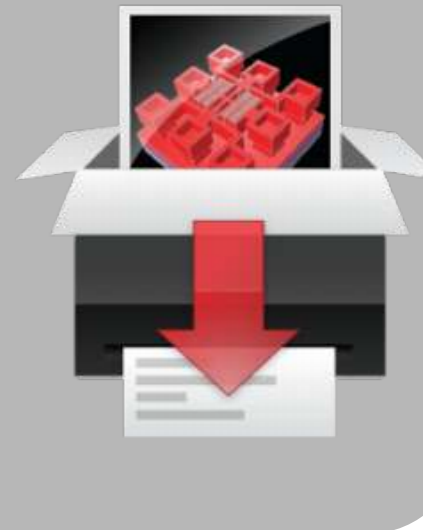
## Clean Room

Process flow design  
Process debug  
Process visualization



## Fast Field

Multiphysics solvers  
Coupled field analysis  
System model extraction



## EDA Linker

Link to EDA tools  
Cadence, Mentor,  
Synopsys, Ansoft,  
Mathworks etc...

# Behavioral modeling



# Synple capabilities (Behavioral)



## Schematic capture

Design Exploration  
Optimization  
Design for manufacture

## Multiphysics computation

Mechanics  
Electrostatics  
Damping/Dissipation  
Piezo  
Mixed Signal  
Control Systems  
1000X faster than FEA

## Synthesis

Schematic to mask  
Schematic to 3D  
Schematic to mesh

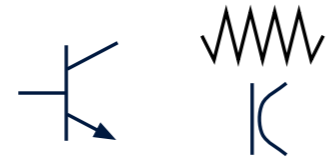
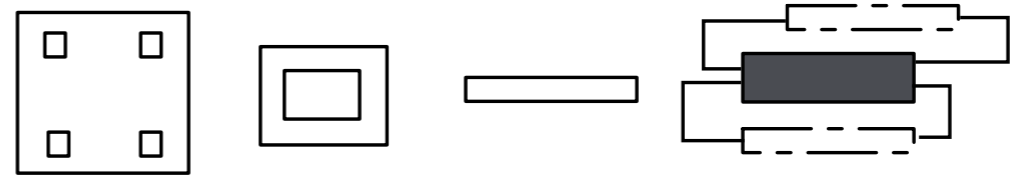
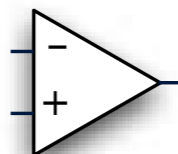
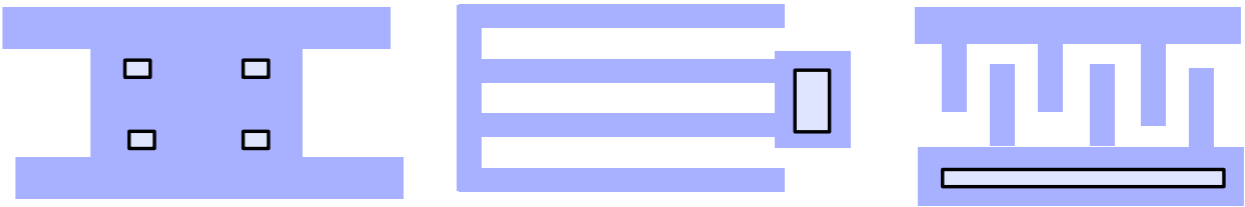
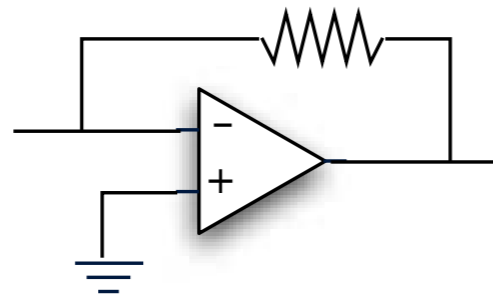
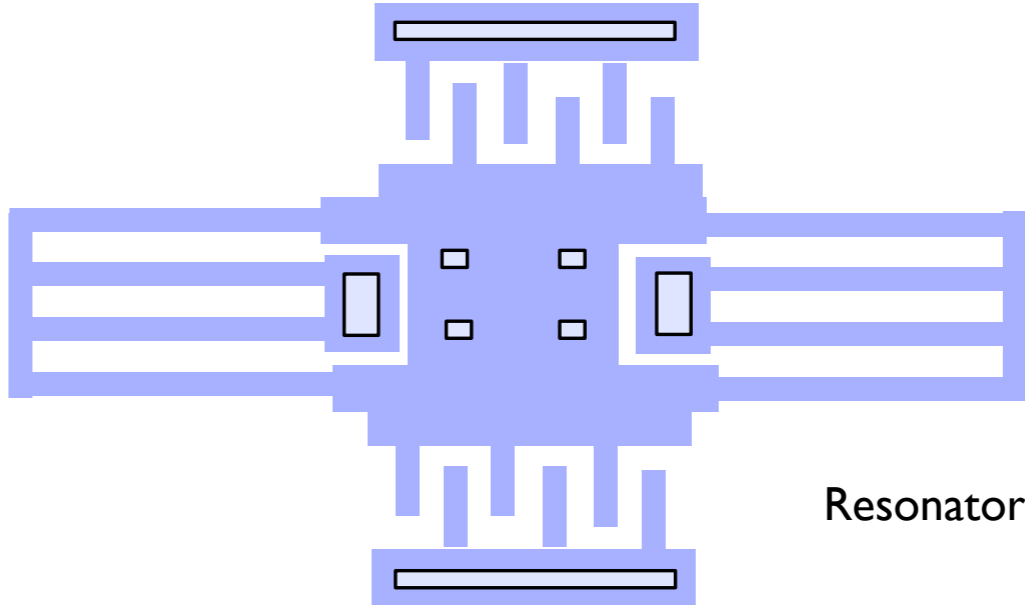
## Yield Engineering

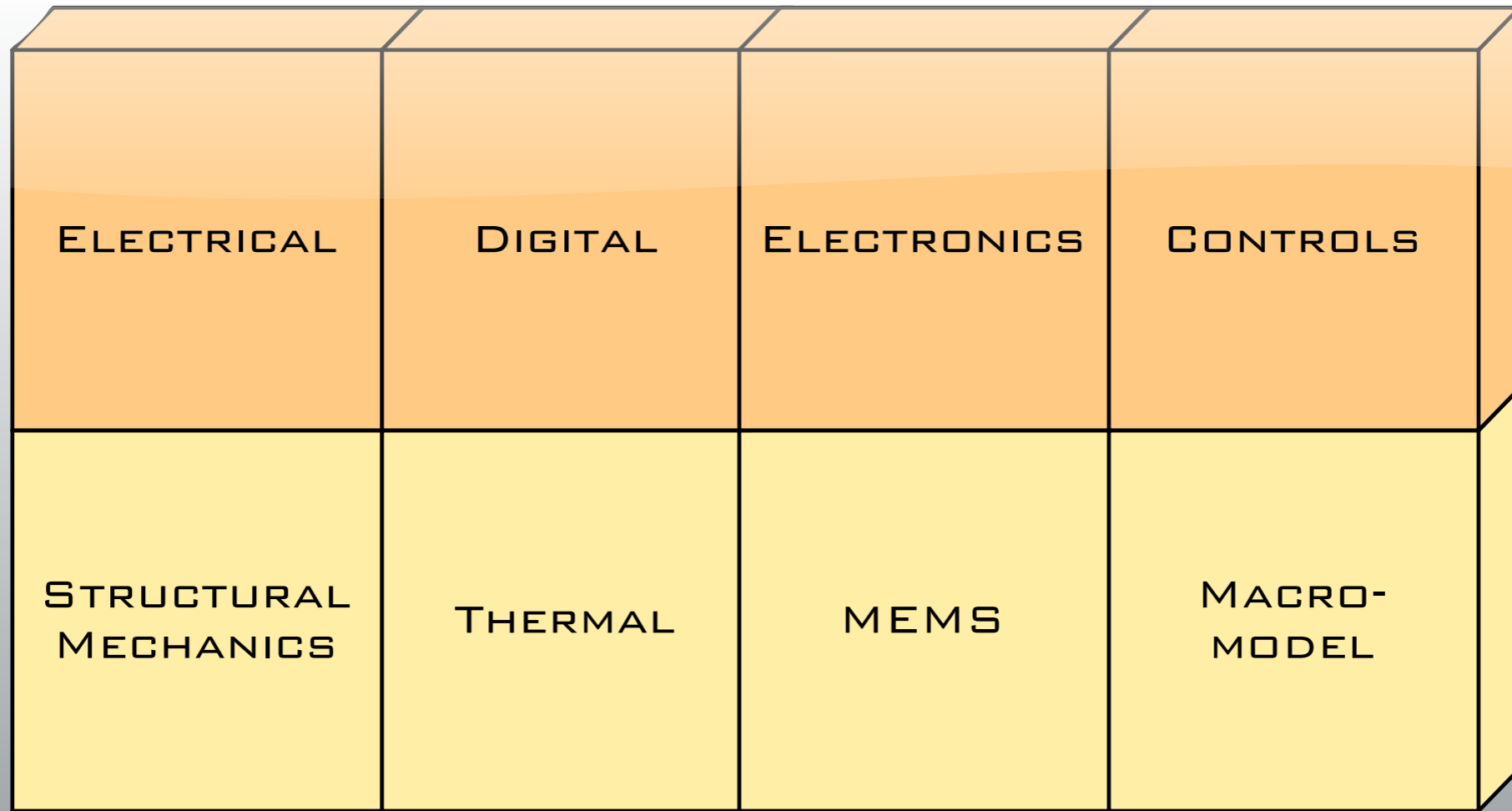
DfM  
Process Corner studies  
Yield prediction

## Link to other tools

Automatic meshing  
Derive process flow

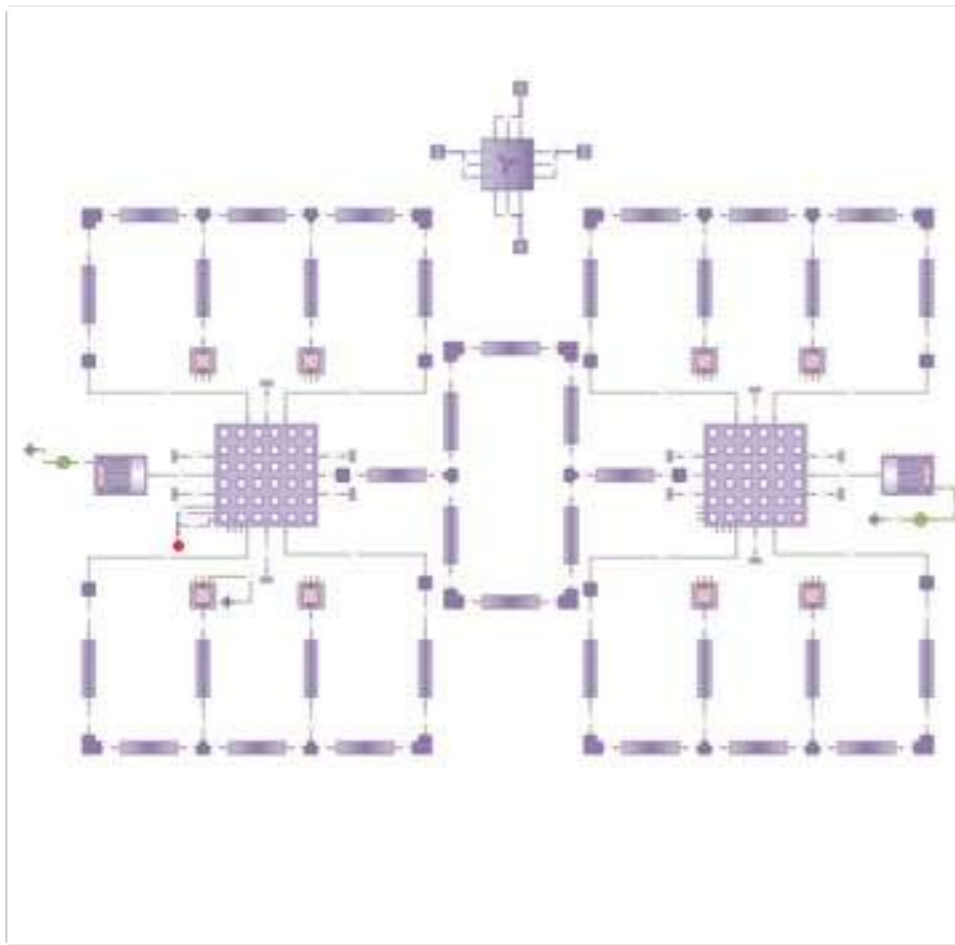
# Hierarchical multi-domain design

<p>Atomic elements</p>	 <p>Transistor    RLC</p>	
<p>Compound elements</p>	 <p>Op-Amp</p>	 <p>Shuttle mass    Folded flexure spring    Comb drive</p>
<p>Device elements</p>	 <p>Interface circuit</p>	 <p>Resonator</p>

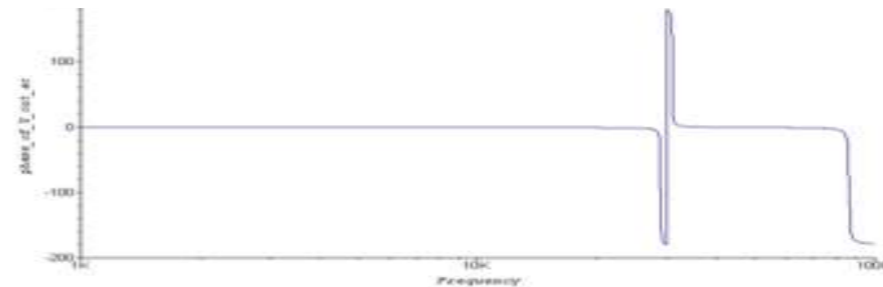
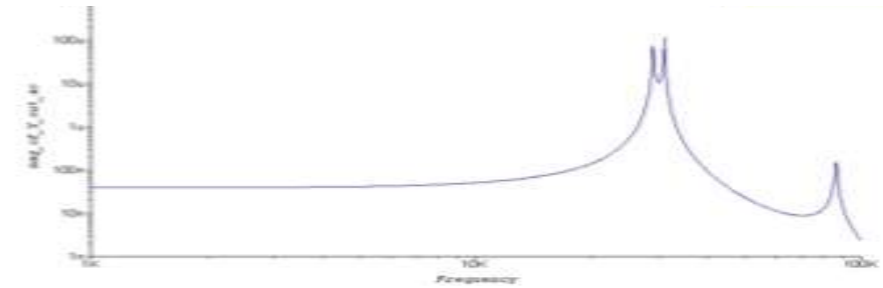


**WIDE RANGE OF BUILDING BLOCKS**

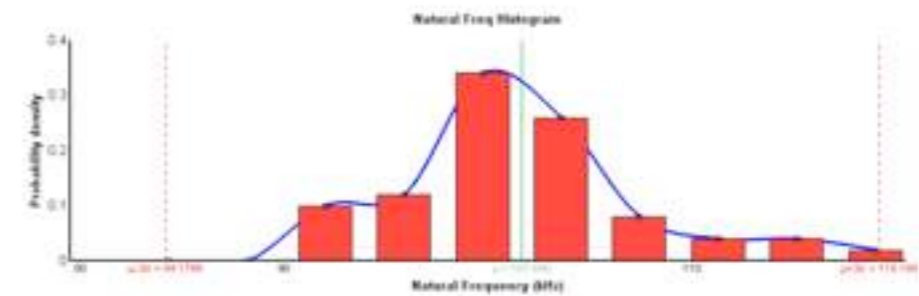
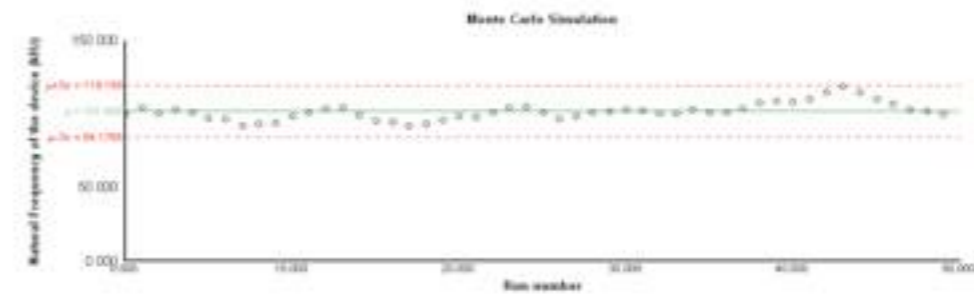
# Schematic based design exploration



Band pass filter



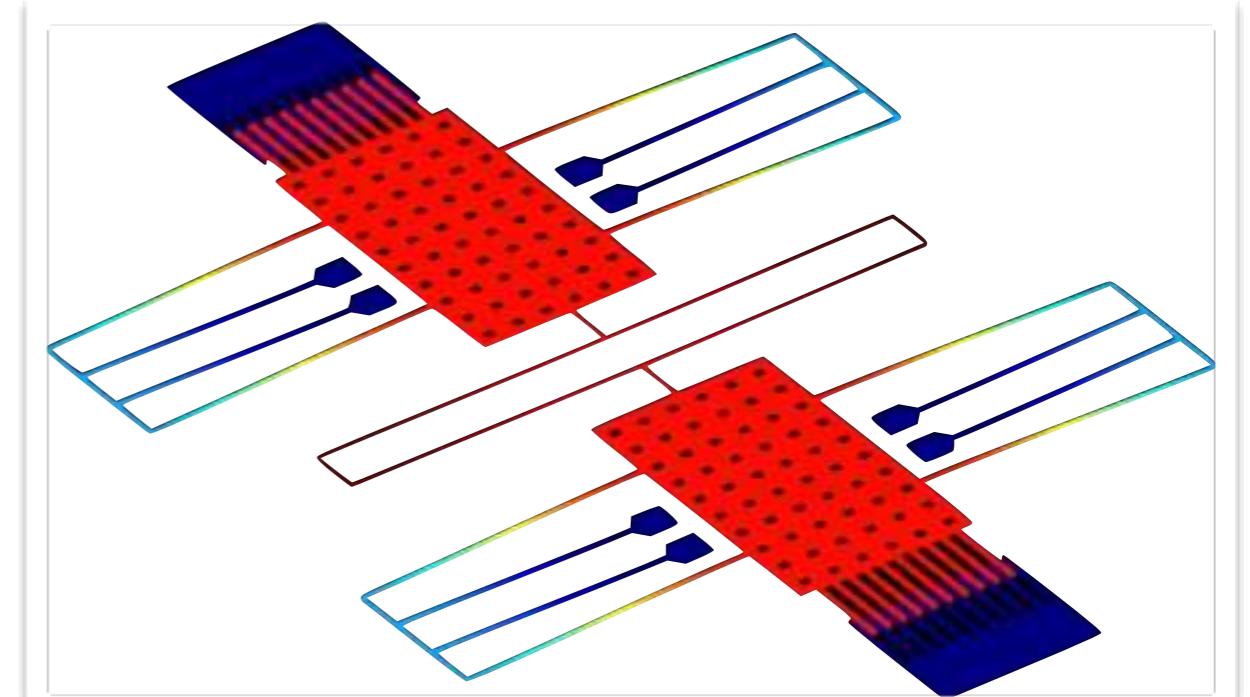
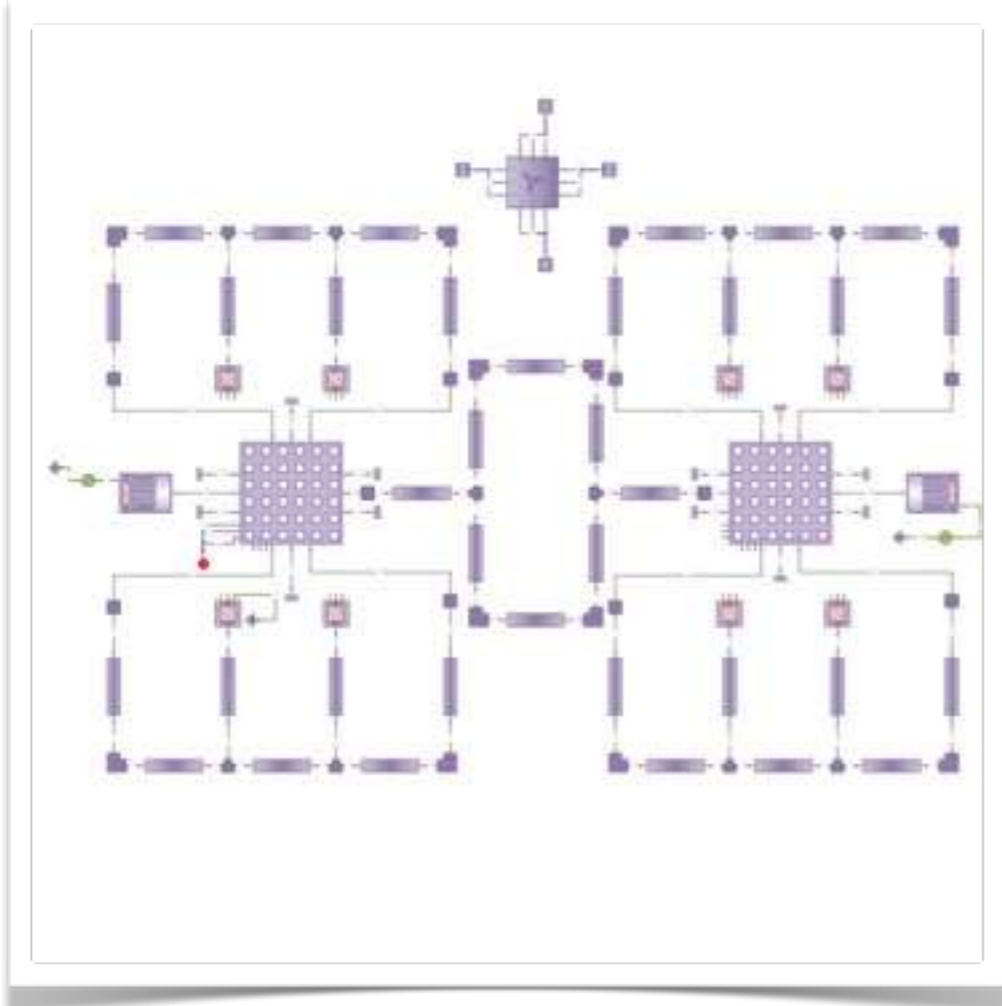
Compute time: 4 hr (Full 3D) vs 30s (compact)



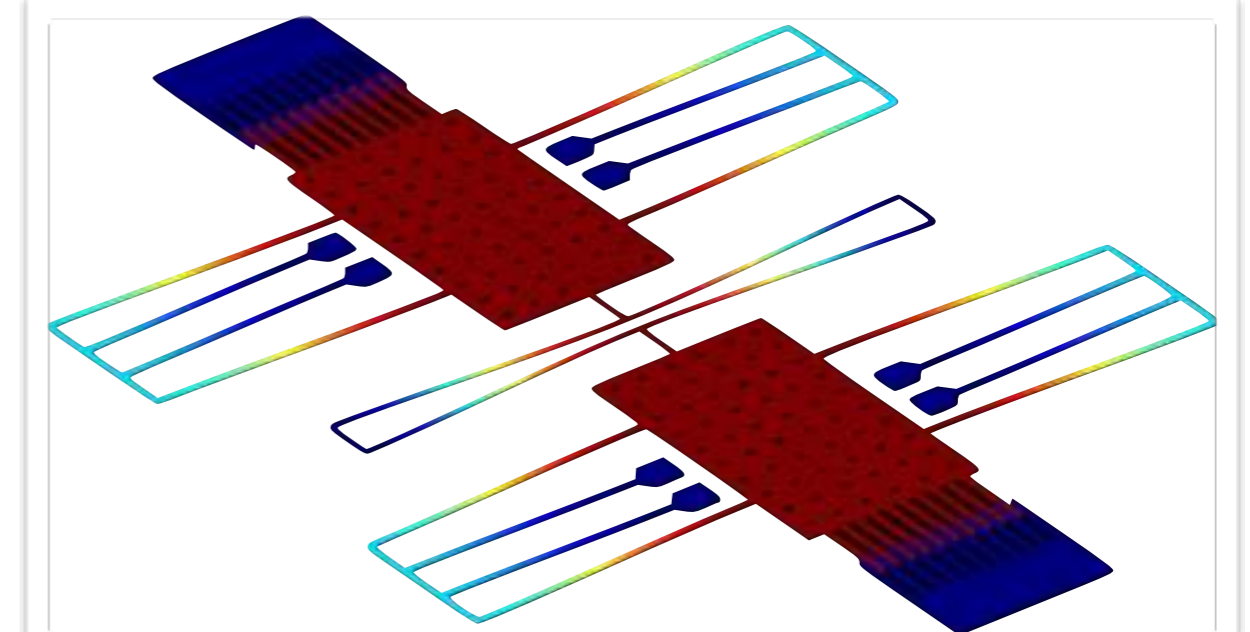
Monte Carlo based  
process variation analysis



# Visualize schematic results in 3D

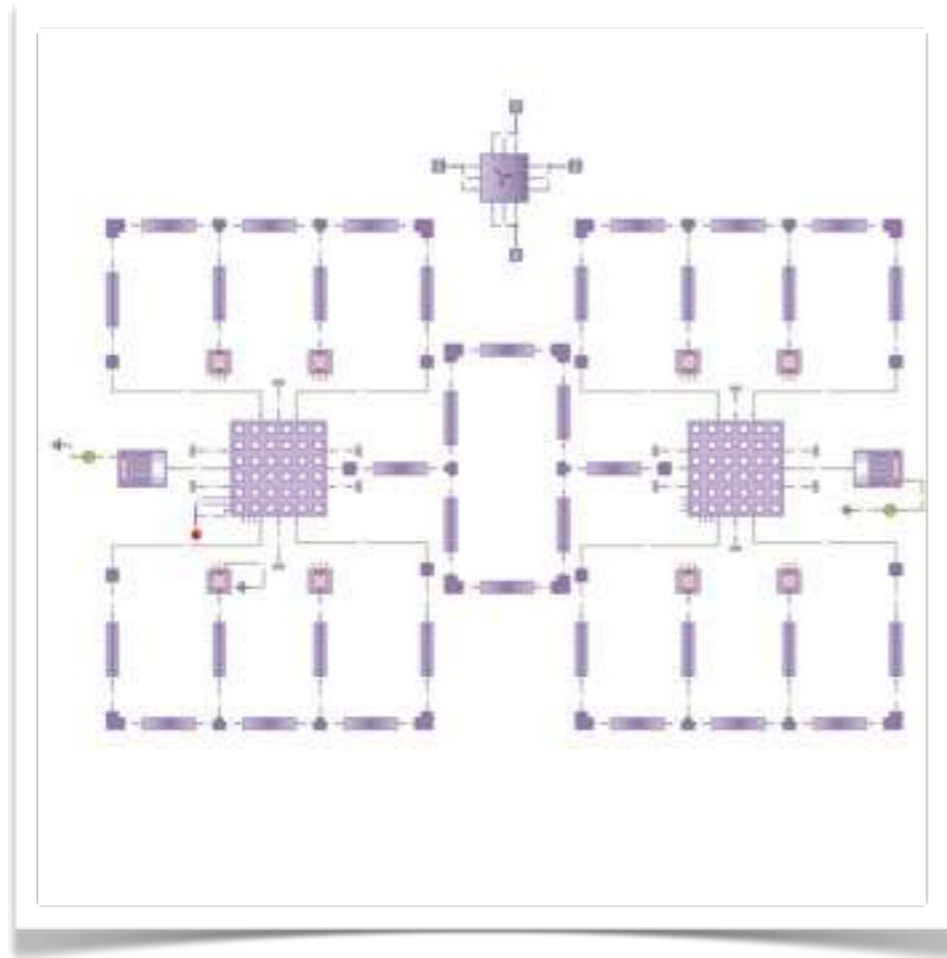


**Mode 1: In Phase**

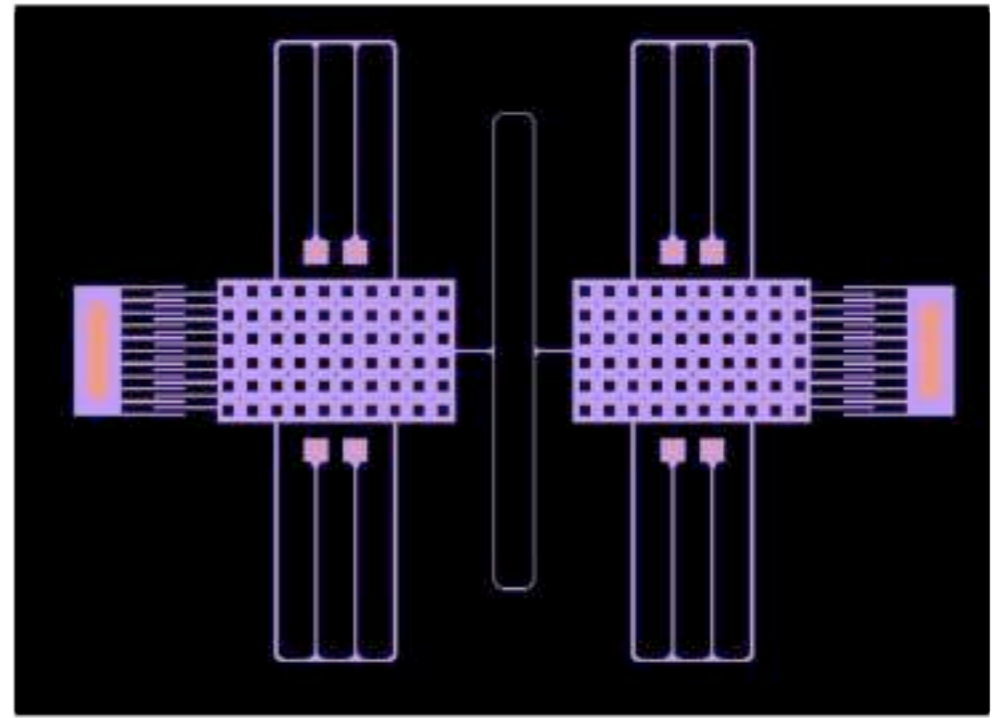


**Mode 2: Anti Phase**

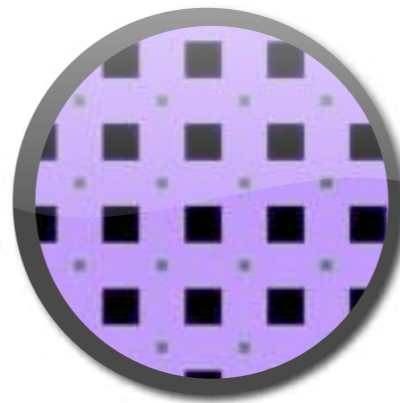
# Schematic to mask



Automated layout synthesis



Stress relief curves



Dimples



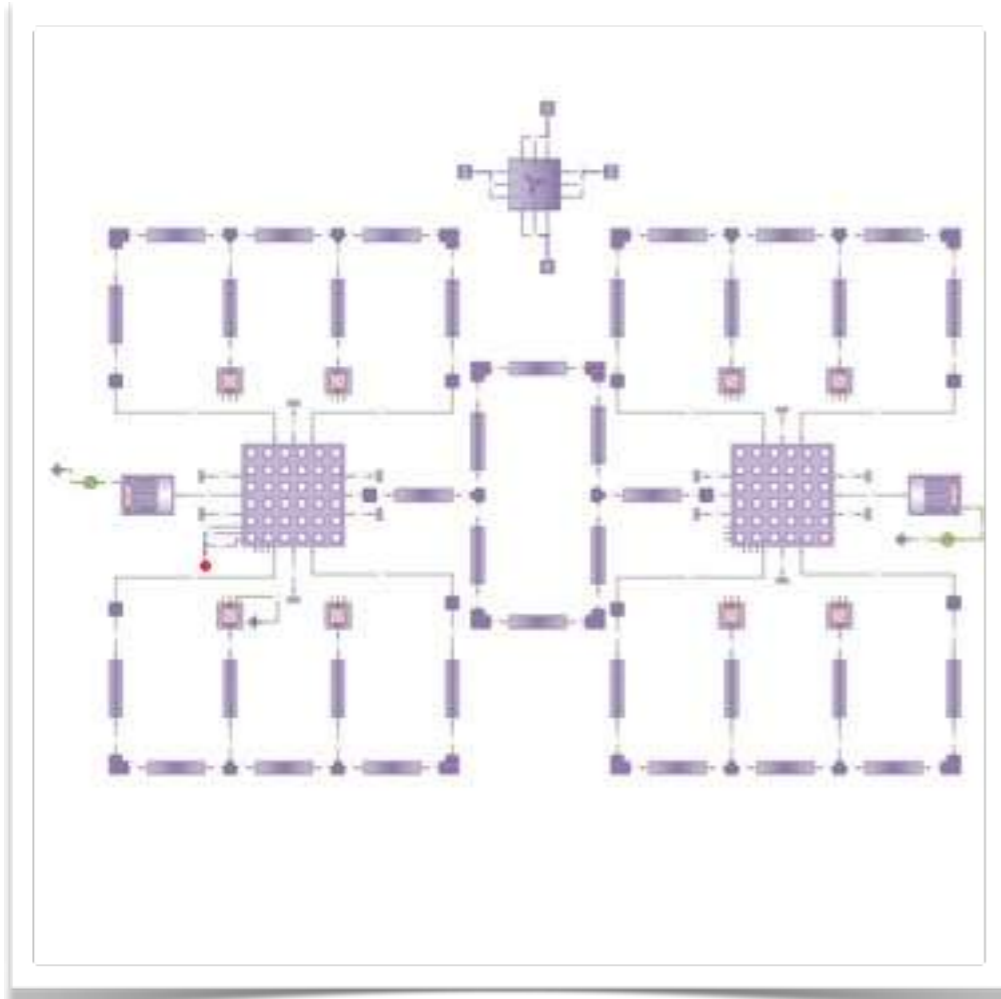
Comb bumpers



Etch compensation features

Attention to detail

# Schematic to process flow

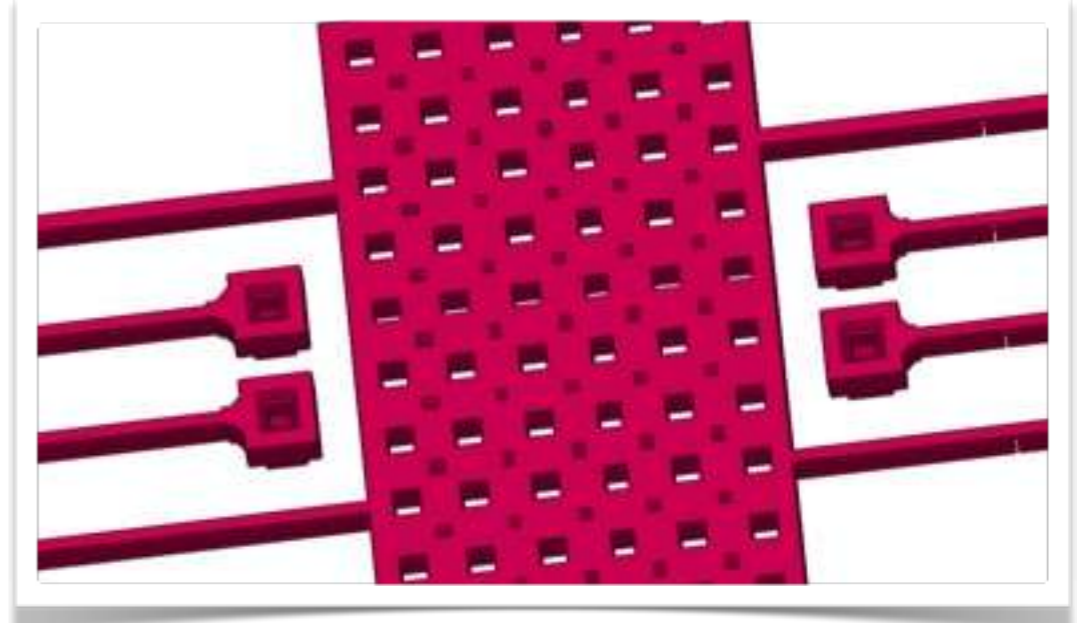
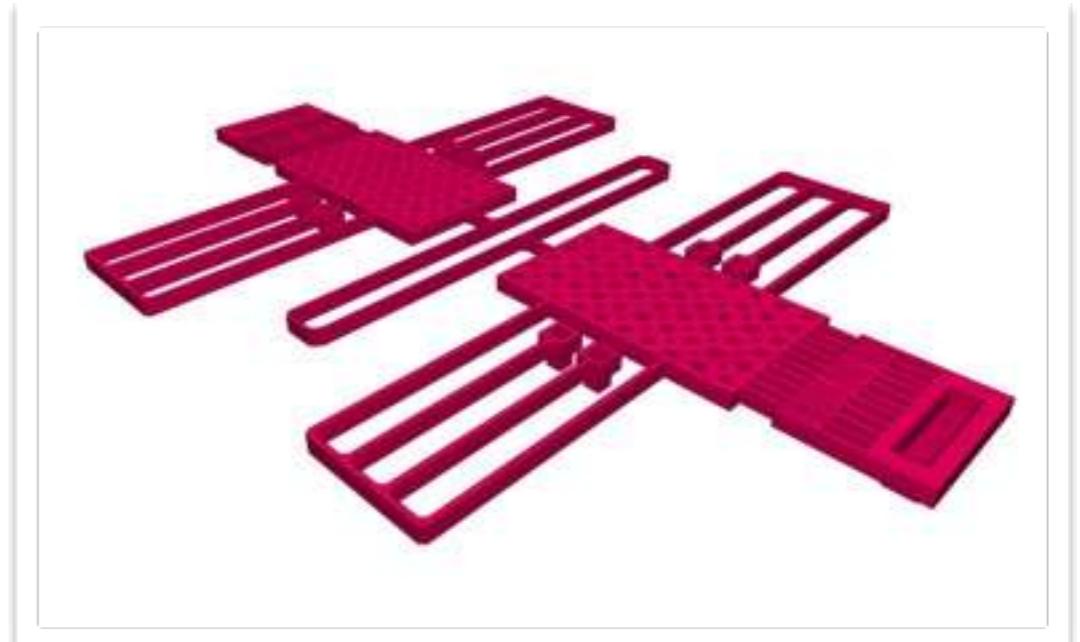
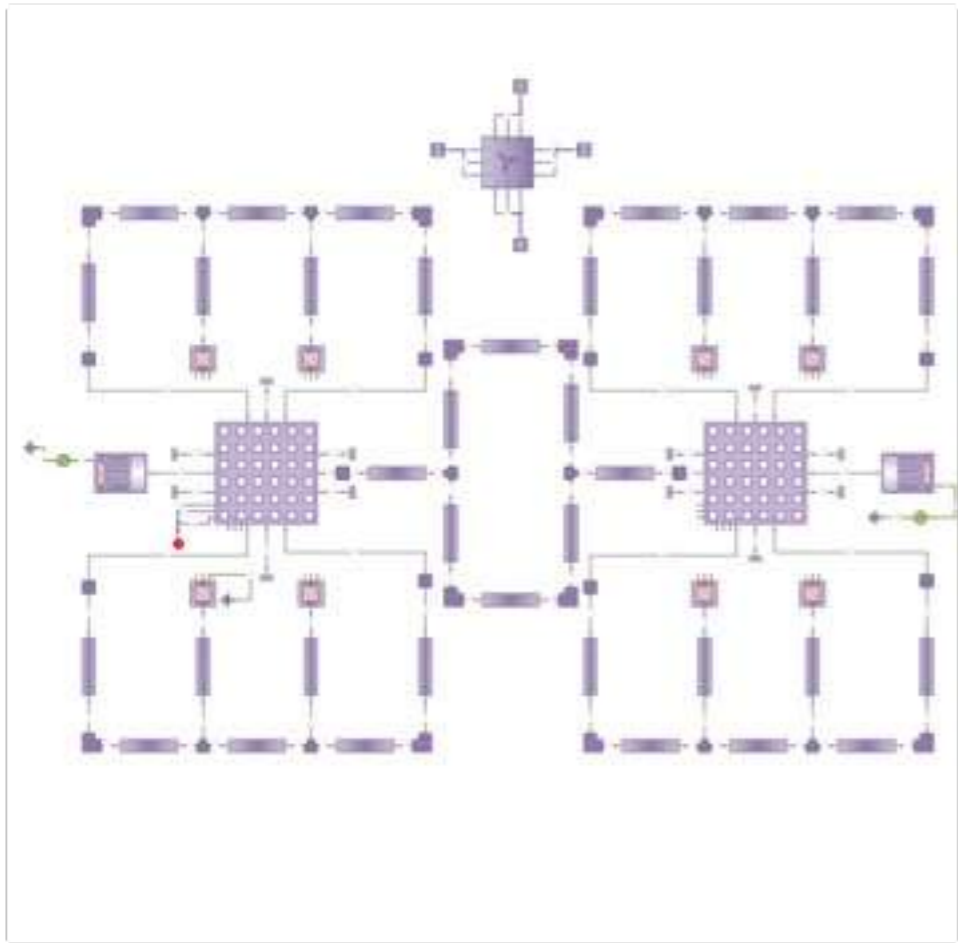


The screenshot shows a software interface with a table of process steps. The table has columns for #, Type, Material, Process, Process ID, and Process Option. The data is as follows:

#	Type	Material	Process	Process ID	Process Option
1	Definition	S	Coschvaki	330	
2	Deposition	PSG	LPOD	Generic	Conformal Deposition
3	Definition	IM	Contact	Scan	
4	Etch	PSG	Generic	Generic	Partial Etching
5	Definition	IM	Contact	Scan	
6	Etch	PSG	Generic	Generic	Etch Through
7	Deposition	Polys	LPOD	SH4	Conformal Deposition
8	Definition	IM	Contact	Scan	
9	Etch	Polys	Dry	SP4-Plasma	Etch Through
10	Etch	PSG	Generic	Generic	Sacrifice
11	Etch	S	Wet	Sacrifice	Sacrifice

Process flow for fabricating the device is automatically derived from the schematic and technology file information

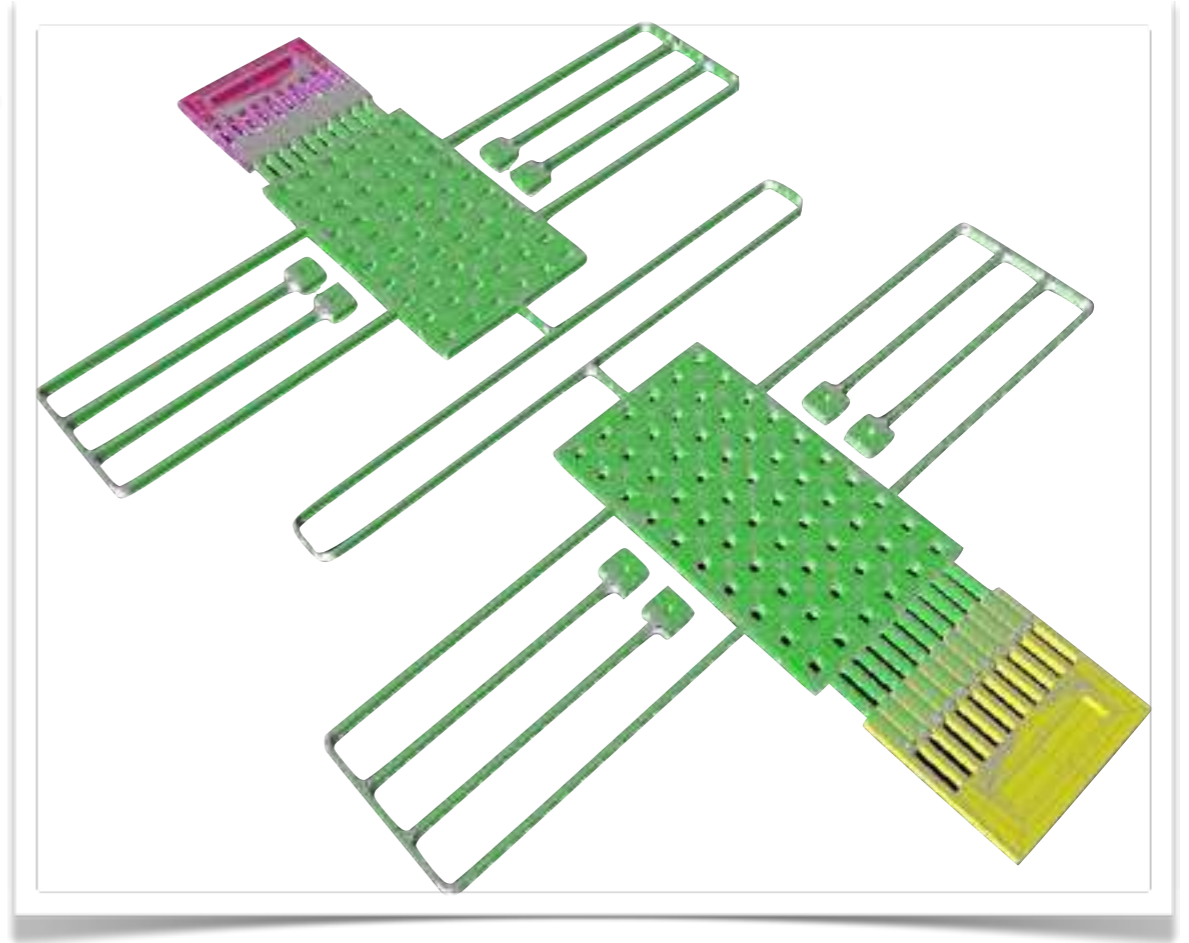
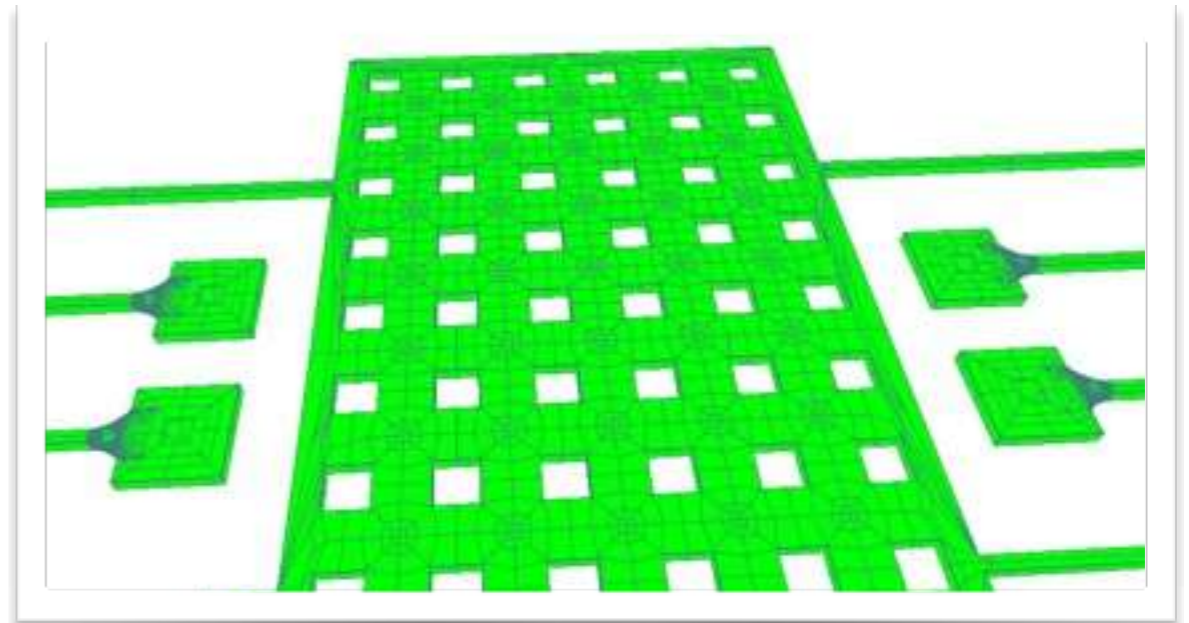
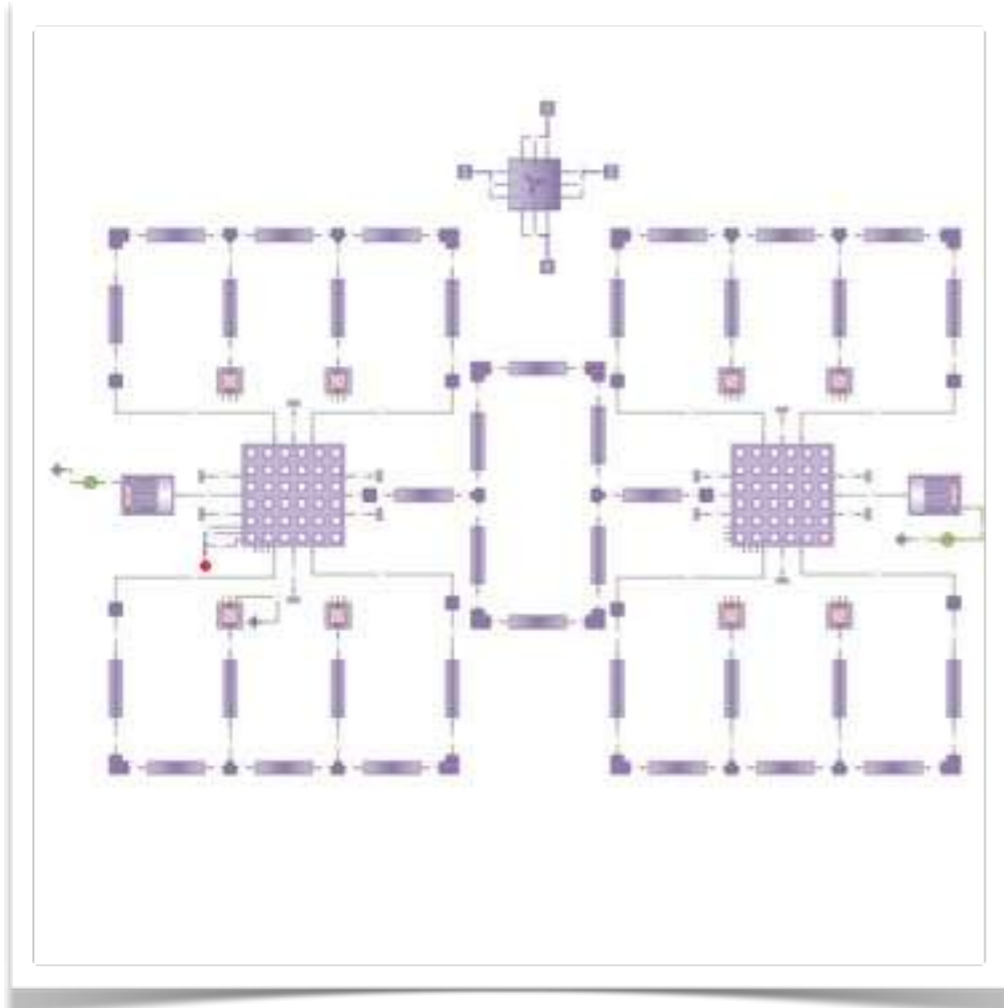
# Schematic to 3D model



**Attention to detail**

Automatic placement of dimples, anchors and other secondary features

# Schematic to mesh



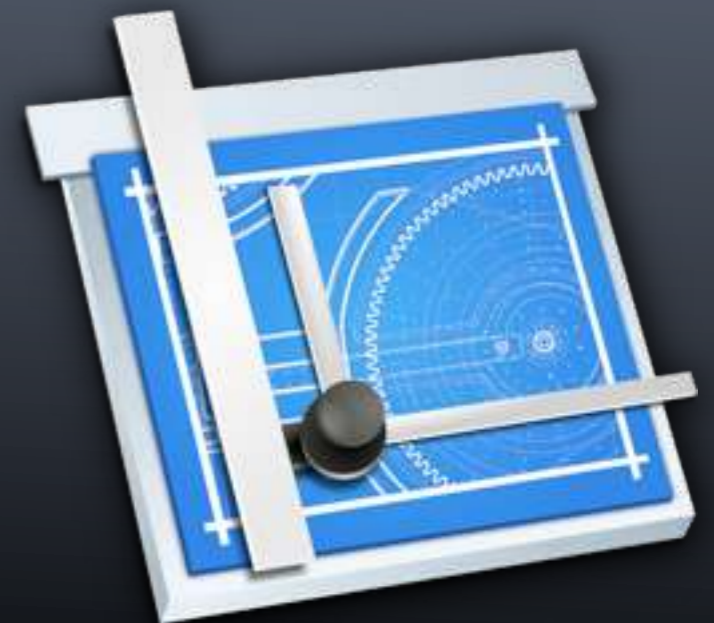
Automated Hexahedral Meshing of the Structure

# Benefits

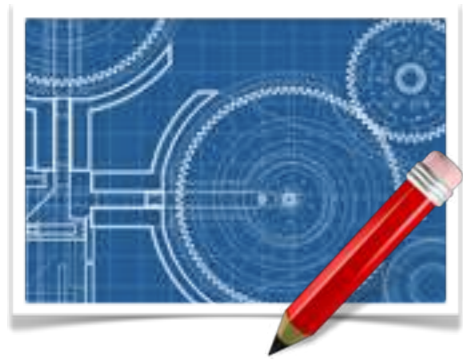


- &• **Schematic driven design**  
Entry point for parametric design and design exploration
- &• **Hierarchical modeling**  
Model your device at system or circuit level
- &• **Save time**  
100-1000X faster than FEA models.
- &• **Design exploration and optimization**  
Quickly prototype and explore multiple designs
- &• **3D System modeling**  
View your results in 3D

# Physical design & verification



# Blueprint capabilities (Physical)



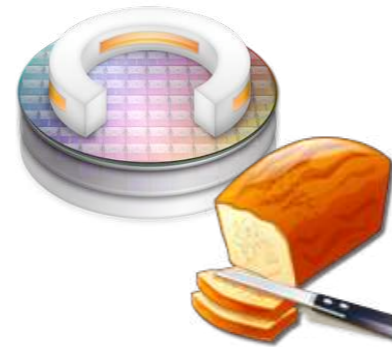
## Design capture

- Layout optimized for MEMS
- AutoCAD™ like interface
- Large design library
- Hierarchy support
- Smart Layers
- Pathfinders
- Scripting



## Design Rule Check

- Tape Out DRC Editor
- Powerful hierarchical DRC
- All angle support
- Easy Error Navigator



## Layout visualization

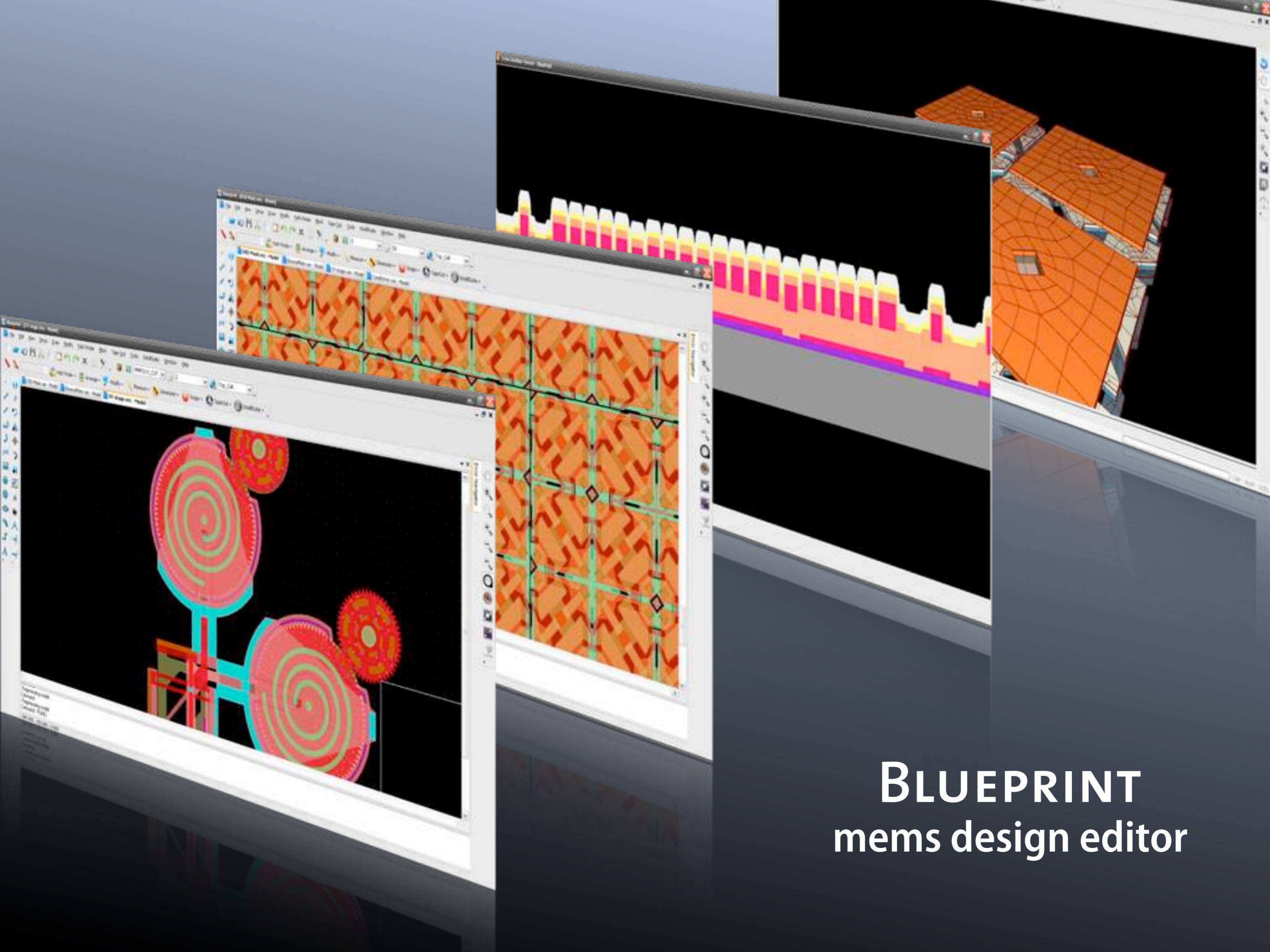
- Cross section drawing
- 3D Visualization of layout



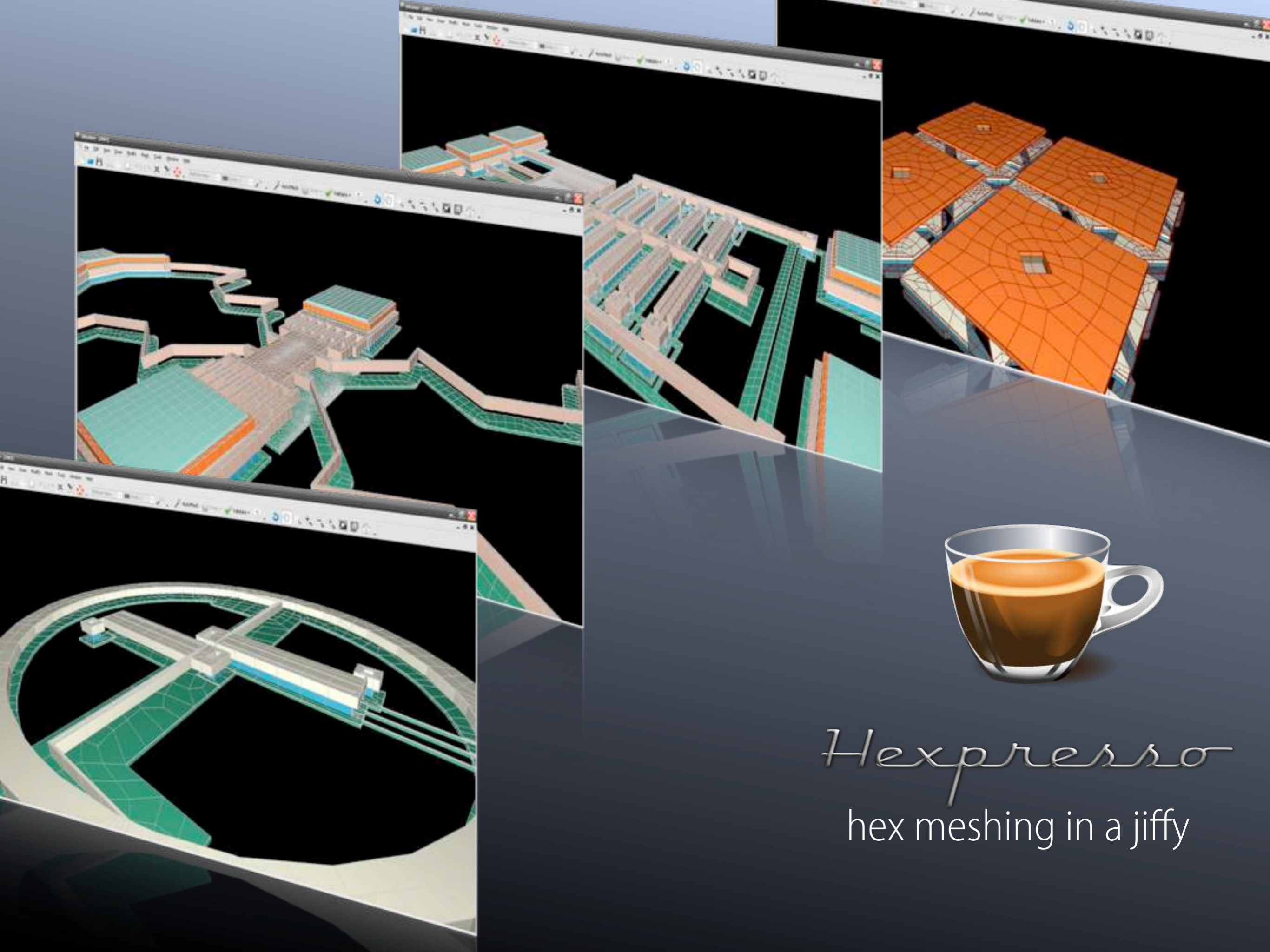
## Hexpresso

- Automated HEX mesher
- 1 click Mask to Mesh

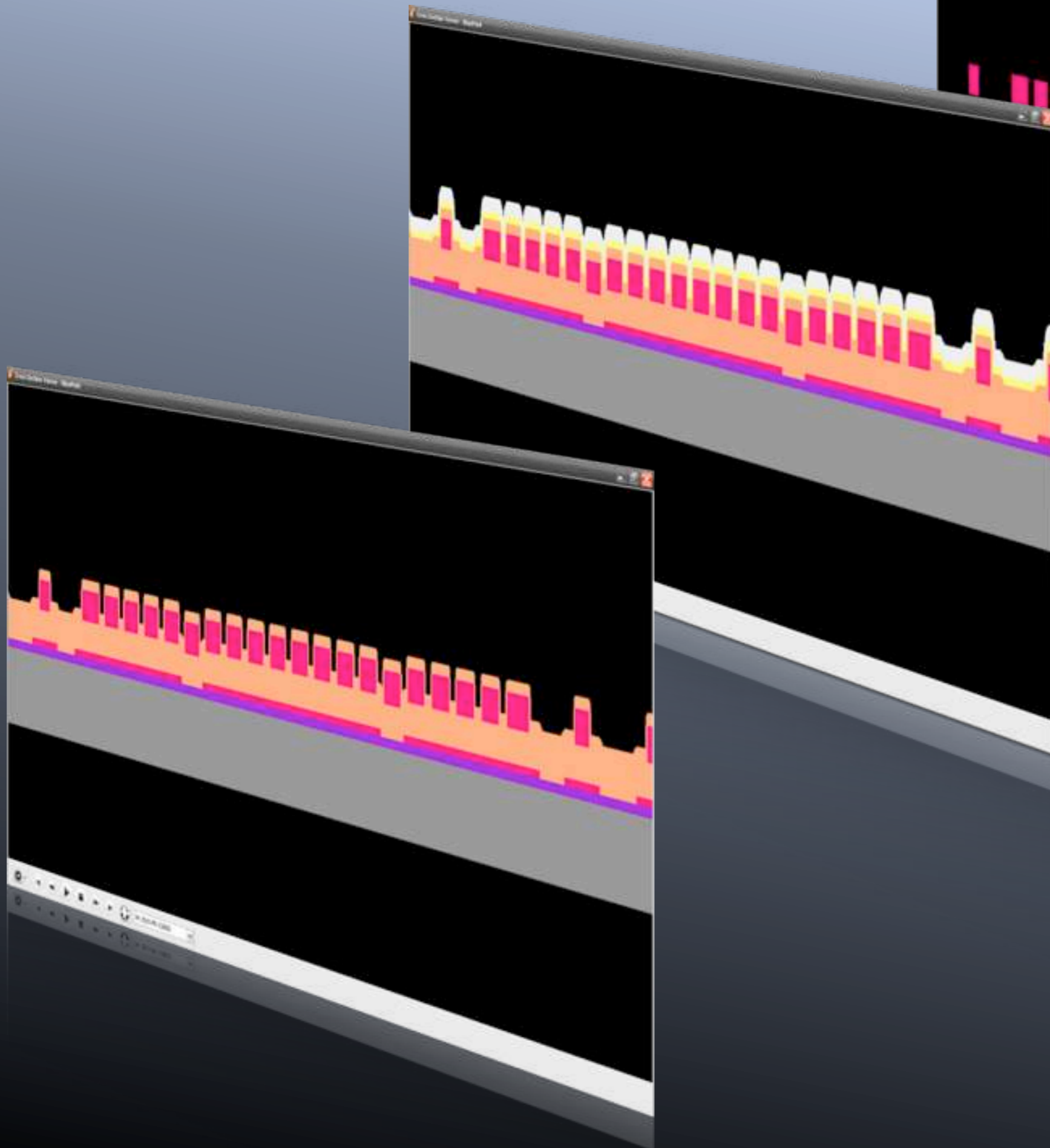




**BLUEPRINT**  
mems design editor

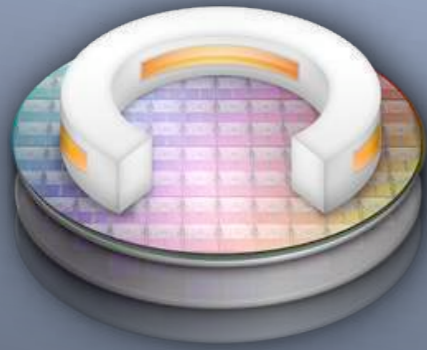


*Hexpresso*  
hex meshing in a jiffy

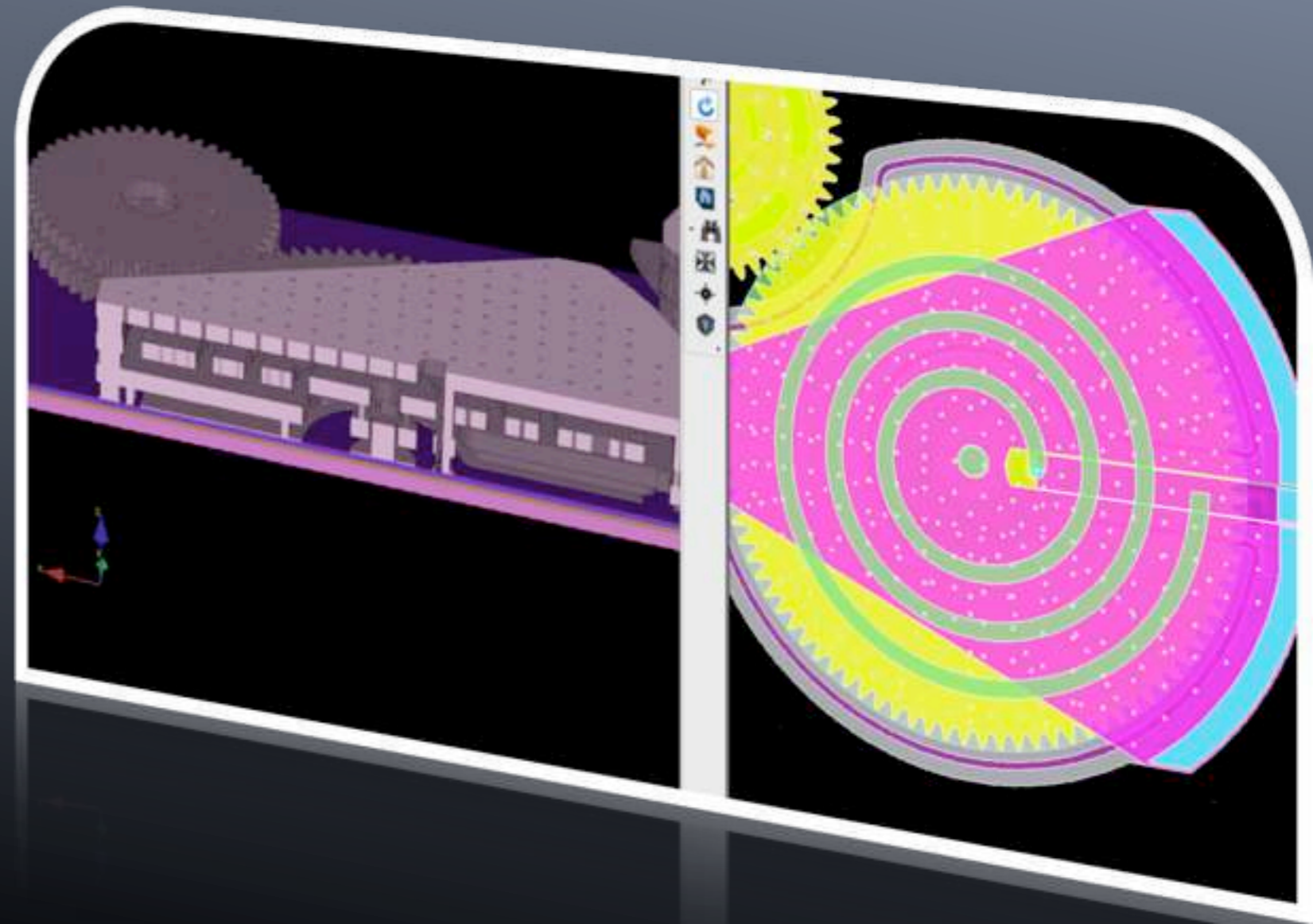
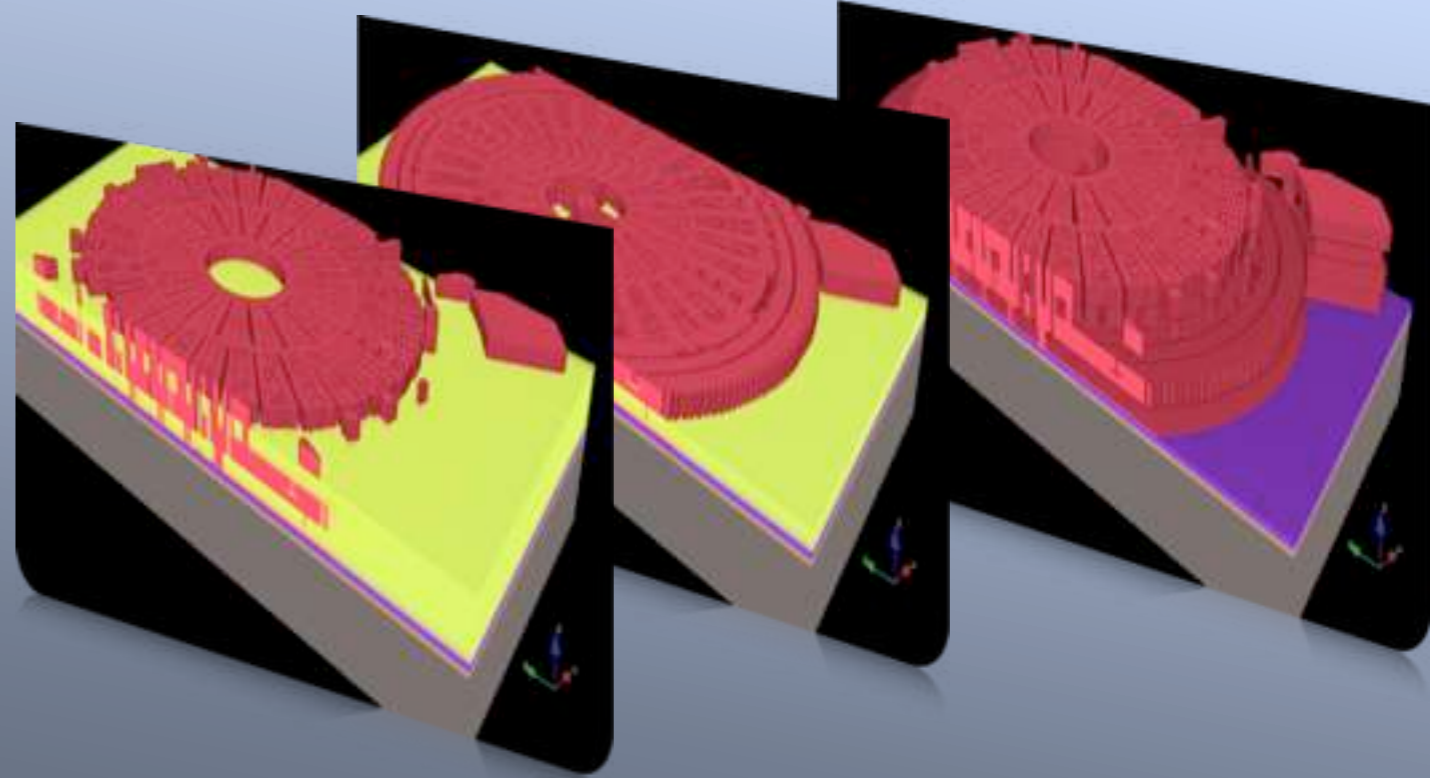


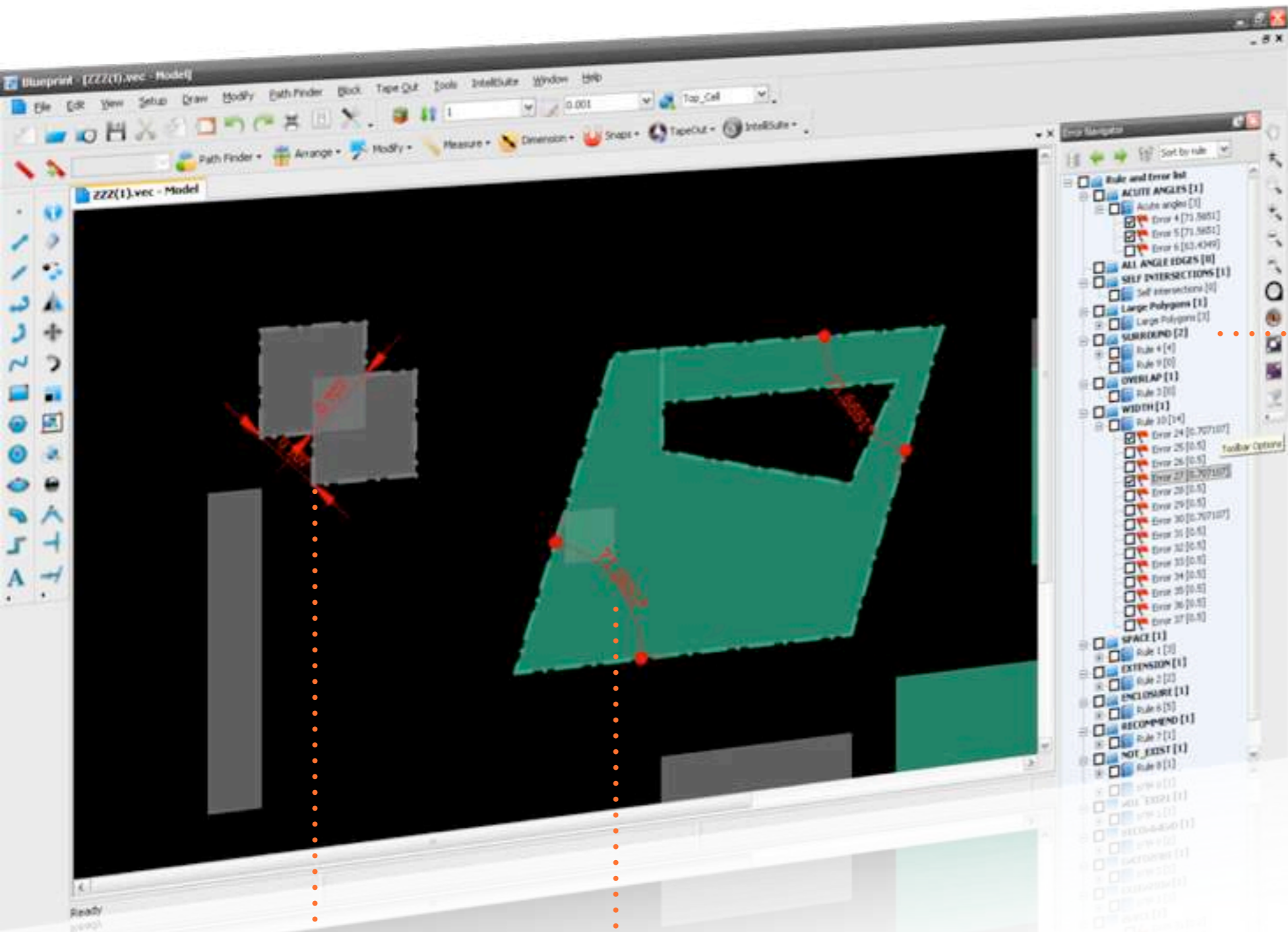
# CS Viewer

Step by step process visualization



# Cleanroom integration





Easy error navigation

intuitive error markings

all angle support



**Tape Out**  
**Physical verification**



# CS Viewer

- Tightly integrated with layout
- Step by step process visualization
- Process debug
- Output cross sections to Powerpoint

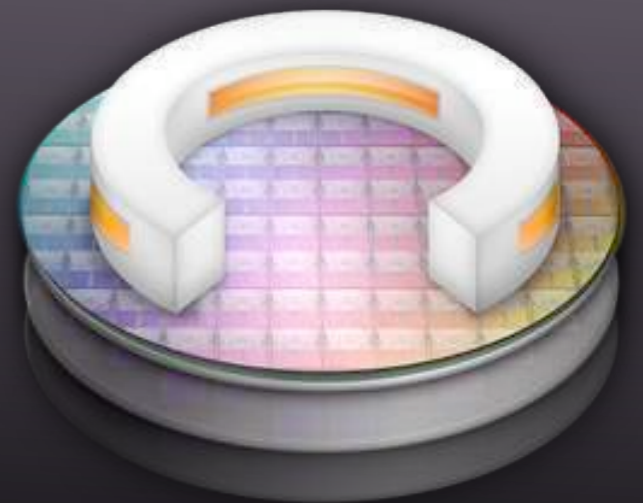


*Hexpresso*

hex meshing in a jiffy

- One click meshing
- Mask to mesh
- Process based meshing
- Adaptive meshing
- Quick and robust mesher

# Process validation





# What is Clean Room?

## **Process simulation and visualization**

State of the art 3D process modeling

## **RECIPE**

RIE/ICP/Bosch etch simulation  
STS etch database

## **IntelliEtch**

*Ab initio* based etch modeling  
wet and dry etch modeling

## **MEMaterial**

Material databases & process optimization

## **IntelliFAB**

Process traveller creation and visualization.

## **Hexpresso**

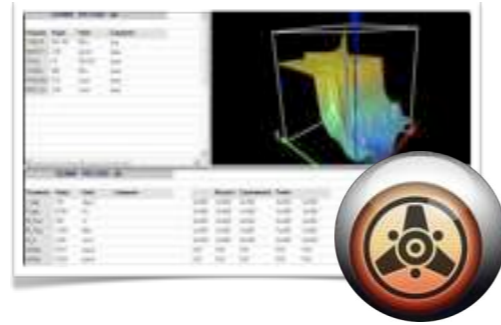
Automated hexahedral meshing engine for FEA/BEA model creation

# Clean Room capabilities (Process)



## Process capture

Develop process traveller  
Debug traveller  
Create process databases



## Material databases

Process correlated databases  
Material properties



## Process simulation

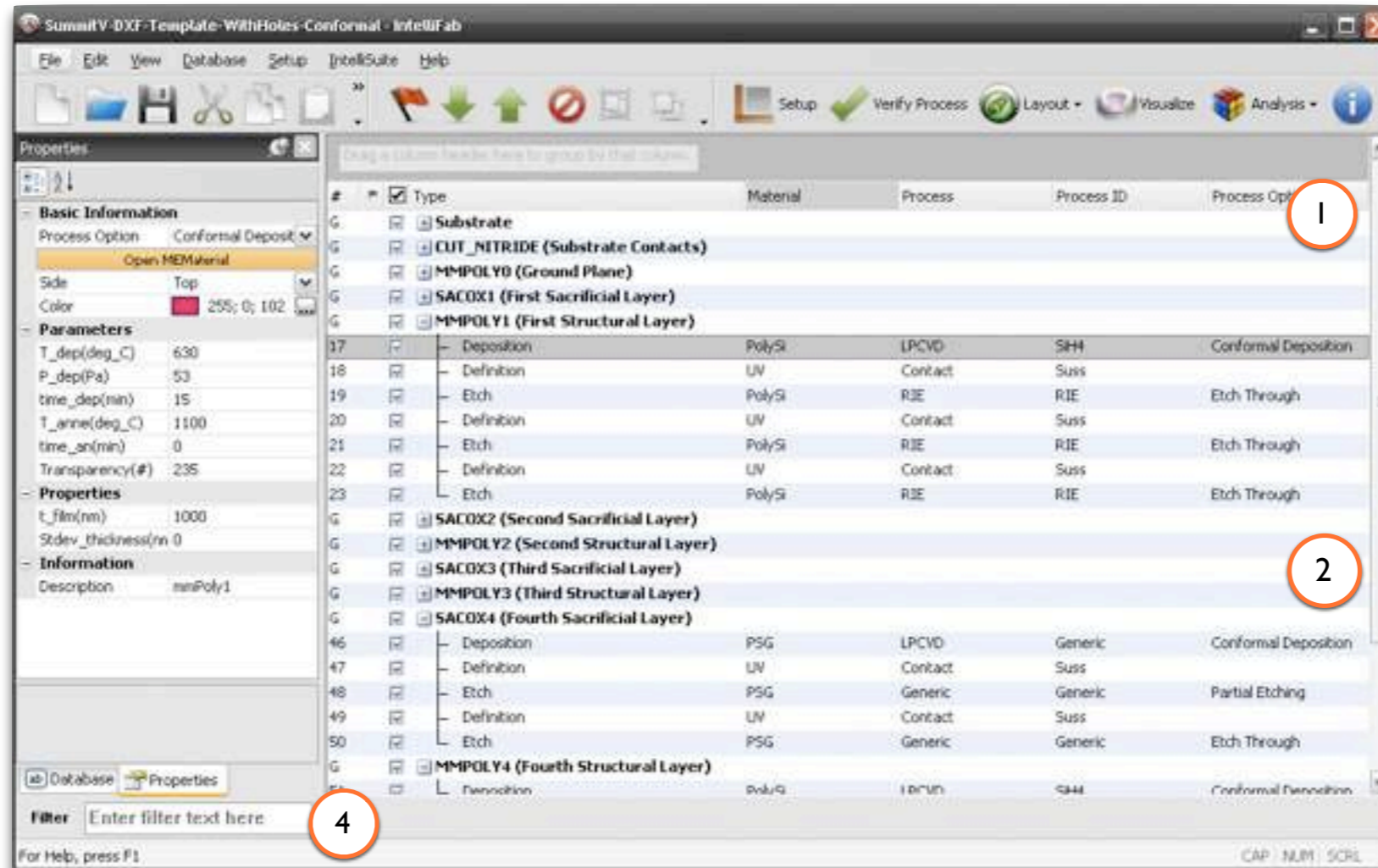
FABViewer: Flow visualization  
AnisE - Anisotropic etching  
IntelliEtch - *ab initio* etching  
RECIPE - RIE/ICP etch simulator



## Hexpresso

Automated HEX mesher  
1 click Mask to Mesh

# Setup complex process flows...



## Process Pane

Enter process parameters, tolerances and visualization settings in a single consolidated pane

## Process Editor for MEMS

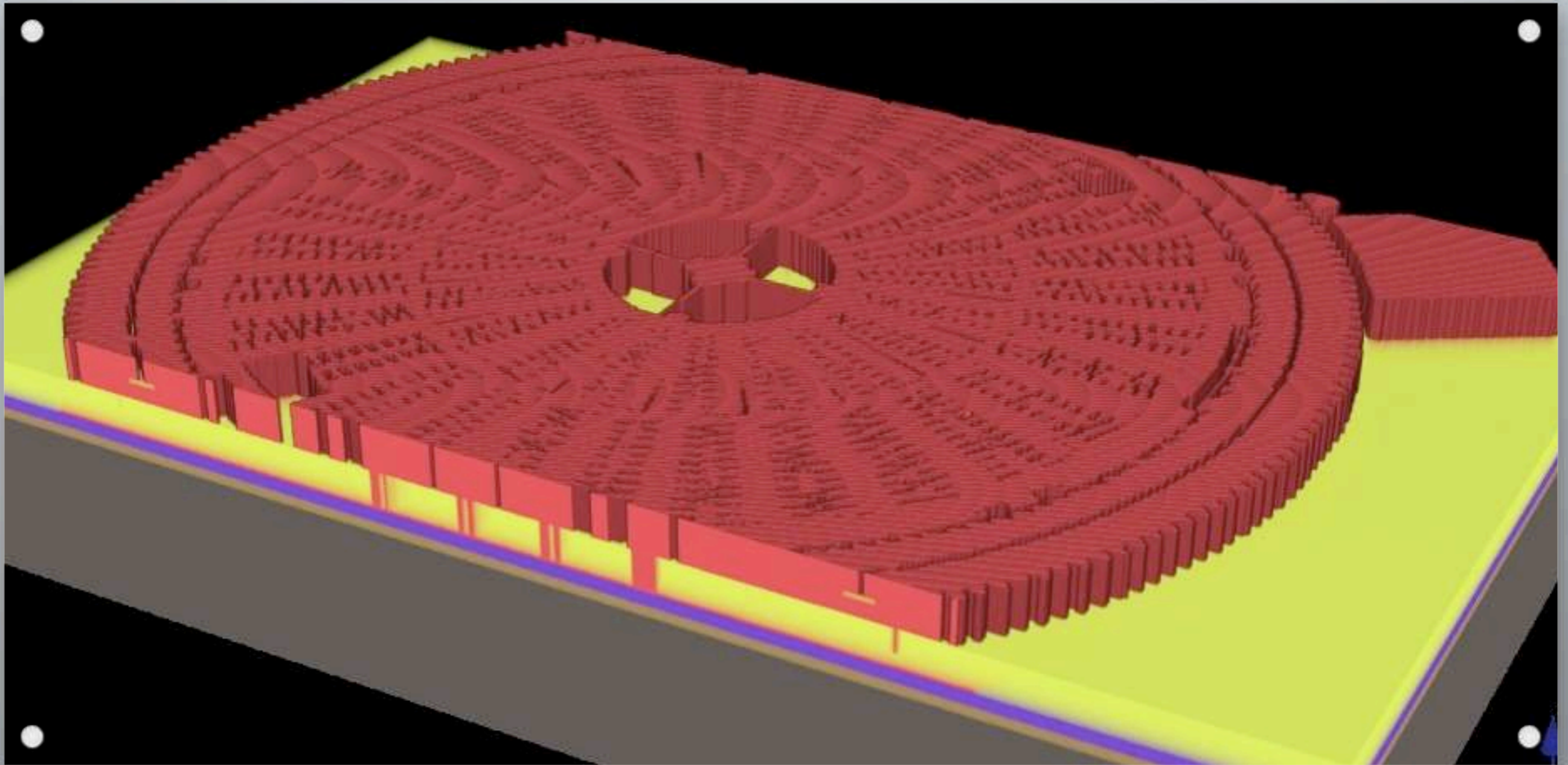
IntelliFAB makes editing and organizing a process table quick and easy. Setup your virtual process traveller exactly as you would for a real foundry.

## Group, section, organize

Grouping common sets of processes into process subsets makes the organizing a complex traveler easy. You can group your process flow in any which way you please: by material, by process type or by process option.

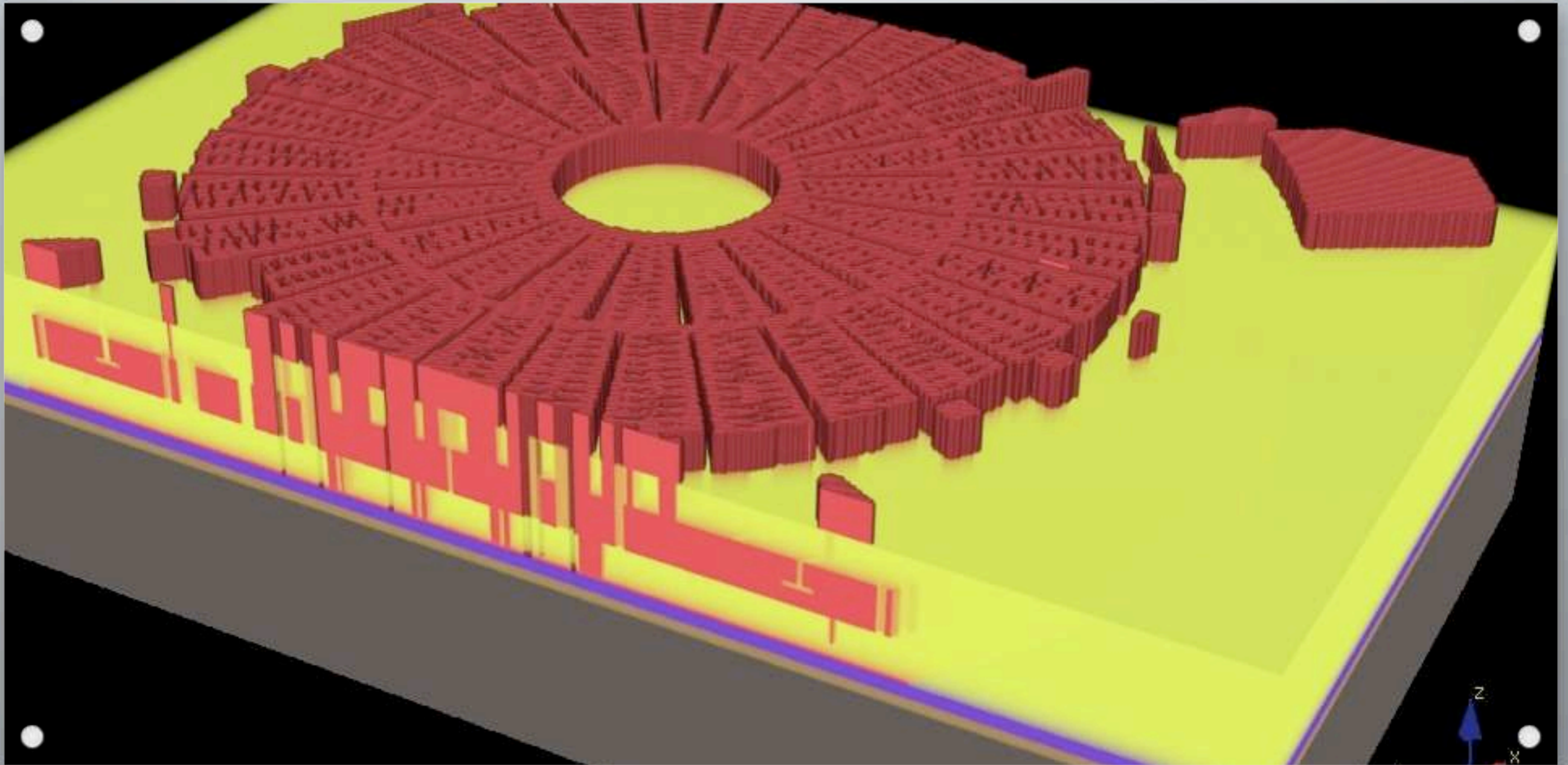
## Filter with ease

Filtering tools allow you to quickly focus on the processes that you want to explore

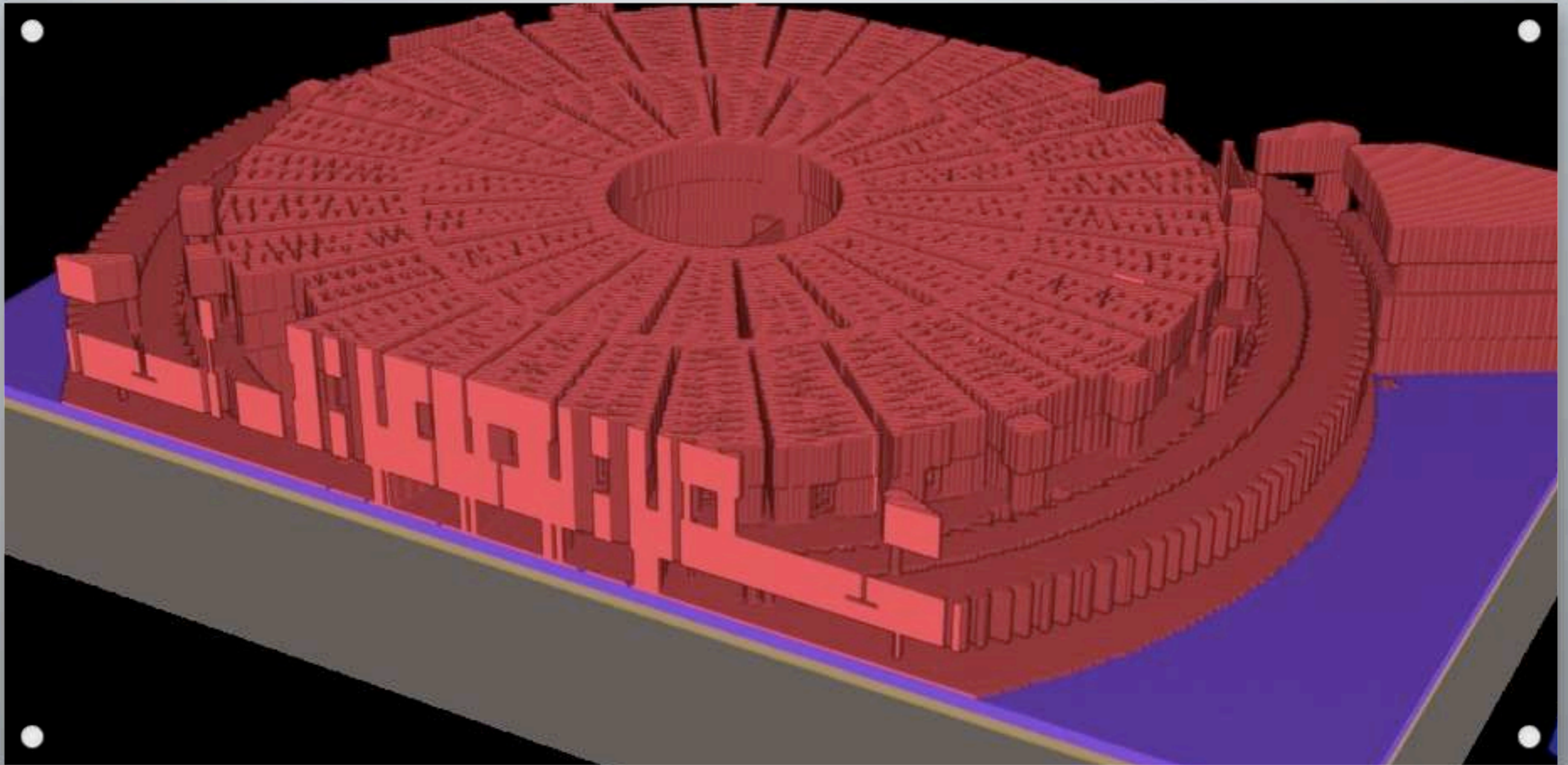


# VISUALIZE COMPLEX PROCESS FLOWS

Courtesy, Prof Tim Dallas, Texas Tech



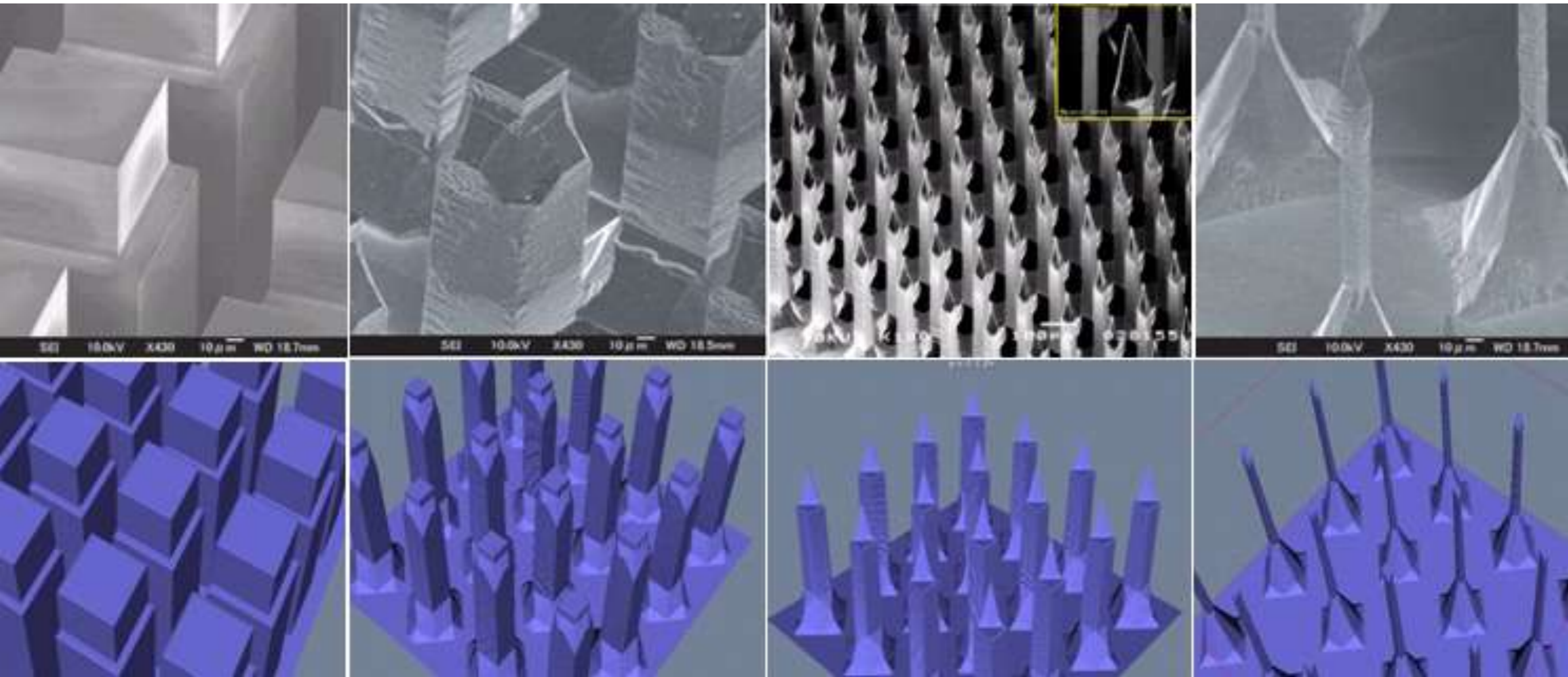
# VISUALIZE COMPLEX PROCESS FLOWS



# VISUALIZE COMPLEX PROCESS FLOWS

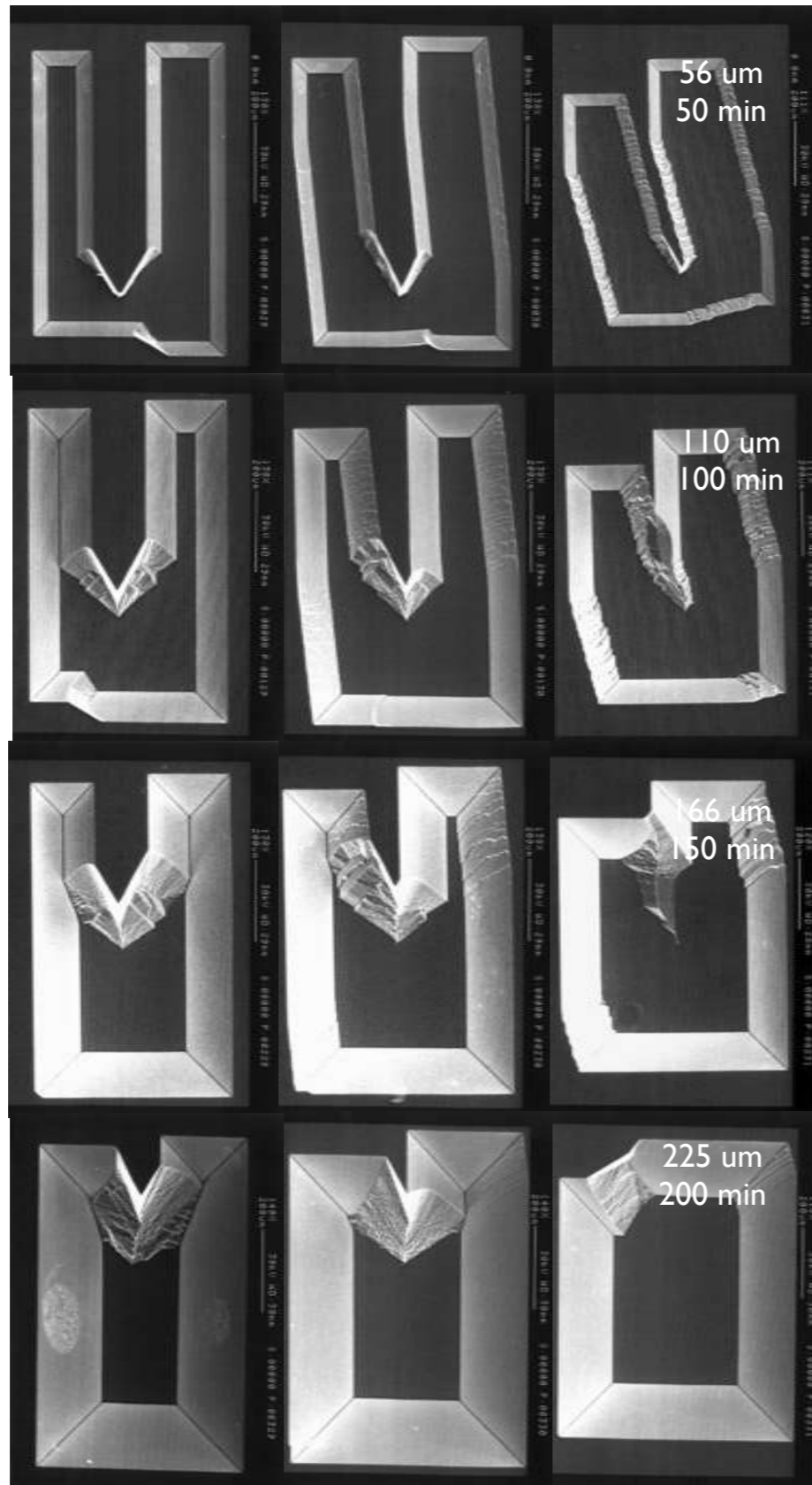
Courtesy, Prof Tim Dallas, Texas Tech

# Simulate composite MEMS processes



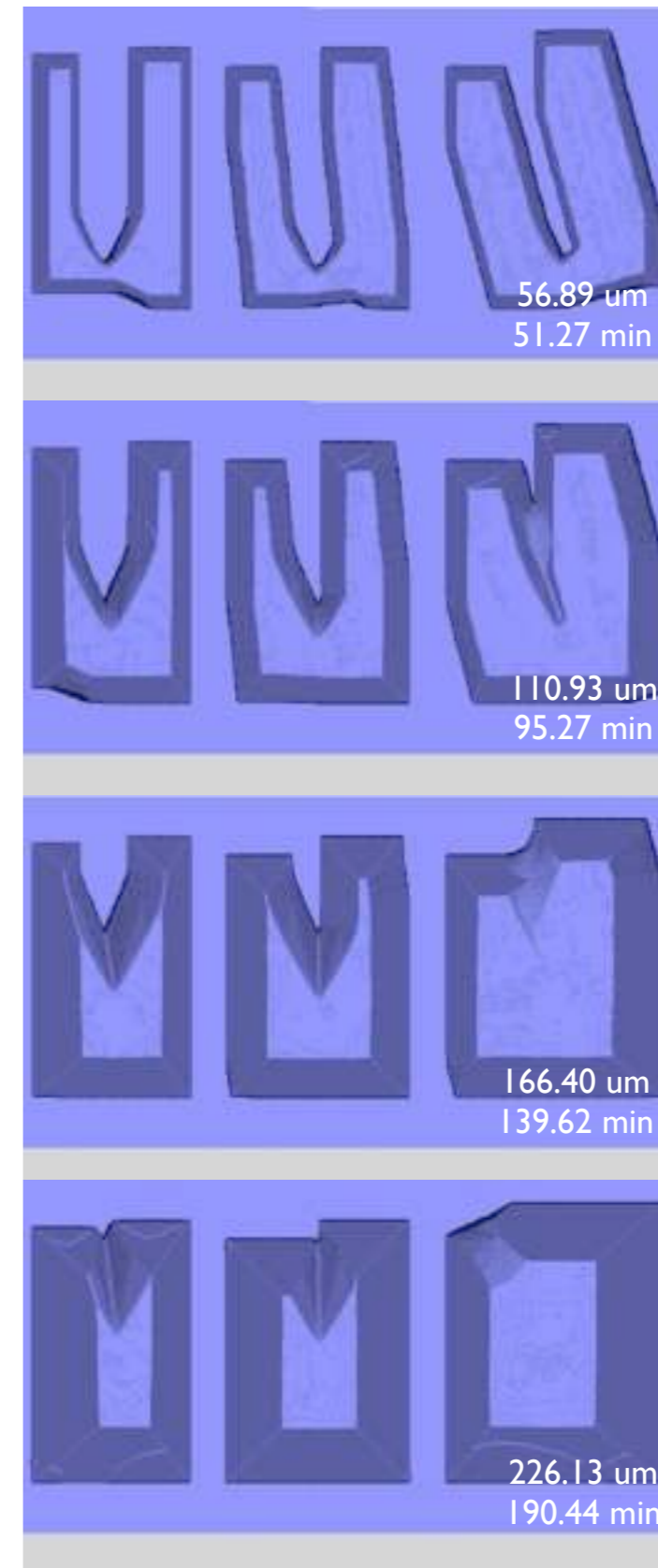
**Combination of multi-step mask transfers, oxide and nitride layers, sacrificial layer deposition and wet etching and DRIE processes.**

# Validate processes in design



Measured

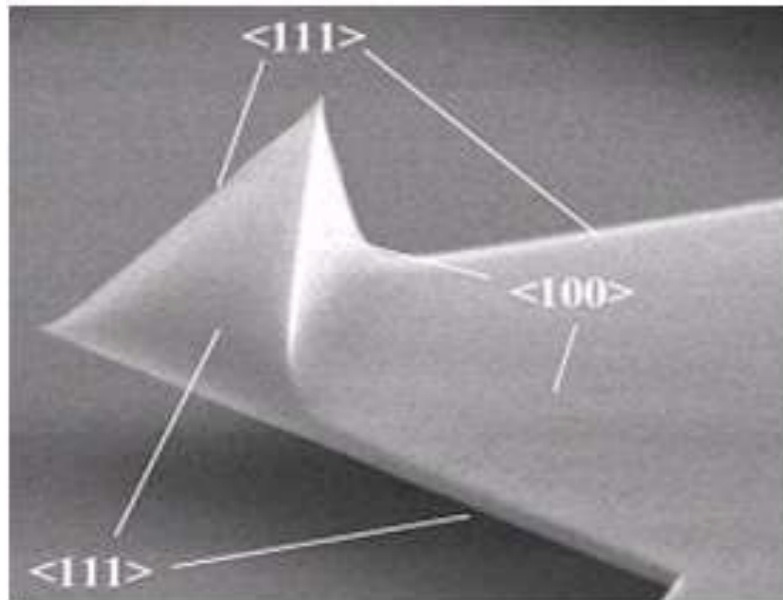
vs



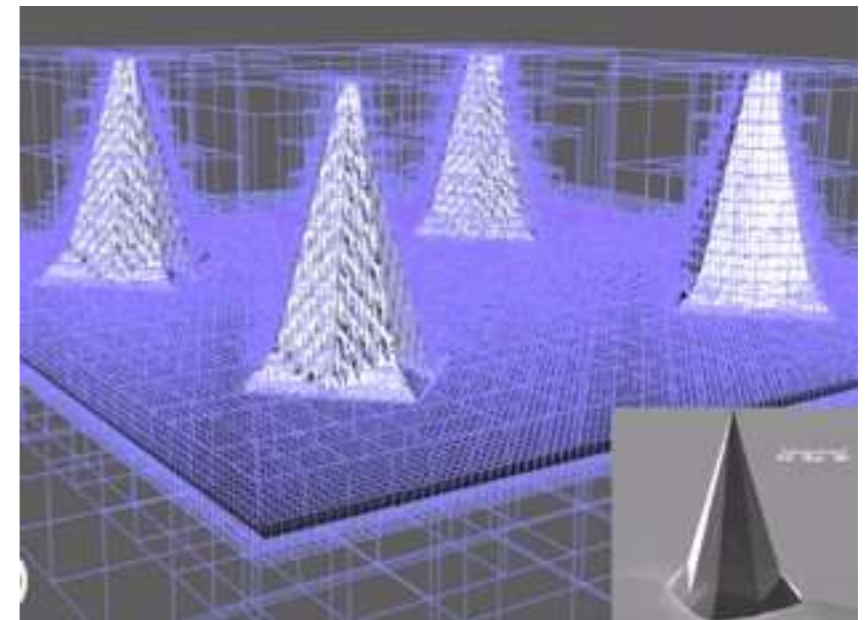
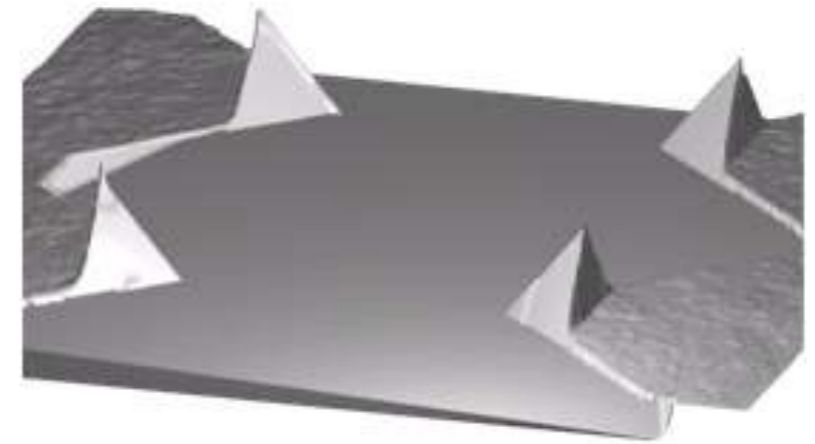
Modeled



# Higher order plane etching

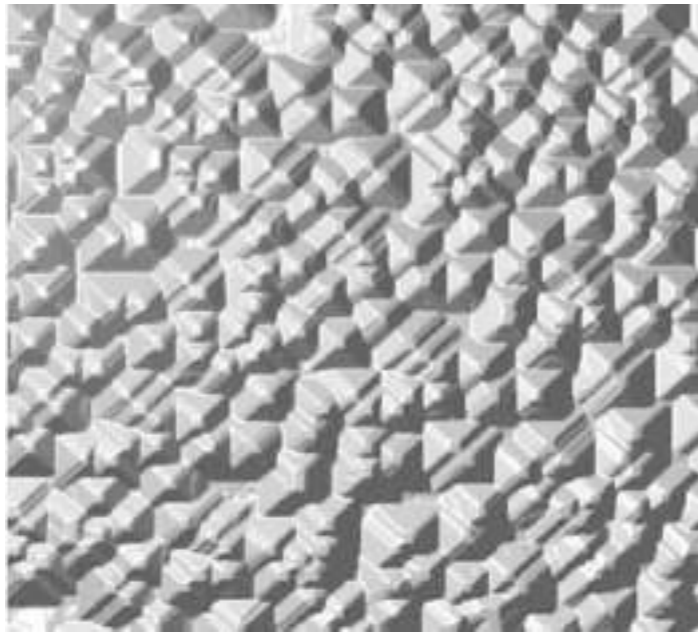


D. Saya, Sensors & Actuators A95 (2002)

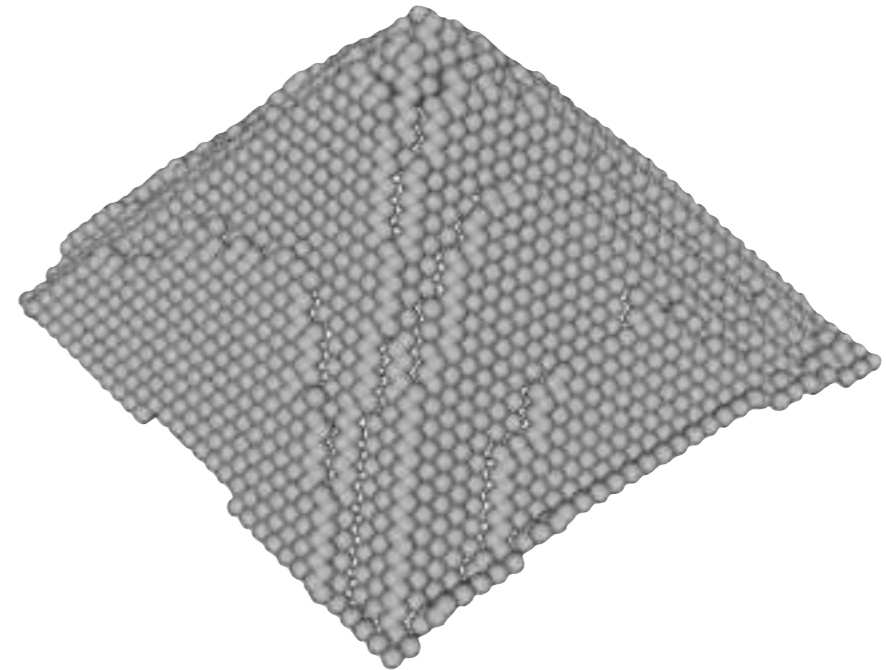


Simulation results

# Surface morphology prediction

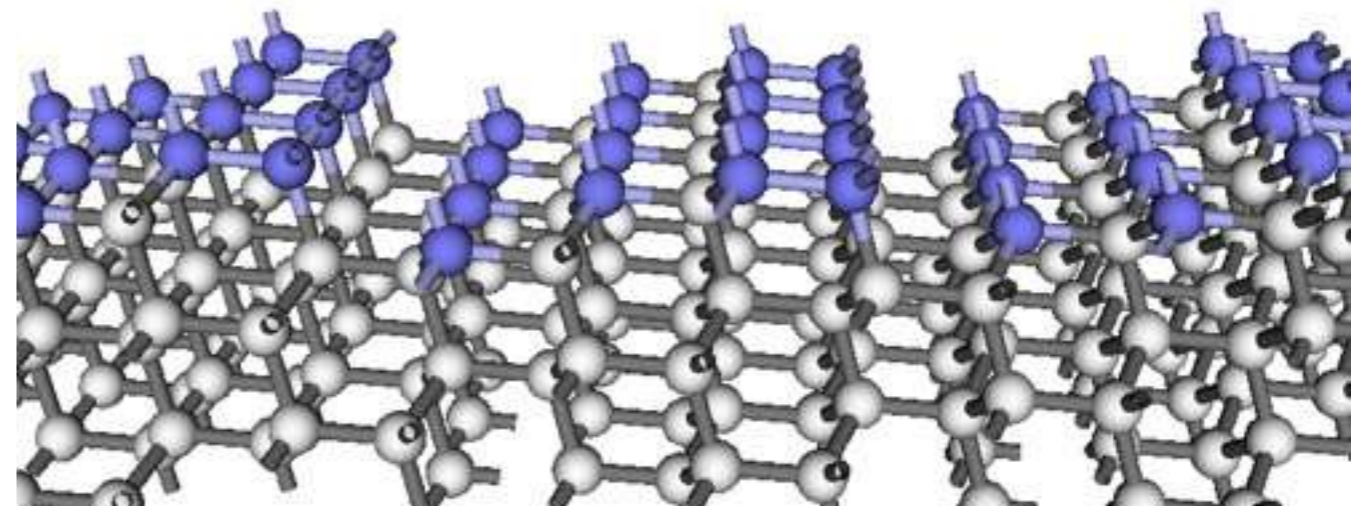


Pyramid like morphology on 100 Si  
subject to wet anisotropic etching

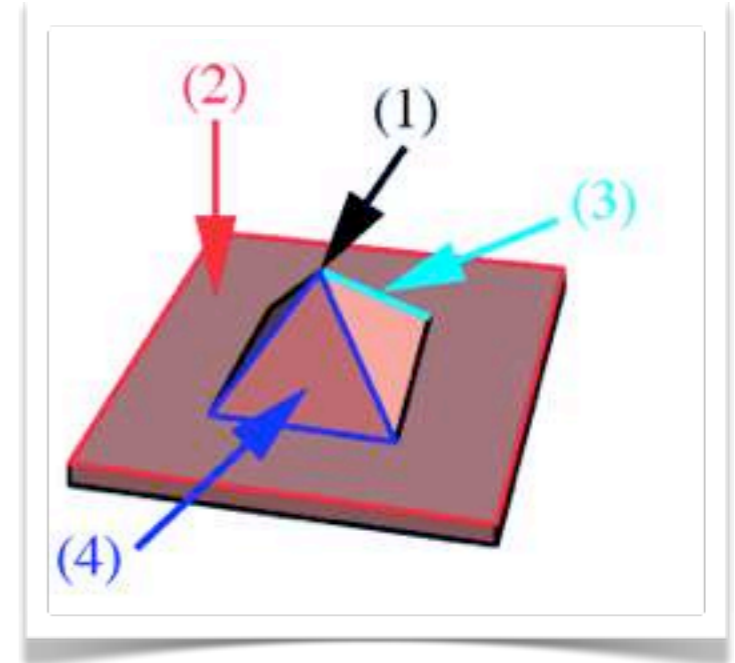
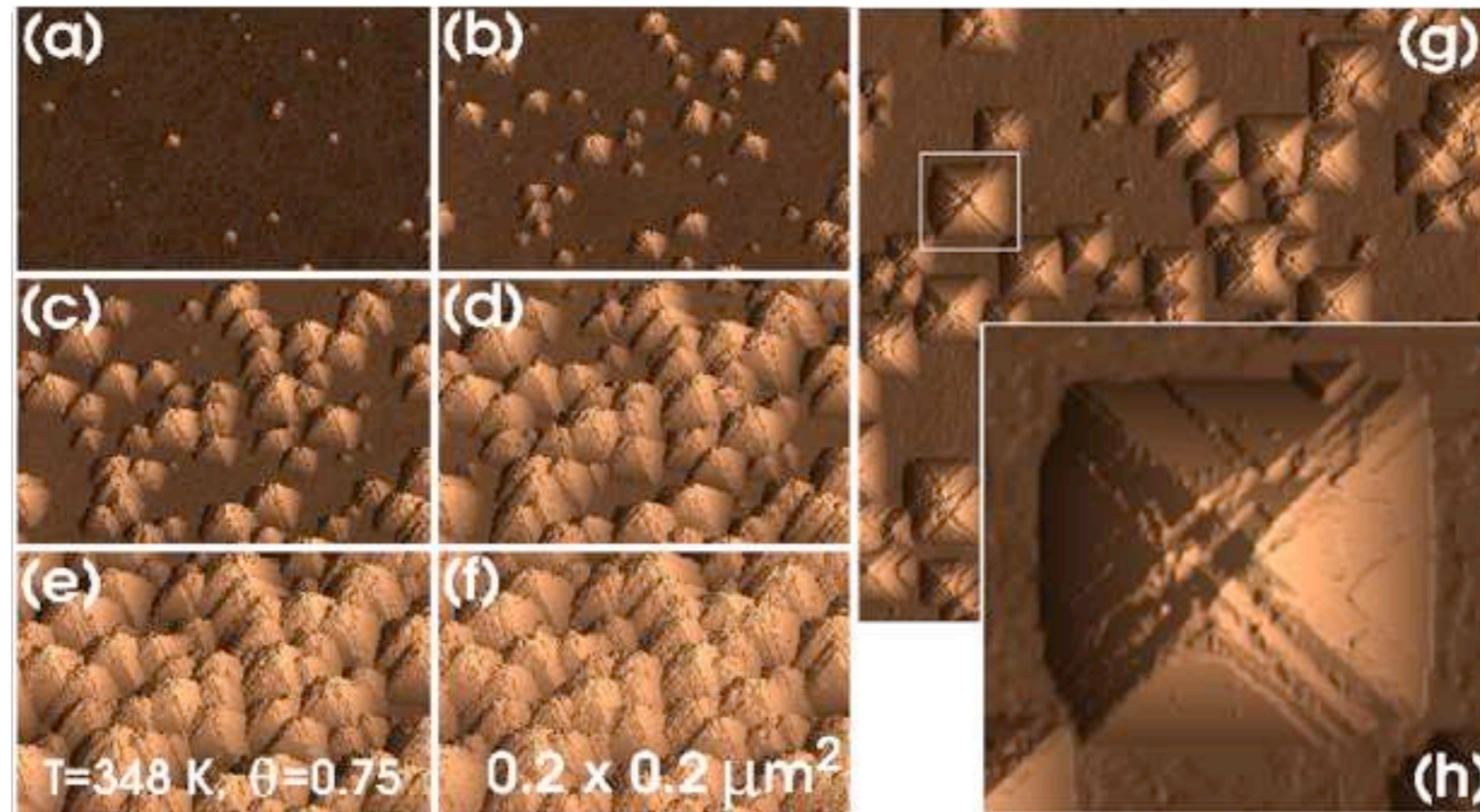


Simulation results predict pyramid formation

Arbitrary Cut Planes  $\langle 533 \rangle$   
to understand the physics



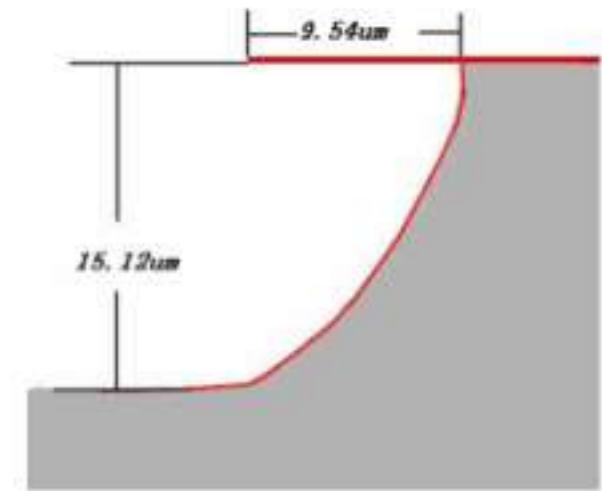
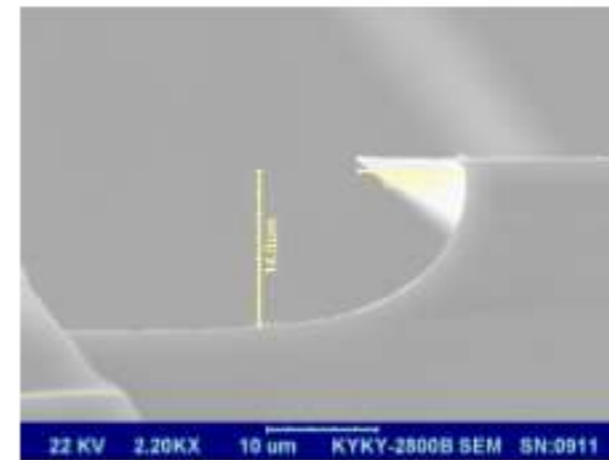
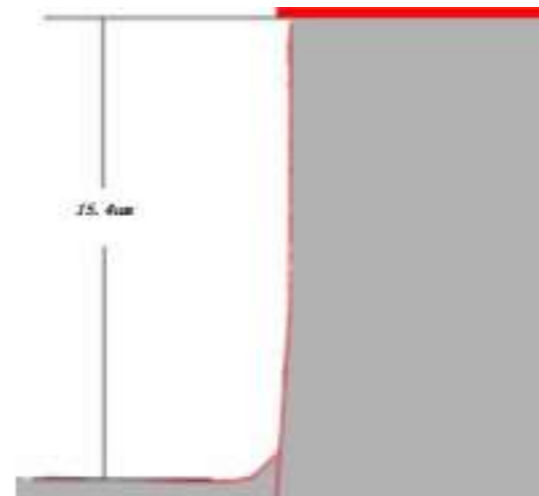
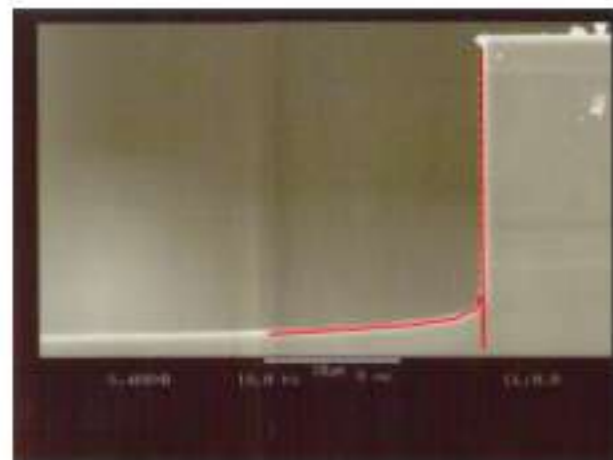
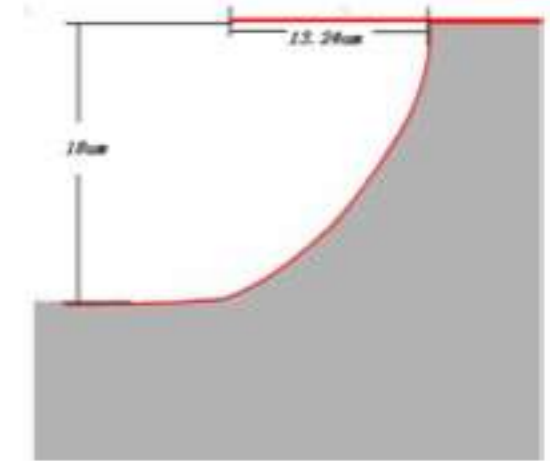
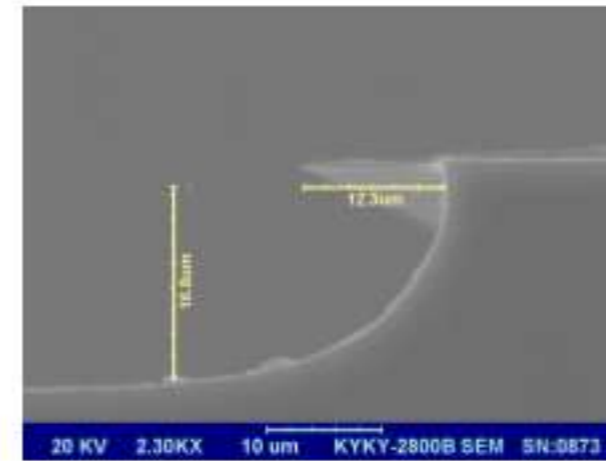
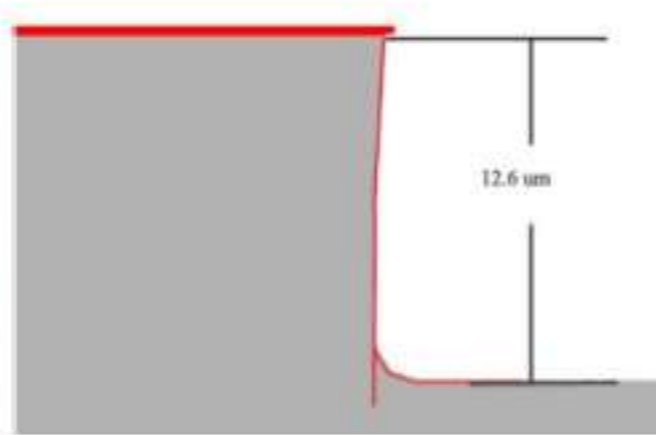
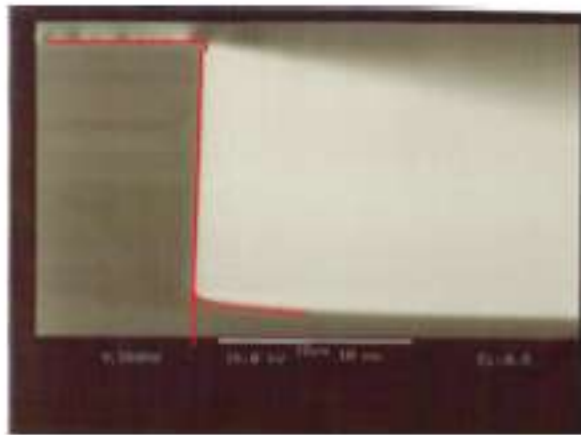
# Surface morphology prediction



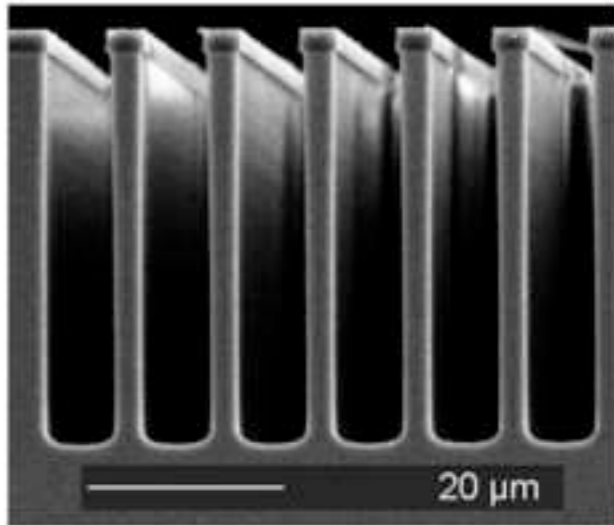
- 1 Micromasking of apex
- 2 Floor moves down fast
- 3 Edges are stable
- 4 Facets are very stable

Hillock formation prediction

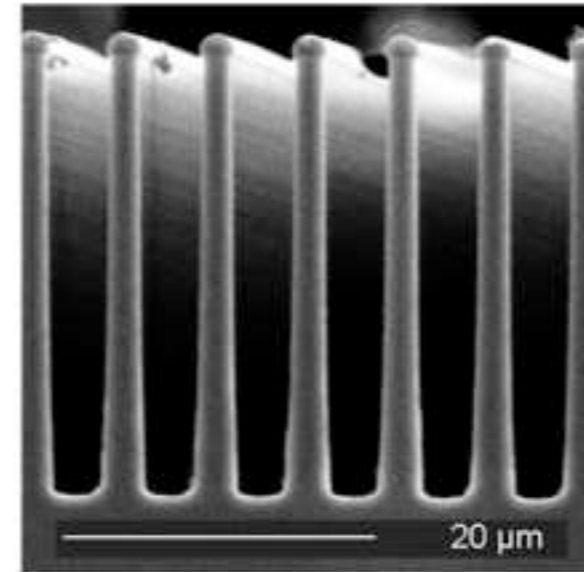
# DRIE Etch characterization experiments (1)



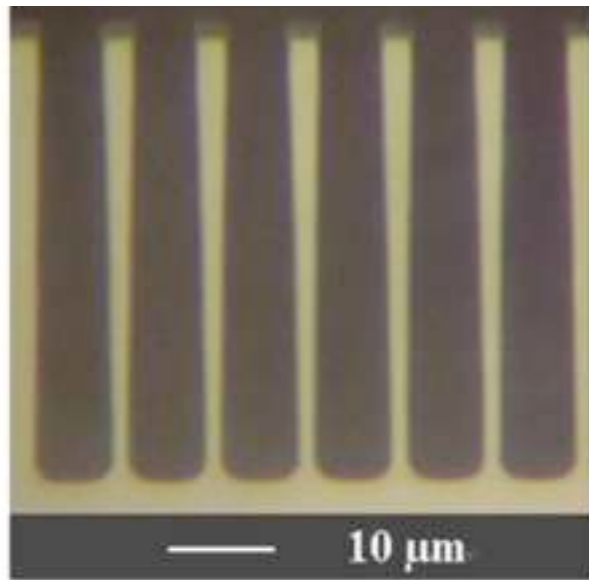
# DRIE Etch characterization experiments (2)



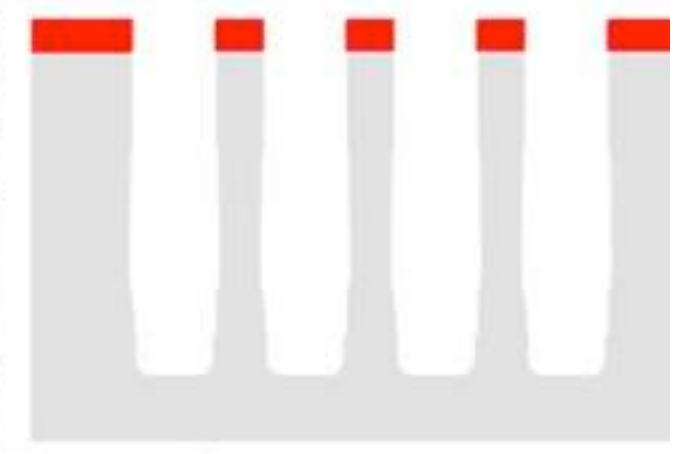
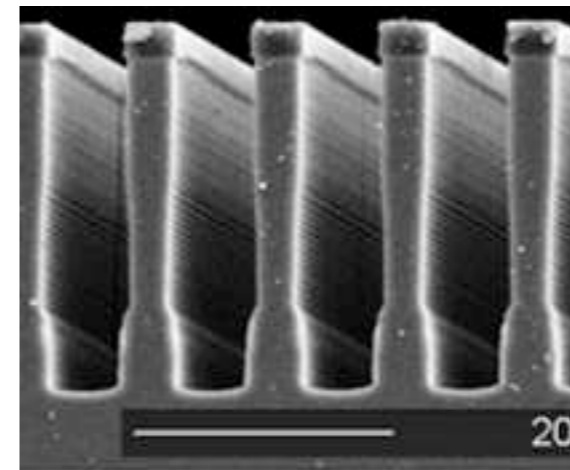
The experimental results of the etching. Comparison of etching 5 μm openings with an etch/dep cycle of 7s/7s.



Comparison of etching a 5 μm trench with a 5s/7s cycle

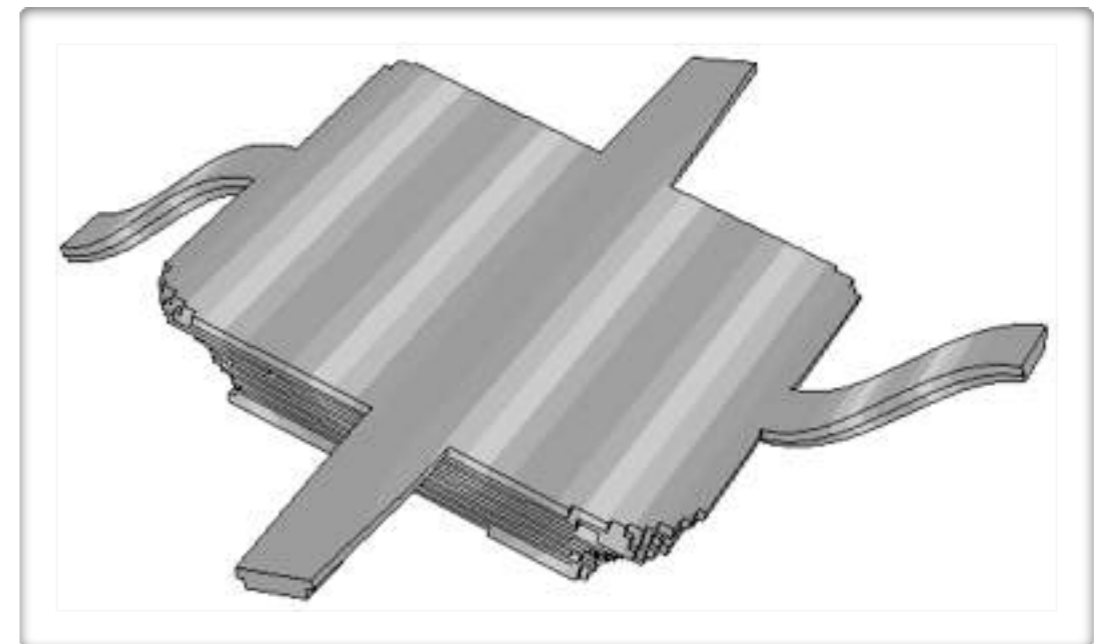
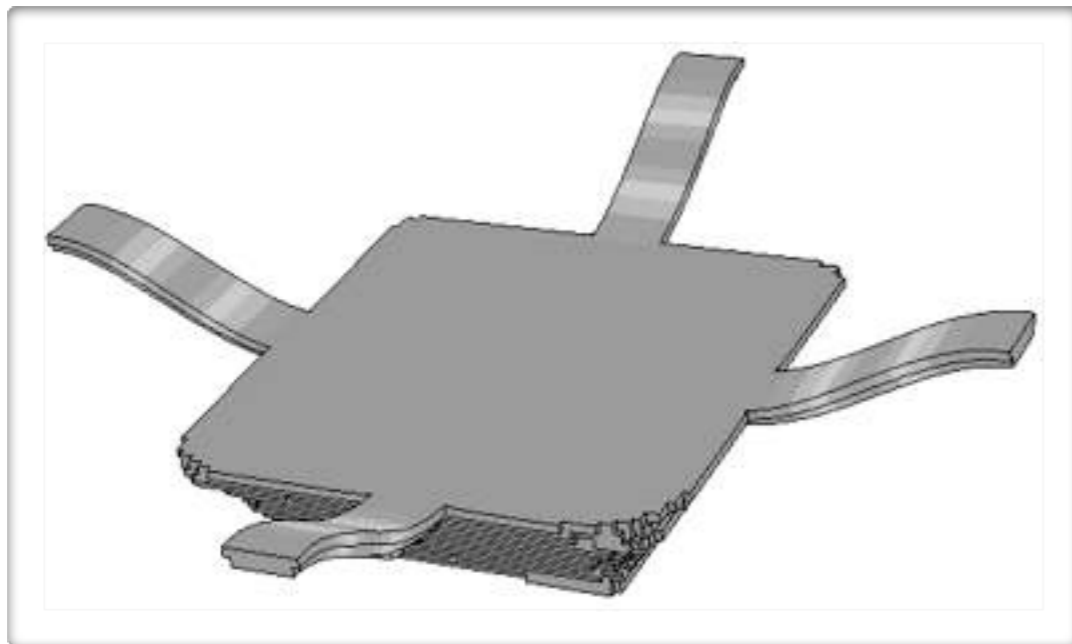
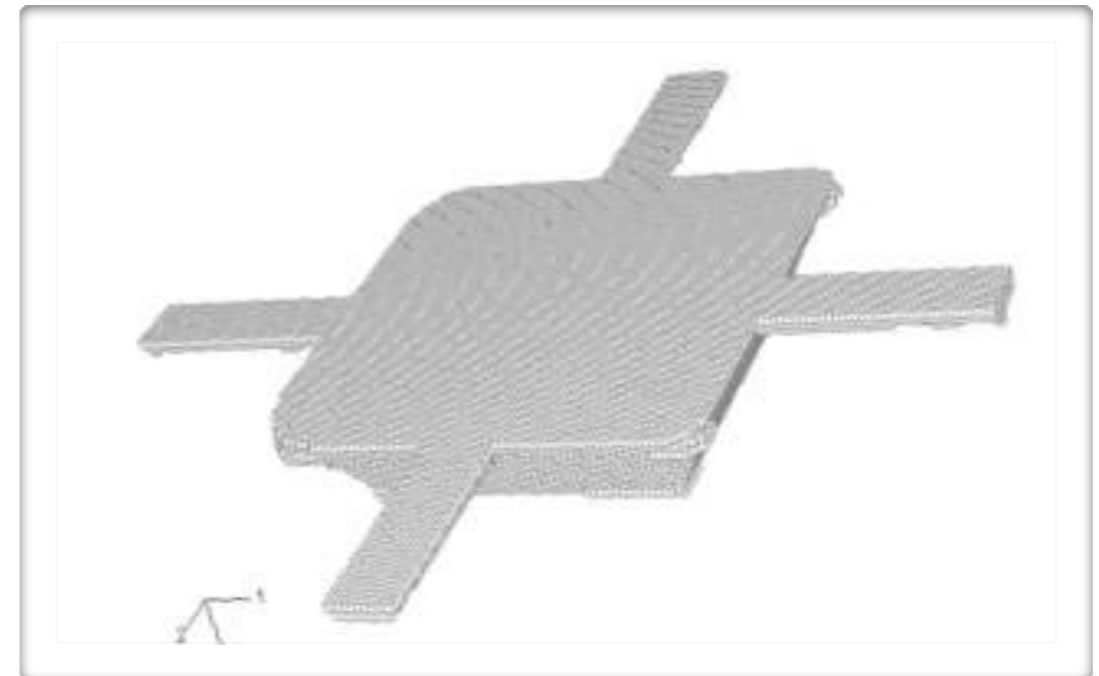
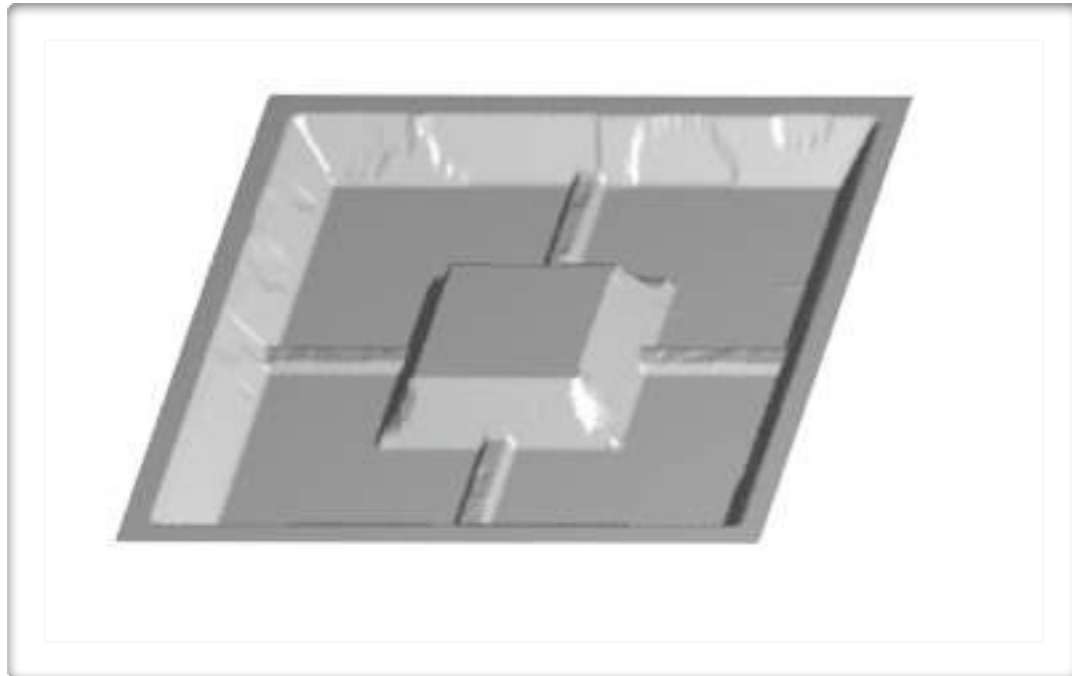


Comparison of etching a 5 μm trench with a 7s/8s cycle

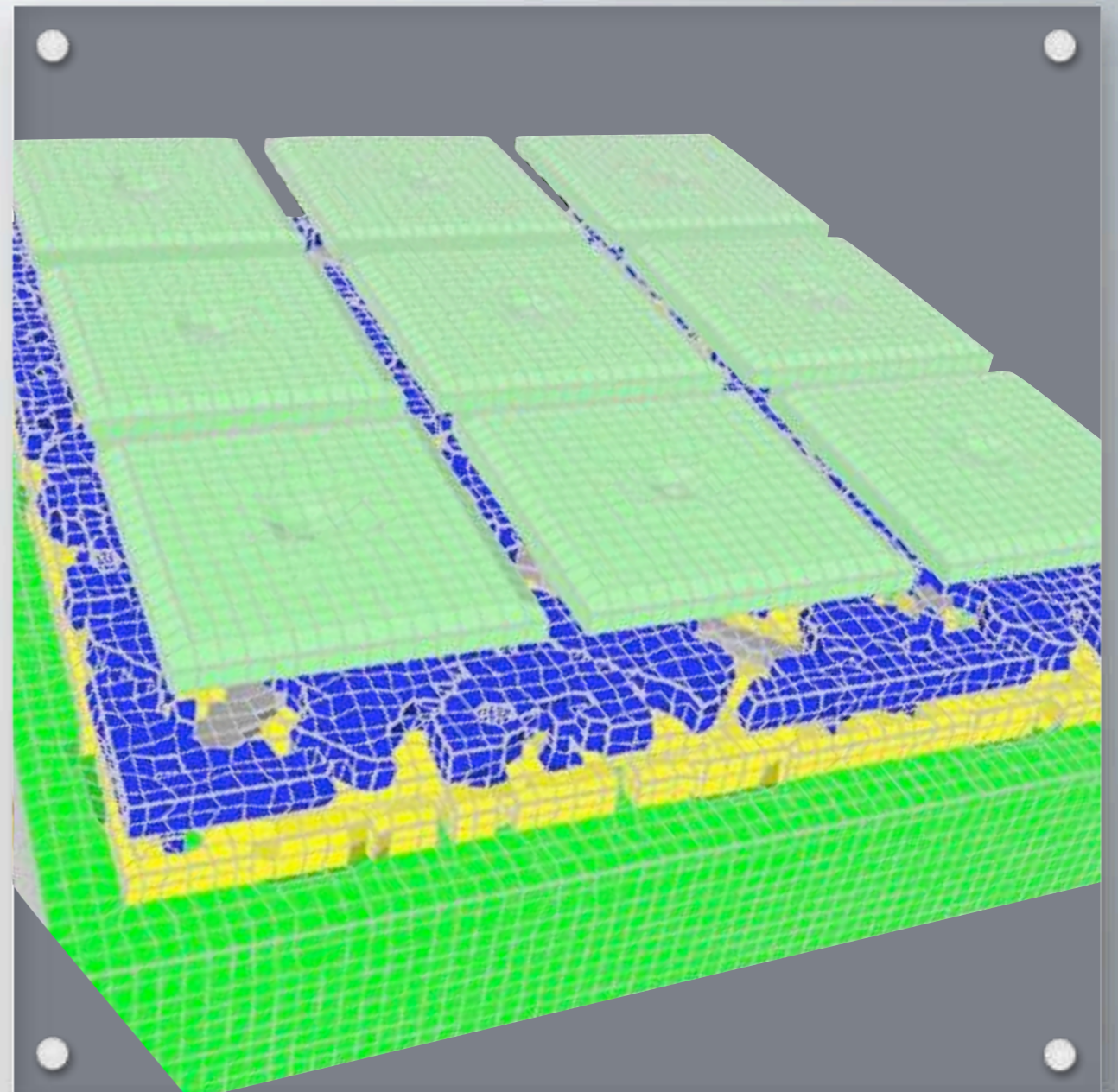
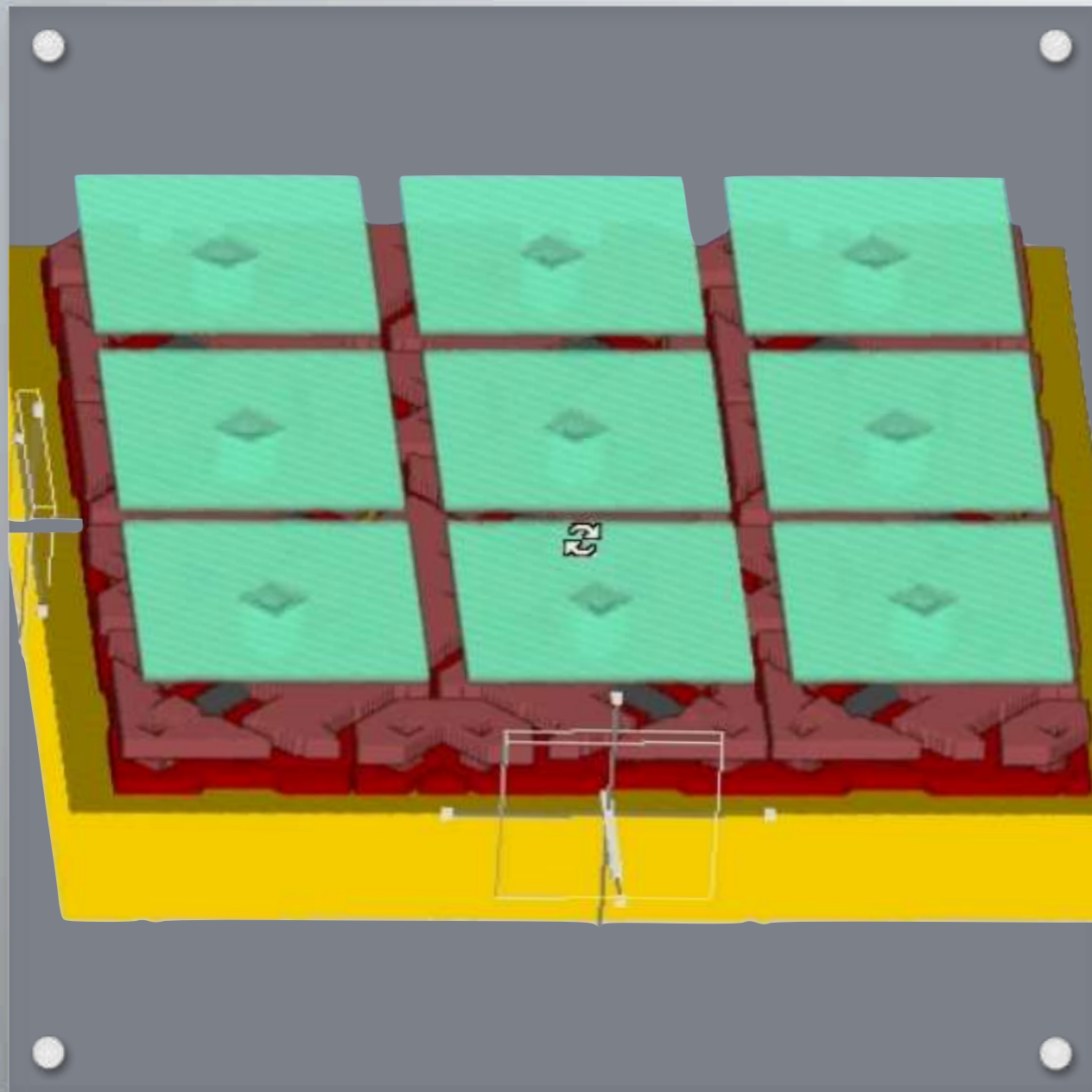


The experimental result of the etching of trenches using three etching steps with different etching/polymerization time configurations. 7s/7s, 9s/7s and 5s/7s are used sequentially, each for 5 minutes.

# Output to FEA



**Interface with analysis tools:** Direct export to IntelliSuite and other industry formats



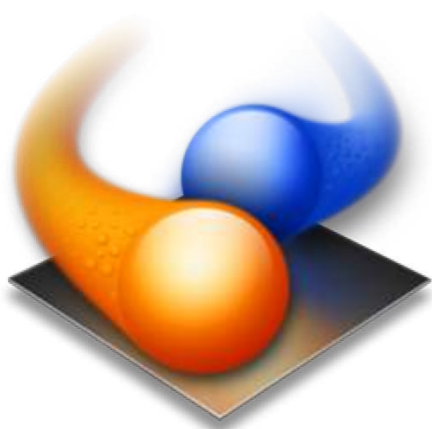
**PROCESS TO MODEL**

# Fastfield solvers





# Fastfield capabilities (Structural)



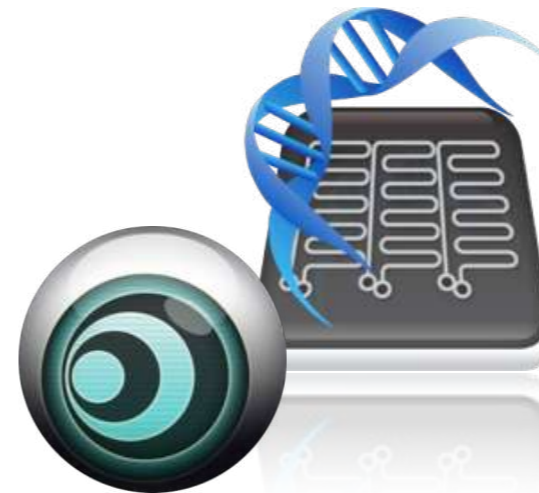
## Fastfield Multiphysics

Unique FEM-BEM formulation  
64 bit multi-processor enabled  
5-10X than pure FEM based



## Fully coupled

Thermal  
Electrostatics  
Mechanical  
Fluidics  
Contact physics  
Piezo  
Magnetostatics



## Specialized engines

BioMEMS  
High frequency EMag



## Extraction

Multiphysics capture  
Efficient for verification  
Lagrangian models  
1000X more efficient than FEA

# What is Fastfield Multiphysics?

- &• **Coupled solver formulation**

ANSYS, Algor, Comsol, etc are all pure Finite Element tools

- &• **Best solver for each physics domain**

Boundary Element Method (BEM): Electrostatics, Electromagnetics

Finite Element Method (FEM): Thermal, Mechanical and Electromagnetics

Volume of Flow (VoF) and Finite Volume (FV): Fluidics, Electrokinetics, Chemical Reactions

- &• **Advanced pre-correction and solver techniques**

Pre-corrected FFT (pFFT++), GMRES, Arnoldi, OpenMP based multi-processor solvers

# Why Fastfield Multiphysics?

- &• **Speed and efficiency**

2-10X Faster than pure FEA formulation (Algor, Ansys, Comsol, etc)

Handle large real world problems

- &• **Surface meshing vs volume meshes**

Internal volumes, air gaps, etc do not need to be meshed

Ease of meshing, no costly re-meshing during deformation

- &• **Ease of convergence**

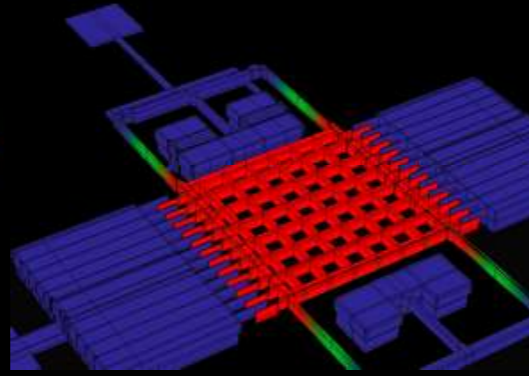
Quickly run your analysis without convergence issues

Deal with large deformations, contact and post-contact without convergence issues

*Rotary ring gyro  
Rate/Coriolis analysis*



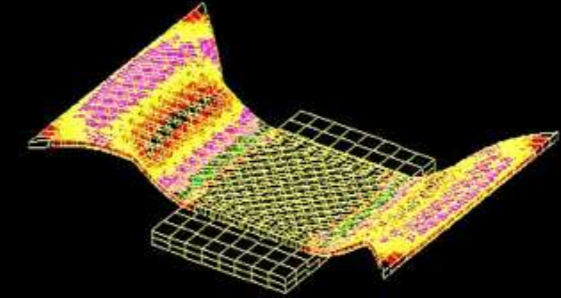
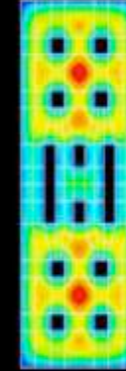
*Draper vibratory gyro  
Electrostatic drive*



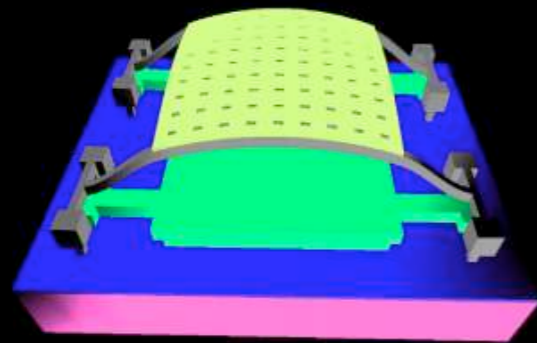
*Lockheed inertial device  
Squeeze film analysis*



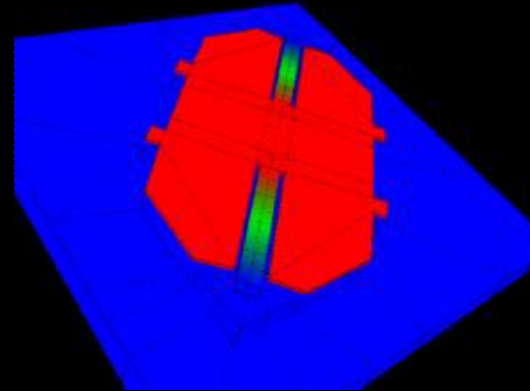
*Raytheon/TI RF switch  
Non-linear contact analysis*



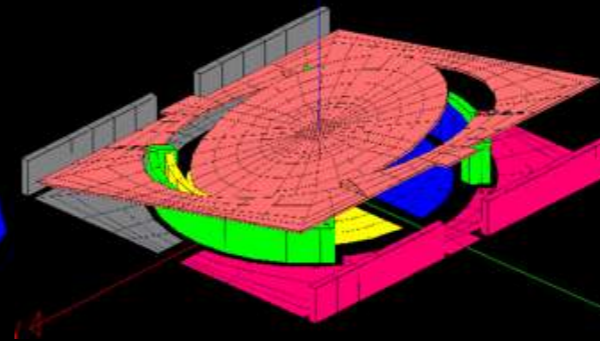
*Hitachi  
RF Tunable Filter*



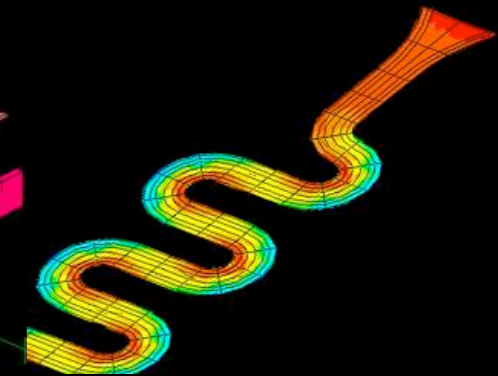
*NASA  
Adaptive optics*

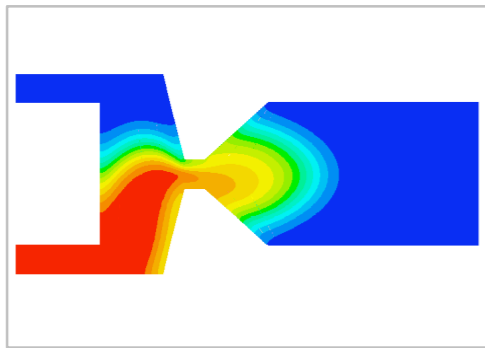


*Corning  
3D Optical cross connect*

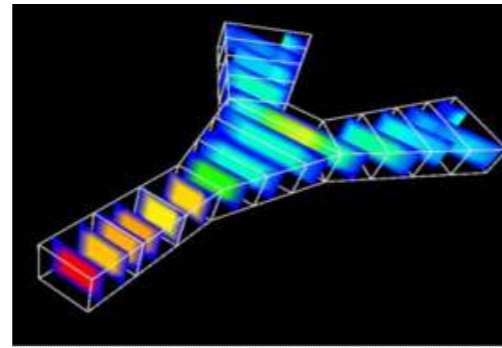


*NASA  
Radiation detectors*

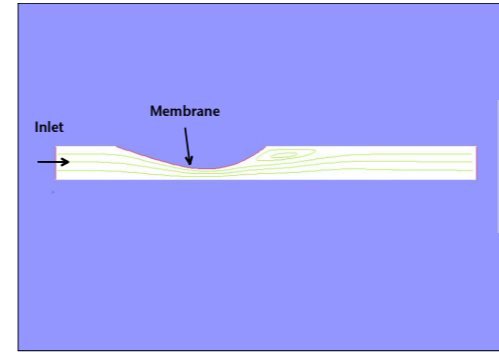




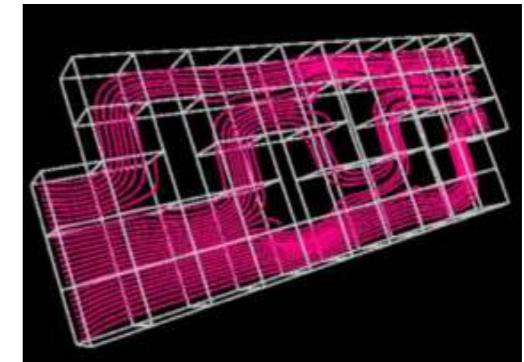
*Micro-mixing in a valve  
Concentration gradient evolution*



*Flow mixing  
Y combiner*

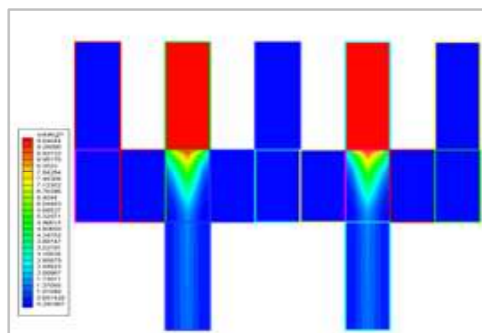


*Fluid Structure Interaction  
Inlet flow - membrane interaction*

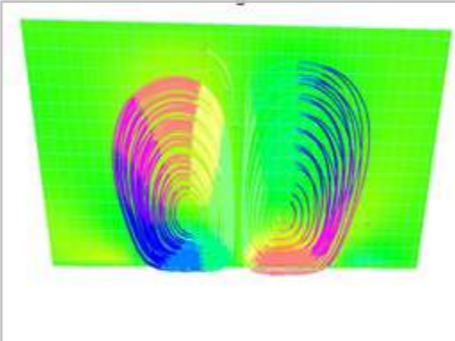


*Flow separation device*

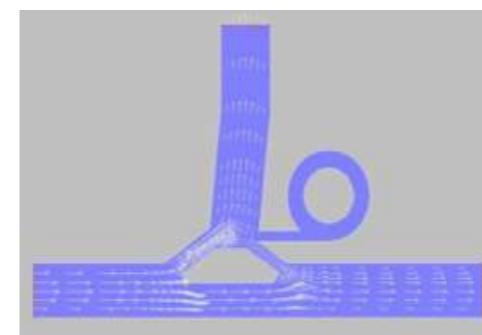
Microfluidics • Electrokinetics • Transport stoichiometry • Heat transfer • Electro-Wetting on Dielectric (EWOD) • Digital droplet microfluidics • Free Surface Flow • Fluid Structure Interaction • Electrochemistry • Micro-mixing • Electrophoresis • Dielectrophoresis • Capillary flow and electro-separation • Electro-osmosis • Electro-hydrodynamics • Micro-pumps



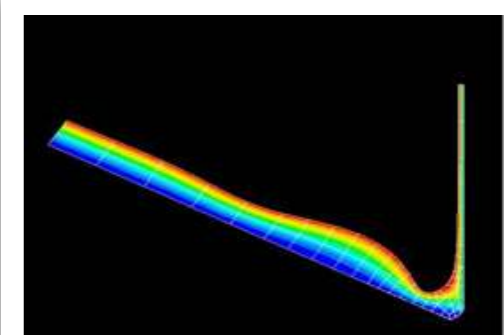
*Electrokinetics  
Multiplex focusing*



*Electro-osmotic driven flow  
Electrohydrodynamics for cooling*

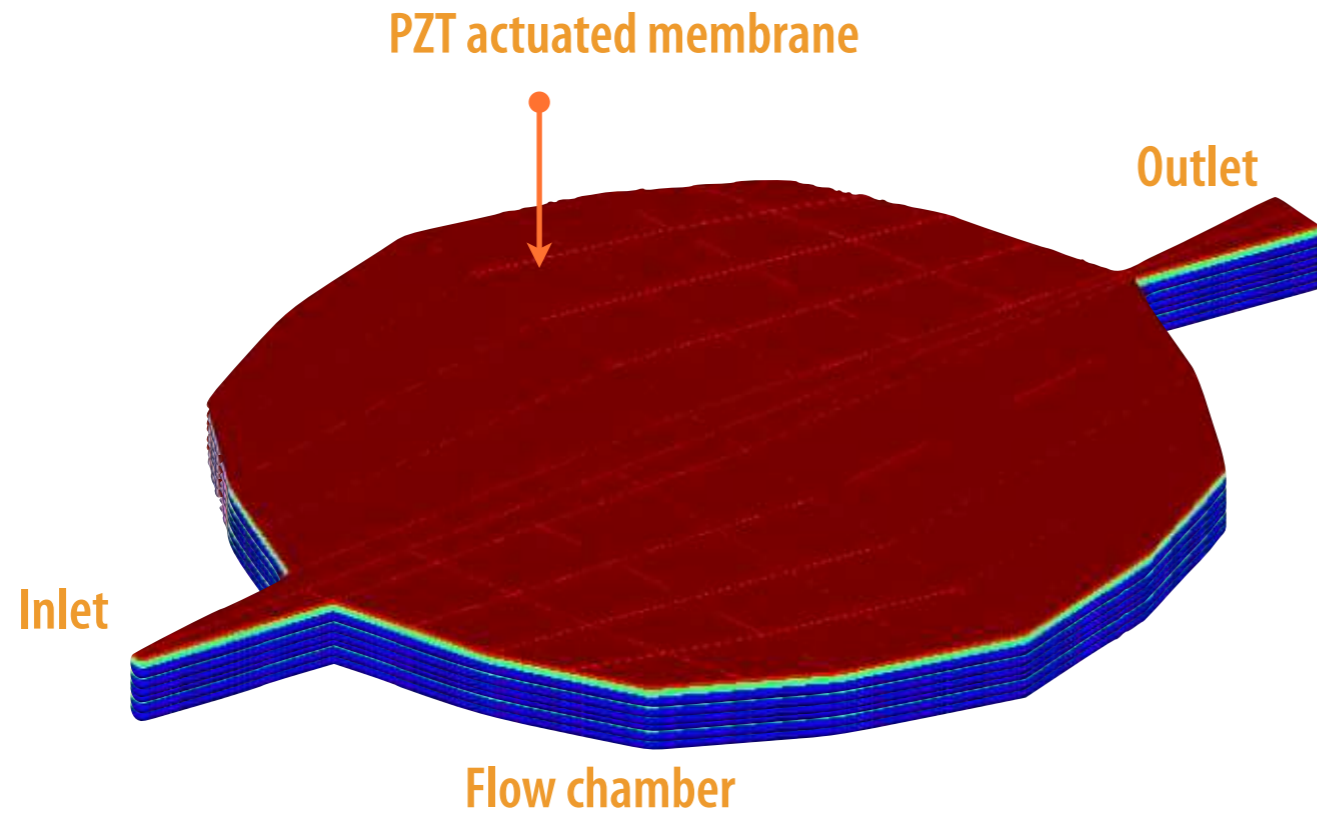


*Electrophoresis/Dielectrophoresis  
High Frequency Waste separation*

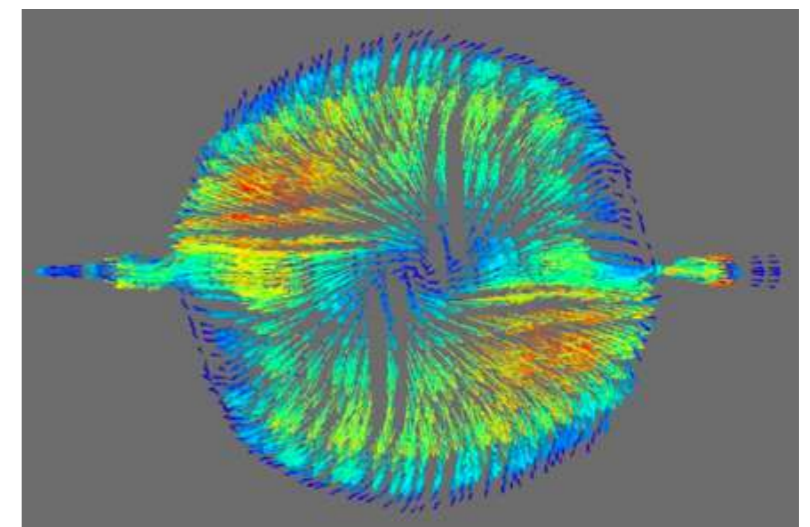
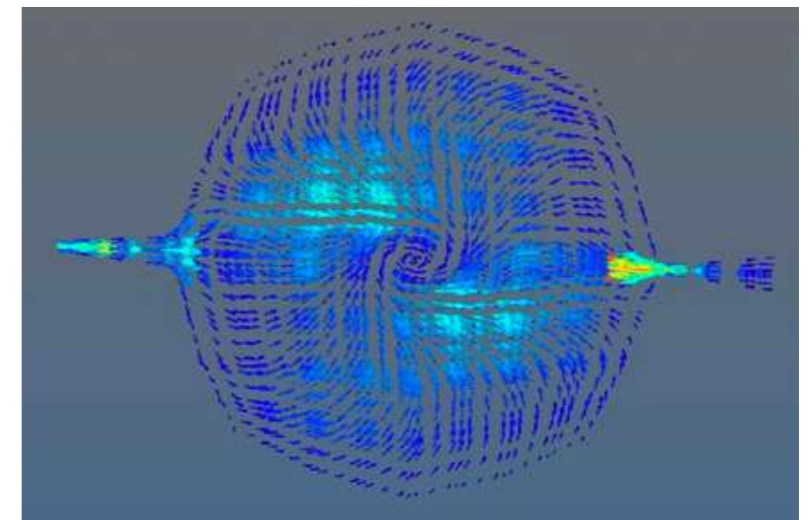
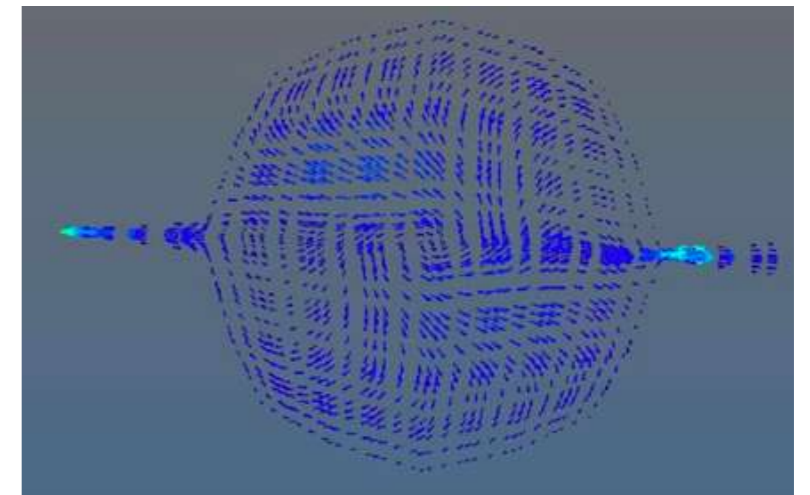


*Free surface flow  
Slide coater*

# Advanced FSI

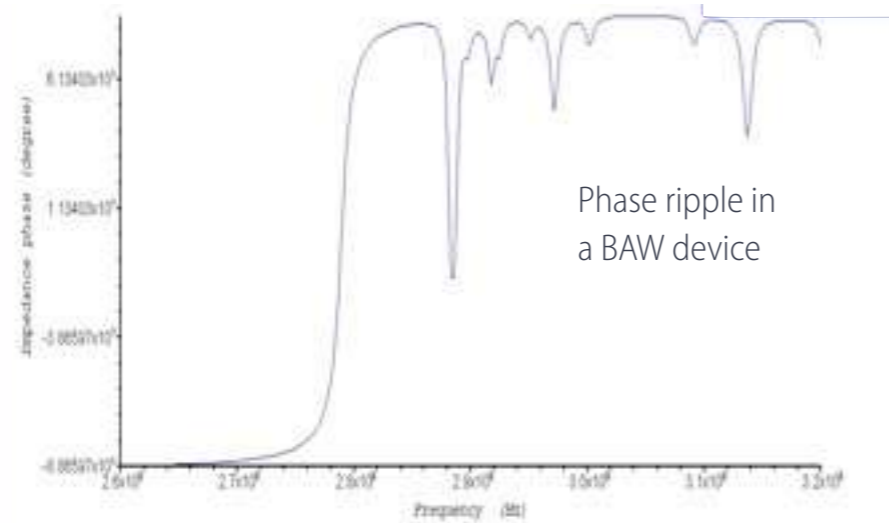
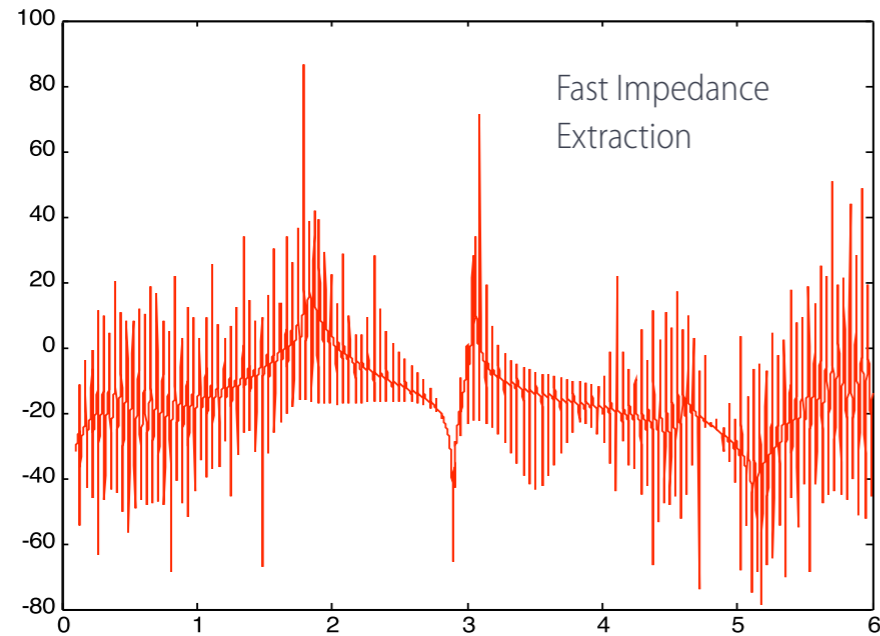


**Example:** Valveless piezoelectrically actuated micropump



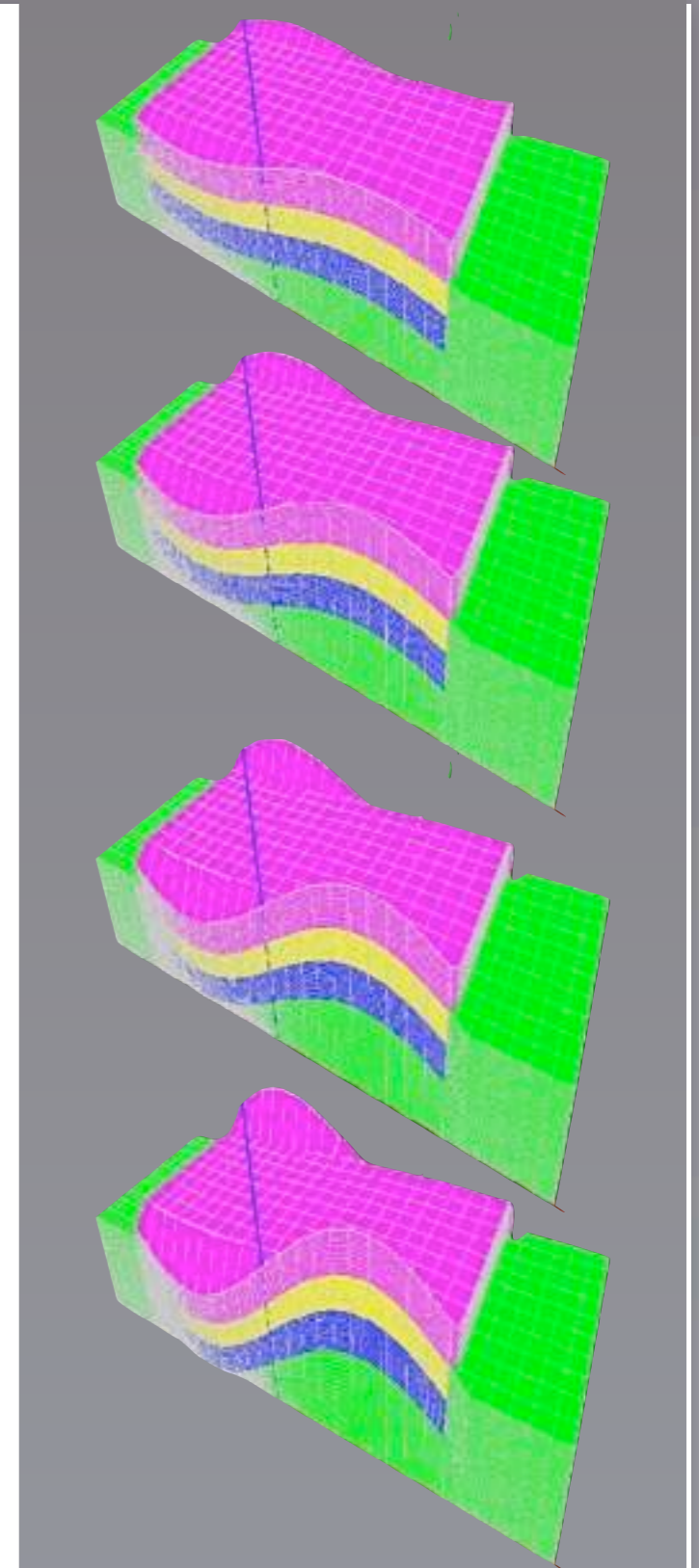
Flow evolution in a piezoelectric membrane micro pump

# Piezo-Acoustics



1

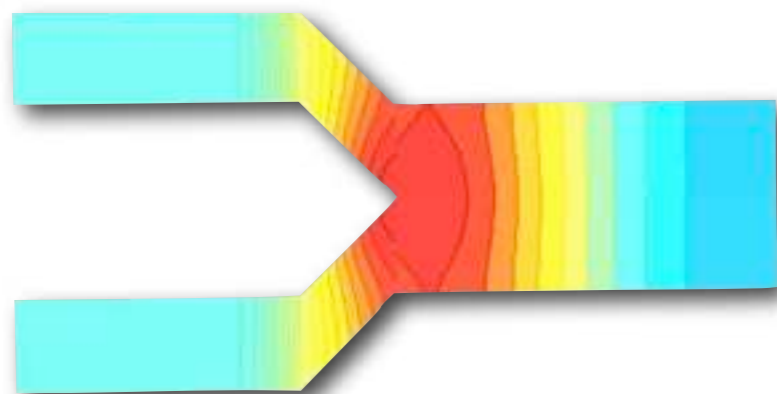
**Multi-processor enabled BAW/SAW simulation**  
Fast impedance and phase ripple calculations



2

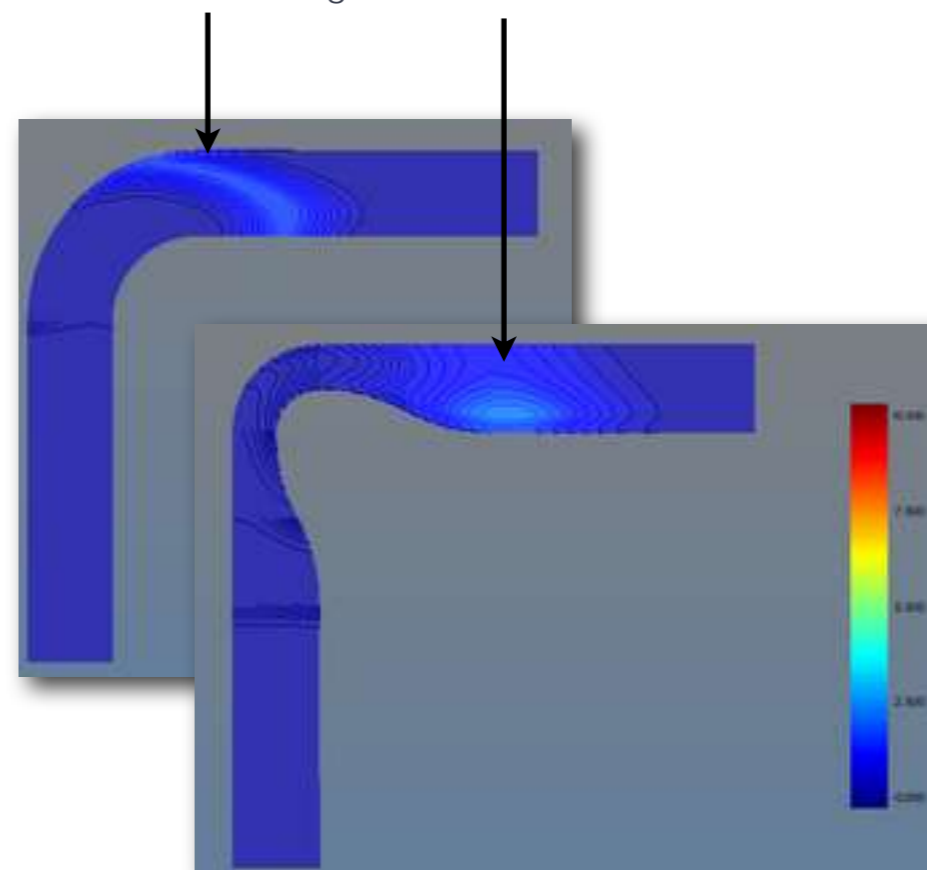
**Piezo-acoustic wave generation**

# Microfluidics



Two reactants meeting at the junction and reacting to form a new analyte. Support for multivalent reactions is new in v 8.5

Concentration skewing      Minimized concentration skewing



Enhanced ion drag calculations allows you to optimize elbow turns to minimize concentration skews

1

## Enhanced Chemical Reaction

Microfluidics with enhanced transport kinetics

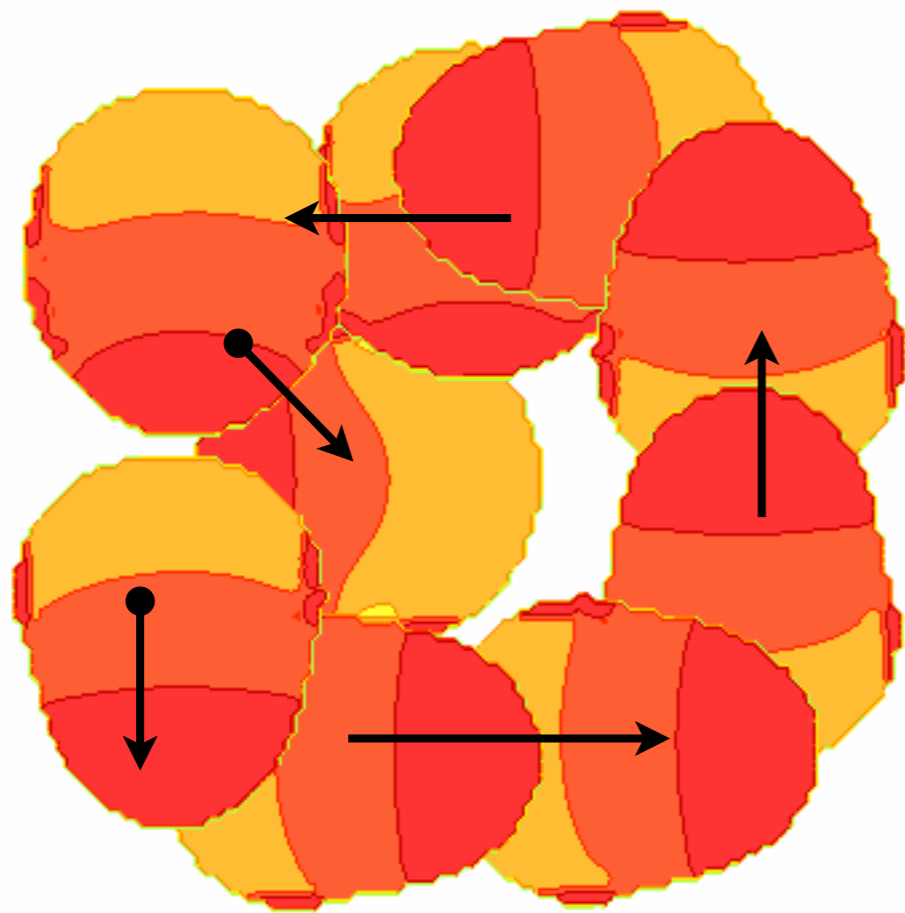
2

## Enhanced transport behavior

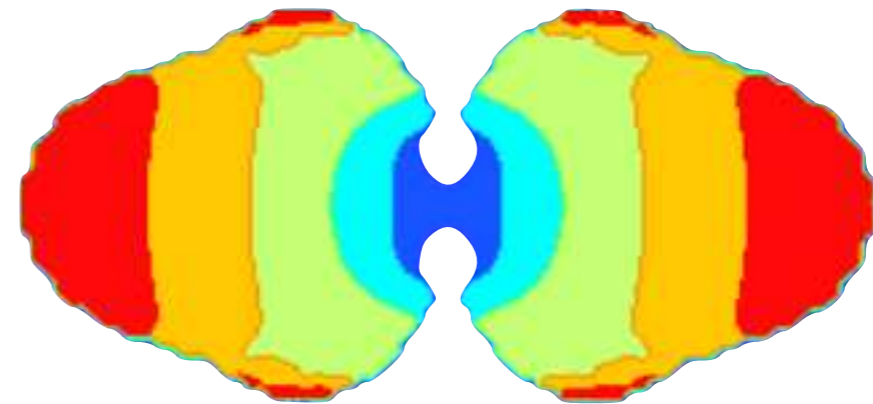
Multivalent Ion drag calculations in electrokinetic transport



# Microfluidics



Droplet moving around a pre-set track (top view)



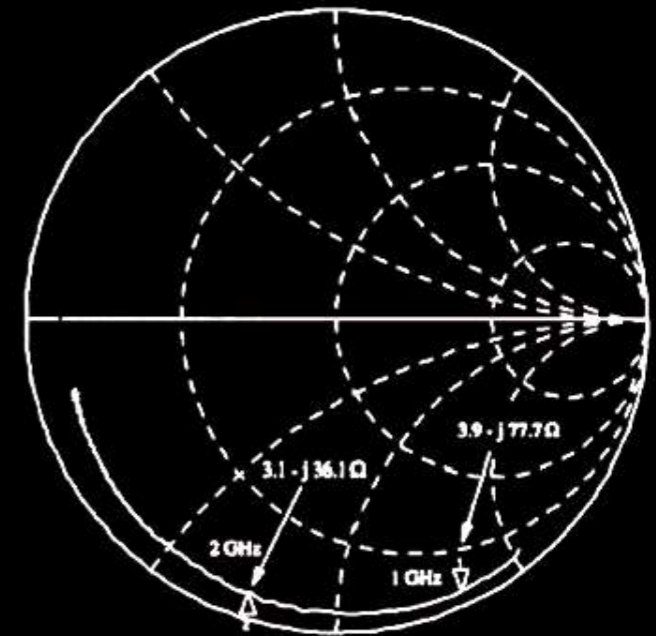
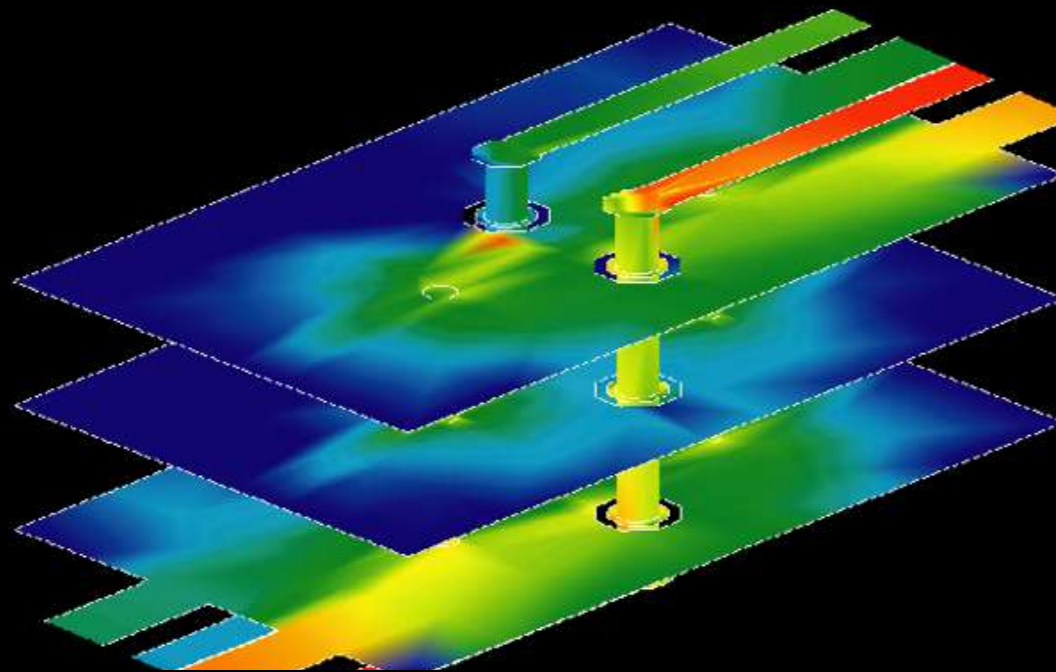
Droplet fission (top view)

3

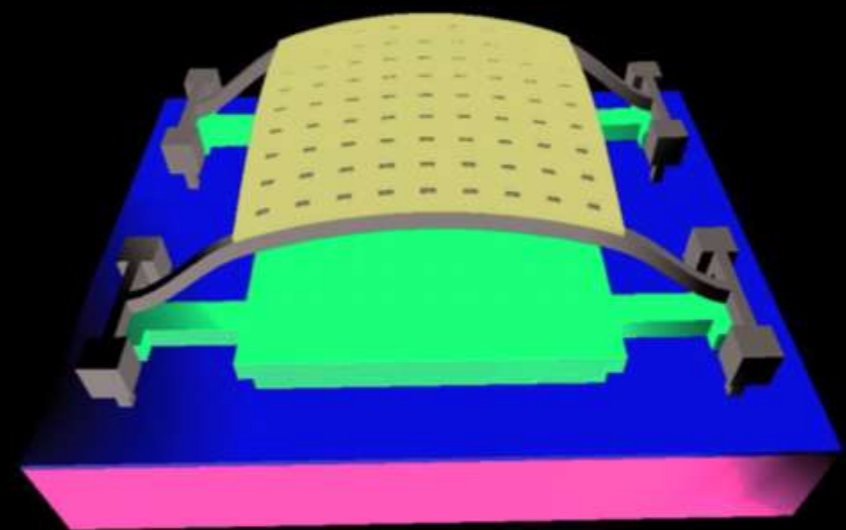
**Electrowetting on dielectric (EWOD)**

3D Electrowetting calculations

# ElectroMagnetics



*IntelliSuite is the only tool on the market that allows you to perform coupled Thermo-Electro-Mechanical & Full Wave ElectroMagnetic analyses— this is particularly useful in designing deformable RF-MEMS such as switches, tunable capacitors and varactors.*



# Extraction & verification



# What is extraction?

## Simplifying a full 3D model into behavioral model

Convert FEA/BEA model (large DOFs) into computationally efficient model

Develop pre-computed energy based model that captures multiphysics

## What is extracted ?

**Mechanical Strain Energy of Modes of Interest** (Including stress and stress gradient effects)

Capacitive energy

**Thermal effects** (deformation due to temperature change)

**Fluidic Structure Interaction** (due to compressive or non-compressive media)

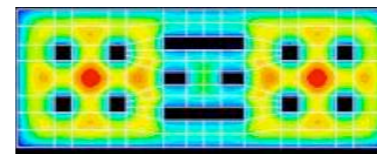
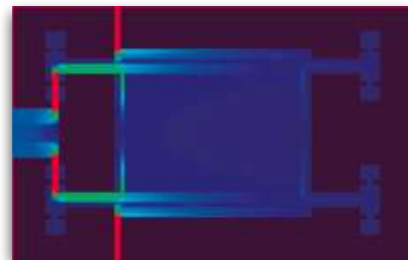
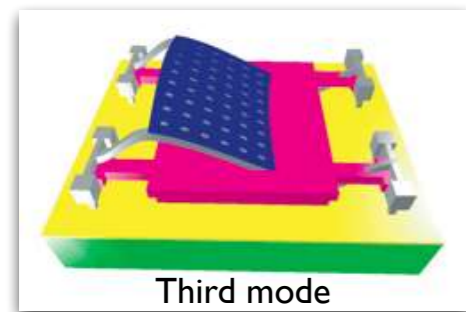
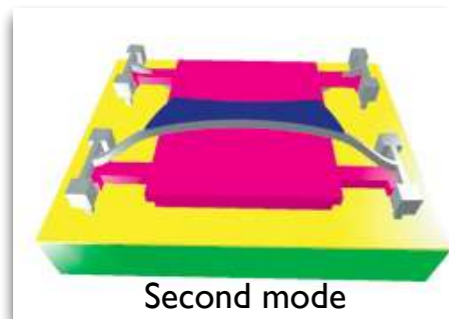
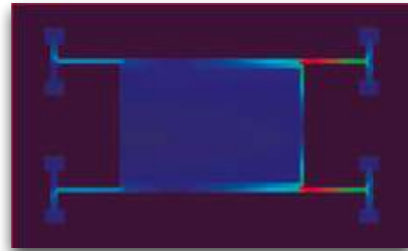
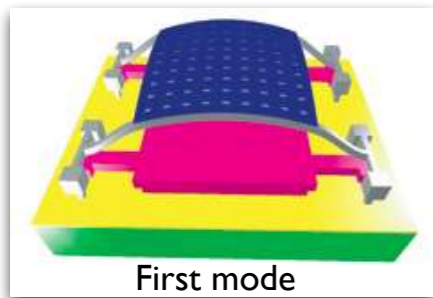
**Other dissipation sources** (thermoelastic damping (v8.6.1) and anchor acoustic losses (v8.6.2))

# System Model Extraction (SME)

Capture strain energy associated with each mode

Capture electrostatic energy associated with each mode

Capture fluid damping characteristics



Arnoldi/Krylov sub-space reduction



N-DOF behavioral model based on Lagrangian formulation

$$\frac{d}{dt} \left( \frac{\partial L}{\partial \dot{q}_j} \right) - \frac{\partial L}{\partial q_j} = 0$$



Compact Representation

**HDL**

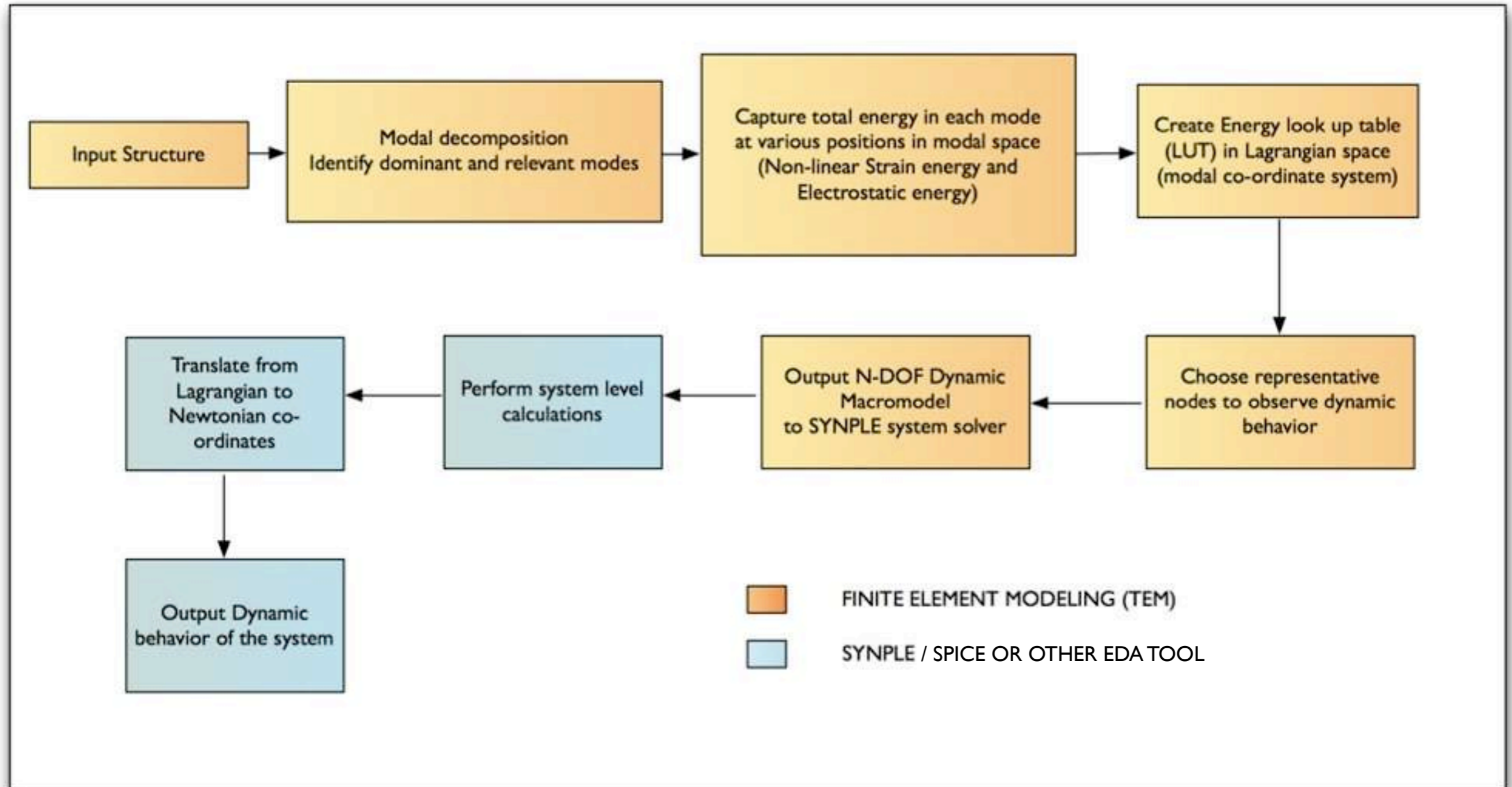
Hardware Description

❶ Capture total energy of relevant mode (Mechanical, Electrostatic, Dissipation)

❷ Krylov/Arnoldi methods to generate Lagrangian formulation

❸ Create Compact model for system modeling

# System model extraction (SME) flow chart



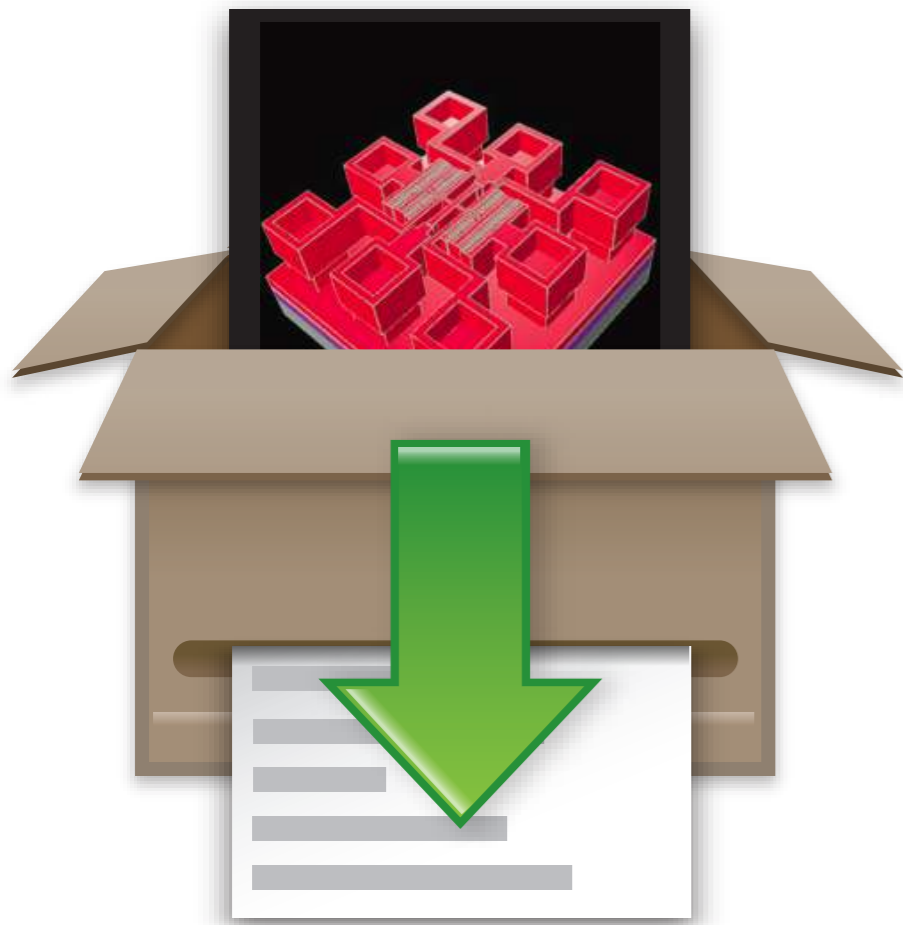
Summary: Convert problem from Newtonian (inertia based) to more efficient Lagrangian domain (energy based)

# SME advantages

- Automated full multi-physics capture
- 1000 X faster than pure FEA
- Matches FEA to within 1% accuracy
- Fully capture harmonic responses
- 3D MEMS system simulation
- Device and package level extraction
- Automated VHDL/ Verilog/ SPICE generation



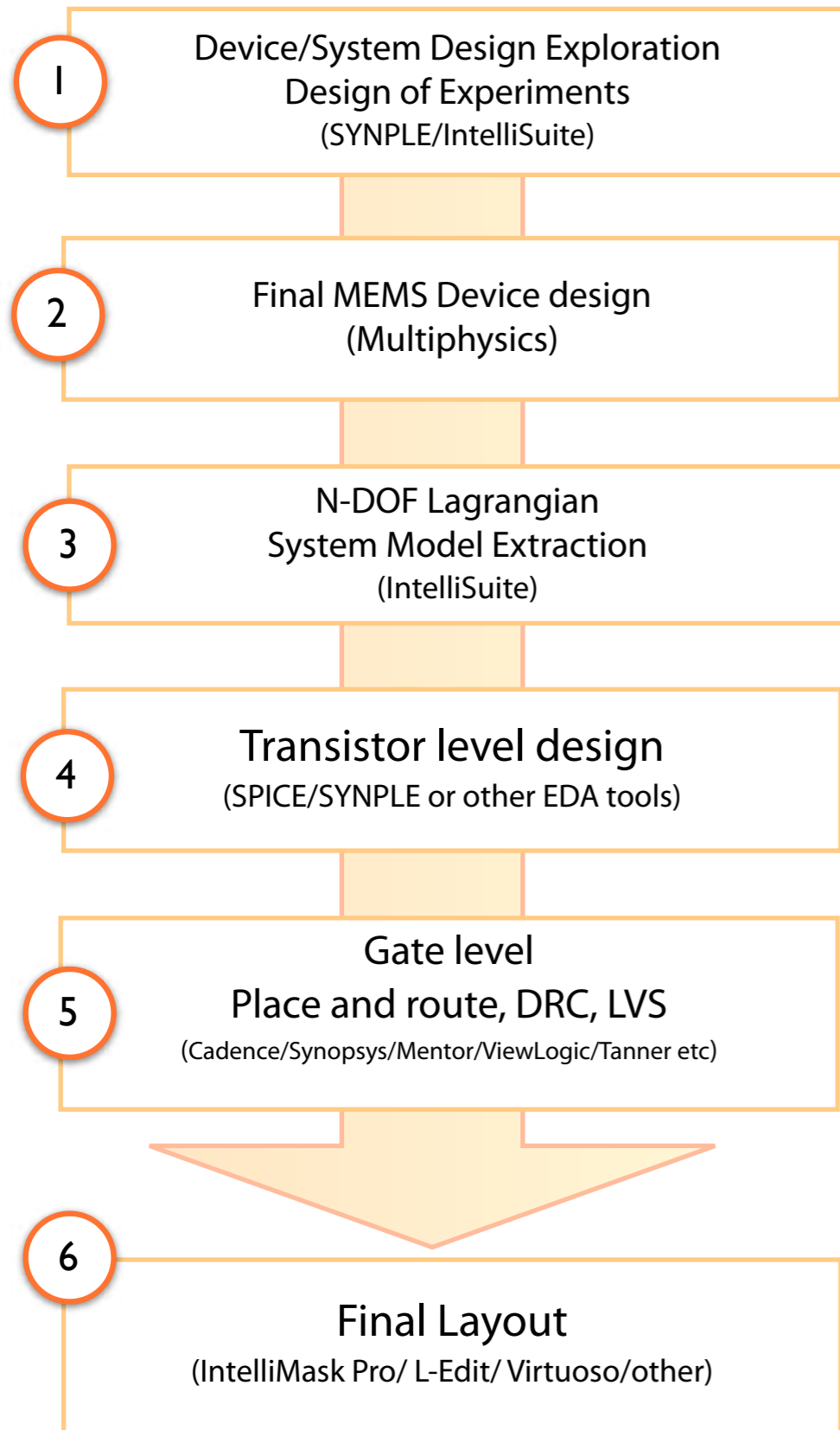
# EDA Linker capabilities (compatibility)



- Create accurate N-DOF dynamic system model from MEMS FEA/BEA model
- Output system model into SPICE, HDL, and Simulink formats
- Compatible with EDA tools from Cadence, Mathworks, Mentor, Synopsys and Tanner
- Integrated CMOS-MEMS (SoC/SiP) compatibility



# Integrated design flow for MEMS + IC



**MEMS-CMOS integration  
design flow can be based on :**

- ✓ VHDL-AMS
- ✓ Verilog-A
- ✓ SPICE netlist
- ✓ Matlab/Simulink .MEX

# What is verification?

## **Model verification (Schematic vs 3D)**

Verify schematic model and 3D model match

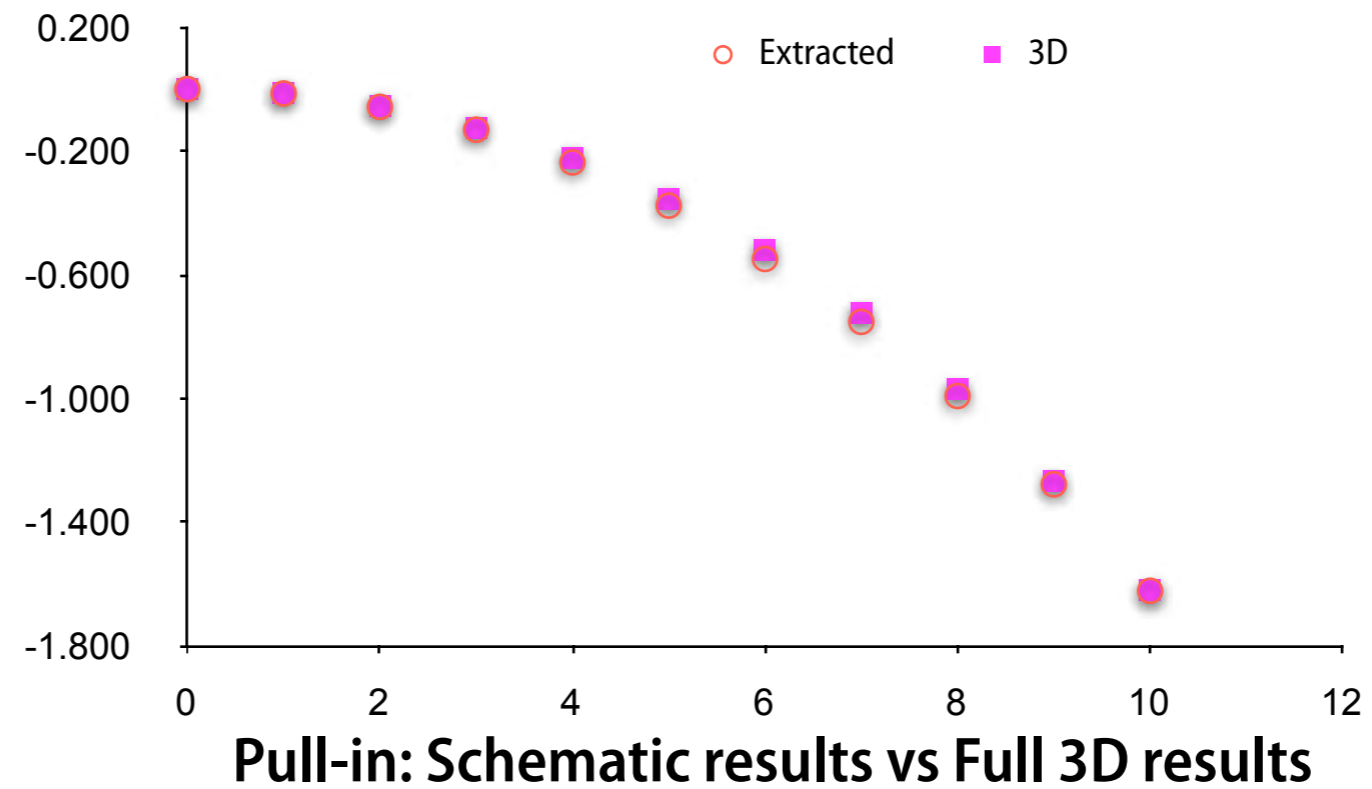
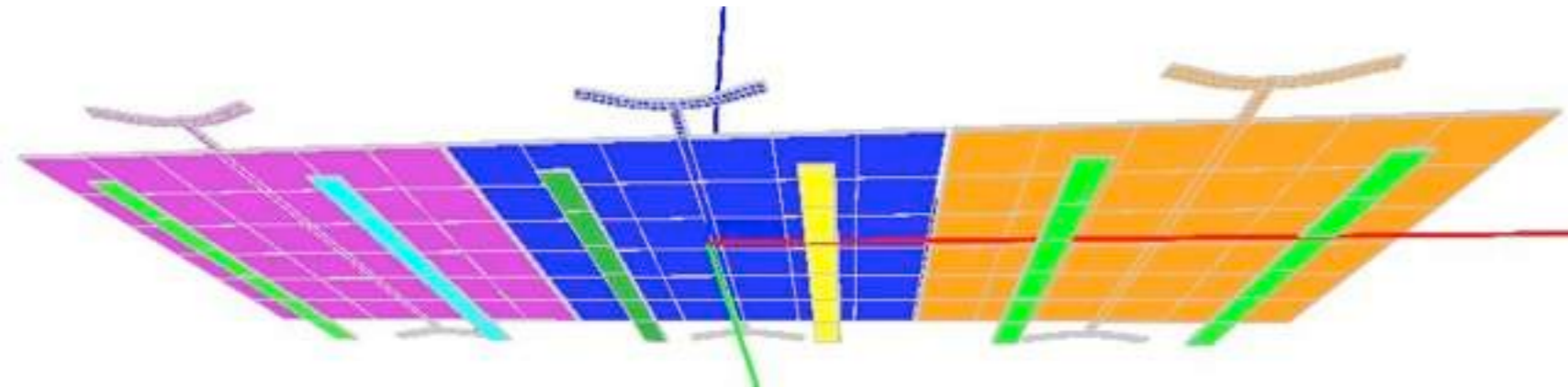
Ensure MEMS model used in circuit development is accurate

## **Physical verification ('Tape Out')**

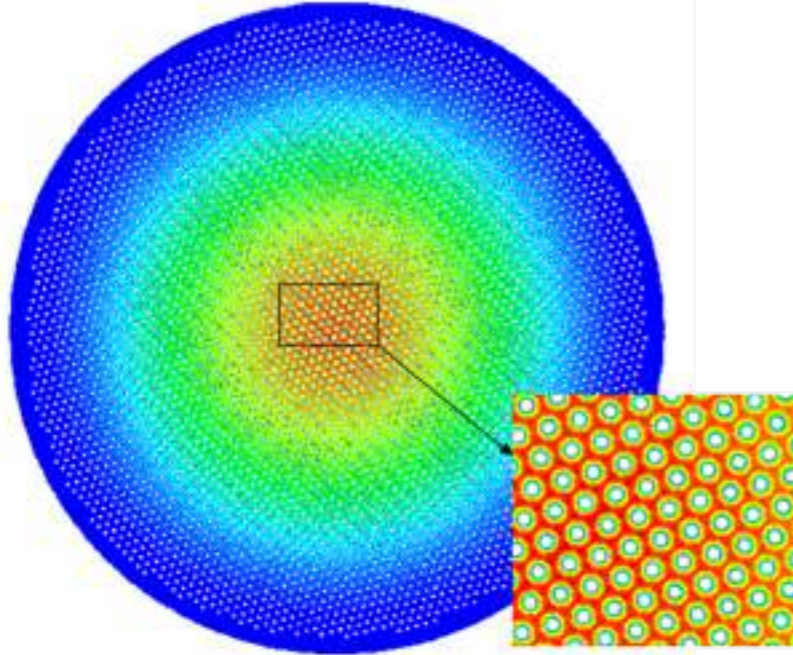
Verify physical layout is consistent with Design Rules

Ensure design meets manufacturability criteria

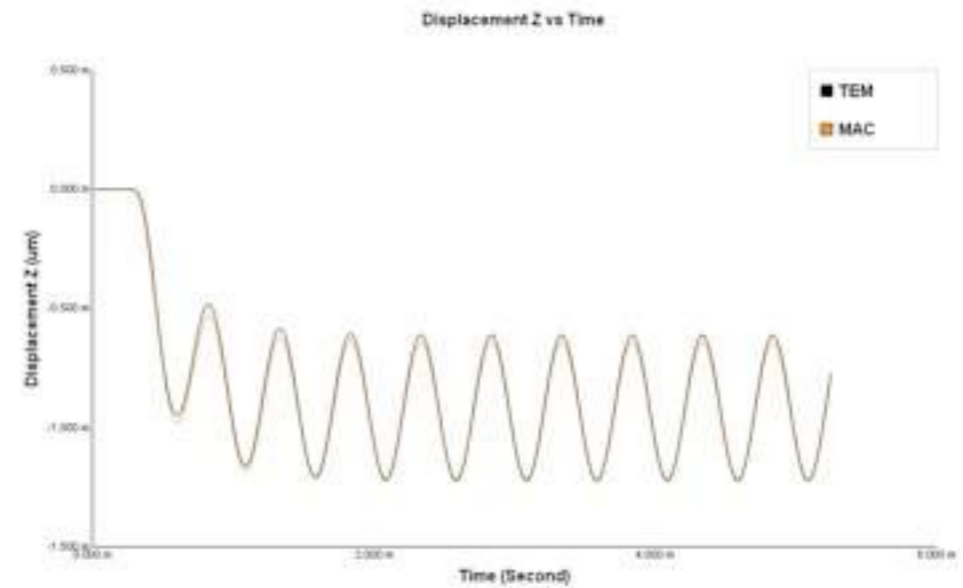
# Static model verification



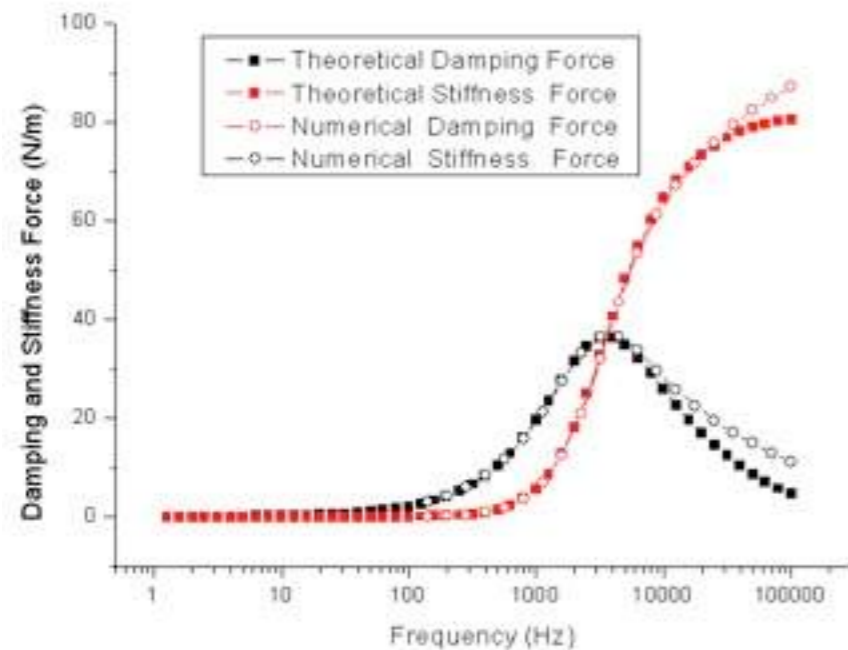
# Damping model verification



Perforated condenser membrane

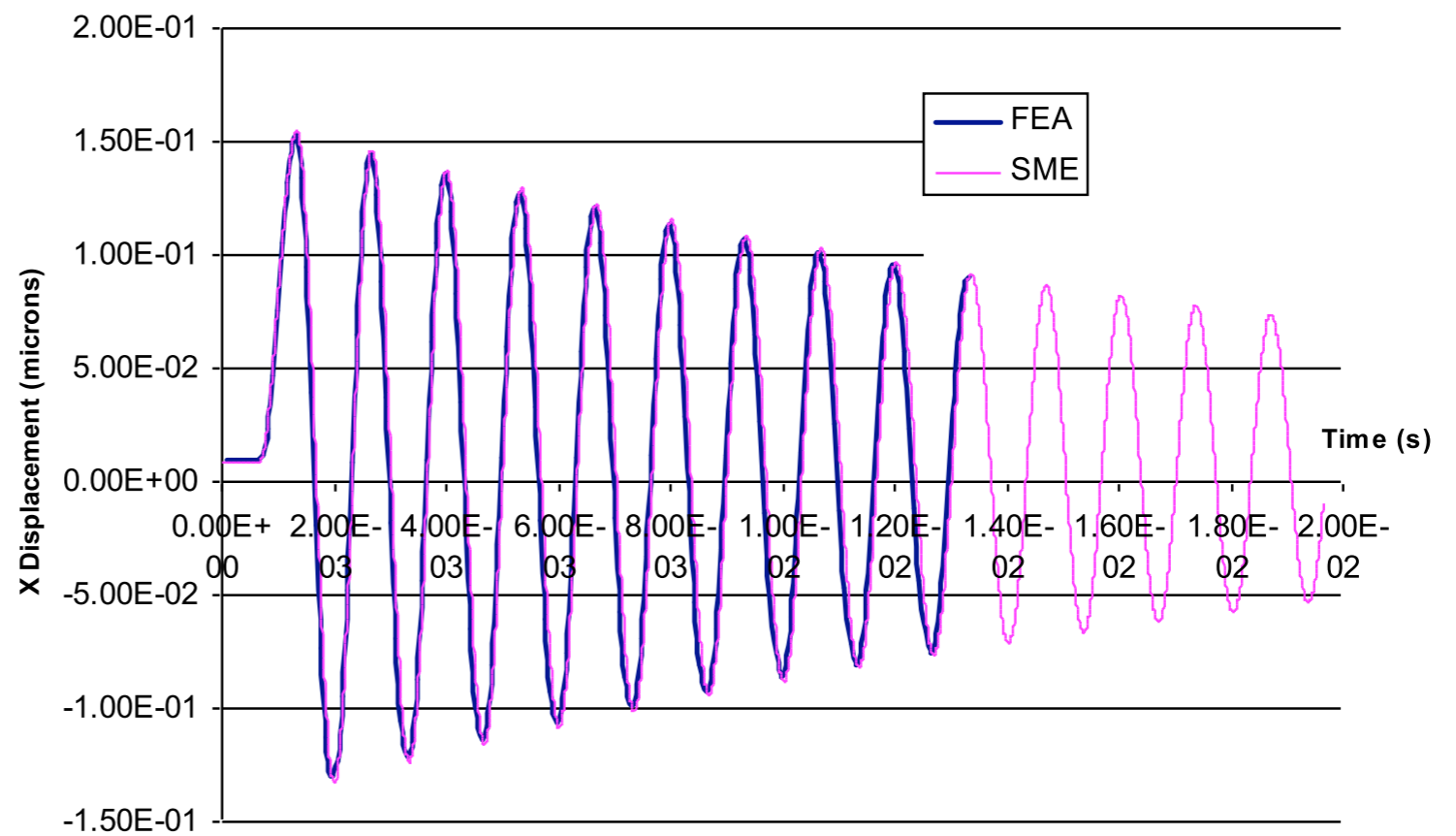
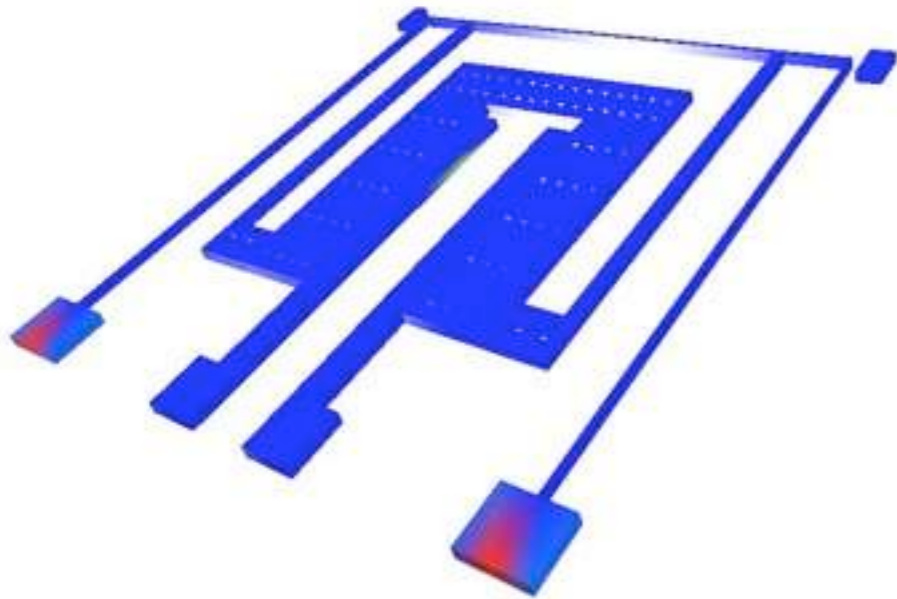


Full 3D (TEM) vs Macromodel comparison



Full capture of fluidic damping and spring force

# Dynamic model verification



Transient response of device: Schematic vs FEA (3D)

# Summary

- End to end design tools for MEMS
- Simulate MEMS at any level:  
*Ab-initio, Component, Device, Algorithm and System*
- Flexible design flow to achieve accurate and fast results
- Used by major customers in 30+ countries



Thank you

ありがとう・謝謝・धन्यवाद・شكرالكم

Grazie • Merci • Gracias • Danke • Obrigado • Dank U • Terima Kasih

Dziękuję • Спасибо • Ευχαριστώ • Asante Sana • Dankie



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